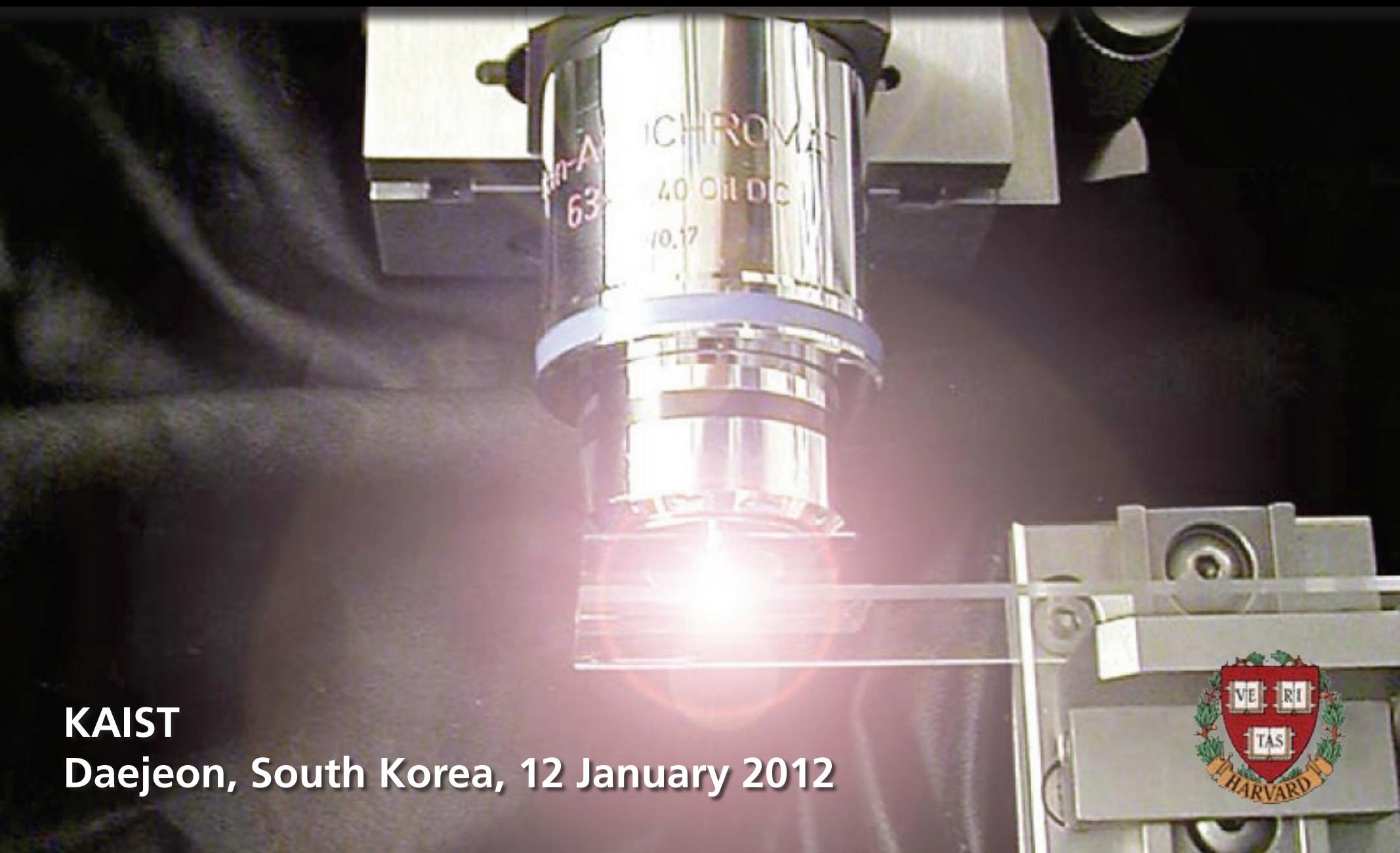


Femtosecond Laser Micromachining



KAIST
Daejeon, South Korea, 12 January 2012

한국어를 하지 않아 미안합니다.

(공부 중입니다.)



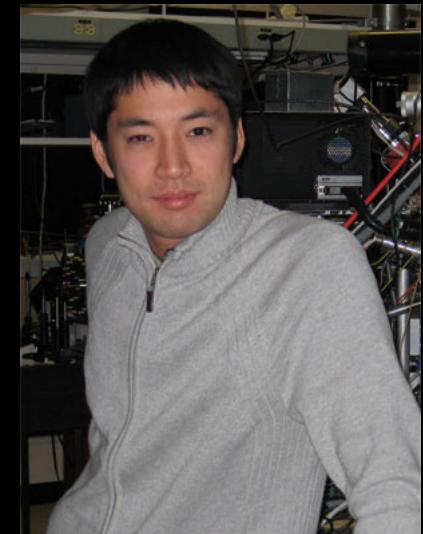
Rafael Gattass



Loren Cerami



Tina Shih



Masanao Kamata

and also....

Iva Maxwell

Sam Chung

Eli Glezer

Chris Schaffer

Nozomi Nishimura

Jonathan Ashcom

Jeremy Hwang

Nan Shen

Dr. André Brodeur

Dr. Sanjoy Kumar

Dr. Limin Tong

Dr. Prissana Thamboon

Prof. Igor Khruschev (Aston University)

Prof. Denise Krol (UC Davis)

Dr. Yossi Chay (Sagitta, Inc.)

Dr. S.K. Sundaram (PNNL)

Prof. Minoru Obara (Keio University)

Prof. Don Ingber (Harvard Medical School)

Prof. Aravi Samuel (Harvard)

My message

fs micromachining: great technique for manipulating matter

Introduction



Introduction

216 J. Opt. Soc. Am. B/Vol. 13, No. 1/January 1996

D. von der Linde and H. Schüler

Breakdown threshold and plasma formation in femtosecond laser-solid interaction

D. von der Linde and H. Schüler

Institut für Laser- und Plasmaphysik, Universität Essen, D-45117 Essen, Germany

Received March 6, 1995; revised manuscript received June 15, 1995

Combining femtosecond pump-probe techniques with optical microscopy, we have studied laser-induced optical breakdown in optically transparent solids with high temporal and spatial resolution. The threshold of plasma formation has been determined from measurements of the changes of the optical reflectivity associated with the developing plasma. It is shown that plasma generation occurs at the surface. We have observed a remarkable resistance to optical breakdown and material damage in the interaction of femtosecond laser pulses with bulk optical materials. © 1996 Optical Society of America

1. INTRODUCTION

The interaction of intense femtosecond laser pulses with solids offers the possibility of producing a new class of plasmas having approximately solid-state density and spatial density scale lengths much smaller than the wavelength of light. These high-density plasmas with extremely sharp density gradients are currently of great interest, particularly from the point of view of generating bright, ultrashort x-ray pulses. To produce such a plasma, the laser pulse should rise from the intensity level corresponding to the threshold of plasma formation to the peak value in a time much shorter than the time scale of plasma expansion. Thus the specification of the tolerance of plasma background or of the acceptable amount of the target material.

or pulse requires some knowledge of the physical properties of the target material.

One of the key points in the research of Bloembergen and his co-workers was the use of very tightly focused laser beams, which allowed them to reach the breakdown threshold of the materials while staying well below the critical power of self-focusing. Self-focusing is one of the major problems in the measurement of bulk breakdown thresholds. In a more recent review Soileau *et al.*⁵ carefully examined the role of self-focusing in experiments measuring laser-induced breakdown in experiments and materials. They concluded that the breakdown and damage thresholds are also strongly influenced by extrinsic effects.

Thus far, the issue of breakdown thresholds in femtosecond laser-solid interaction has barely been touched. Very recently, Du *et al.*⁶ carried out laser-induced breakdown experiments on fused silica with pulses ranging in duration from 7 ns to as low as 150 fs. They reported an interesting dependence of the fluence threshold on pulse duration, particularly a pronounced increase of the threshold with decreasing pulse duration below of the 10 ps. Observations were interpreted in terms of the bulk threshold model. In related research, Stuart

with dependence of the threshold of materials and weak varia-

Introduction

216

J. Opt. Soc. Am. B/Vol. 13, No. 1/January 1996
Breakdown threshold and plasma formation
in femtosecond laser-solid interaction

D. von der Linde and H. Schüler

[and] ... no bulk damage could be produced

with femtosecond laser pulses”

1. INTRODUCTION

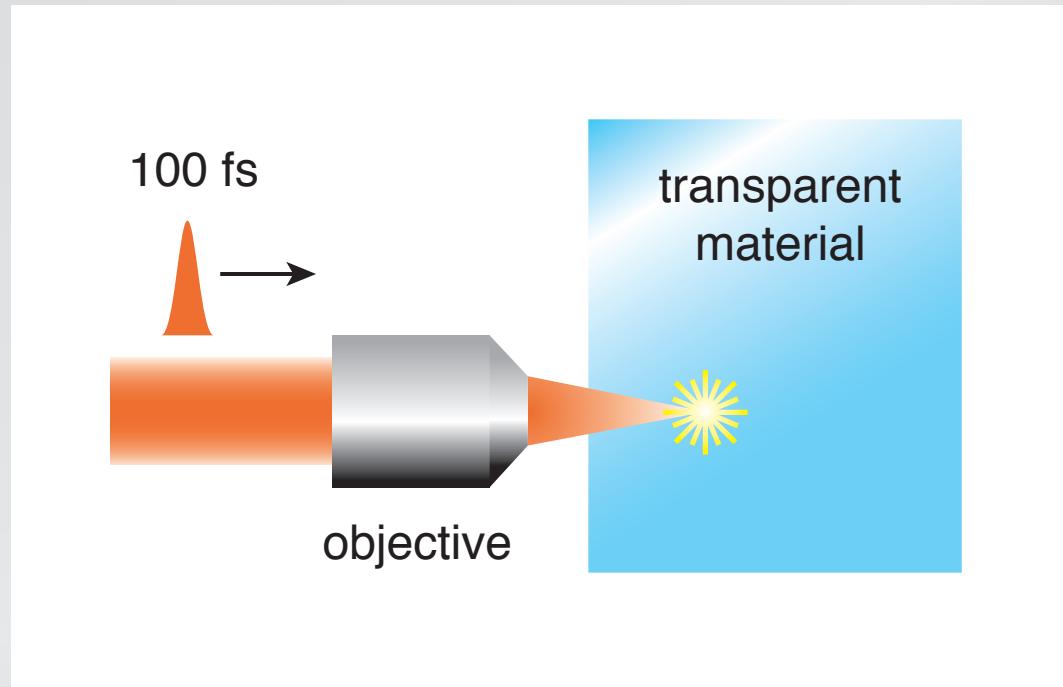
The interaction of intense femtosecond laser pulses with solids offers the possibility of producing a new class of plasmas having approximately solid-state density and spatial density scale lengths much smaller than the wavelength of light. These high-density plasmas with extremely sharp density gradients are currently of great interest, particularly from the point of view of generating short x-ray pulses. To produce such a plasma, the laser pulse must rise from the intensity level corresponding to the threshold of plasma formation to the peak value in a time much shorter than the time scale of plasma expansion. Thus the specification of the intensity background or of the acceptable amount of energy delivered into a dense target is a physics

One of the key points in the research of Bloembergen and his co-workers was the use of very tightly focused laser beams, which allowed them to reach the breakdown threshold of the materials while staying well below the critical power of self-focusing. Self-focusing is one of the major problems in the measurement of bulk breakdown thresholds. In a more recent review Soileau *et al.*⁵ carefully examined the role of self-focusing in experiments measuring laser-induced breakdown of bulk dielectric materials. They concluded that the breakdown and damage thresholds are also strongly influenced by extrinsic effects.

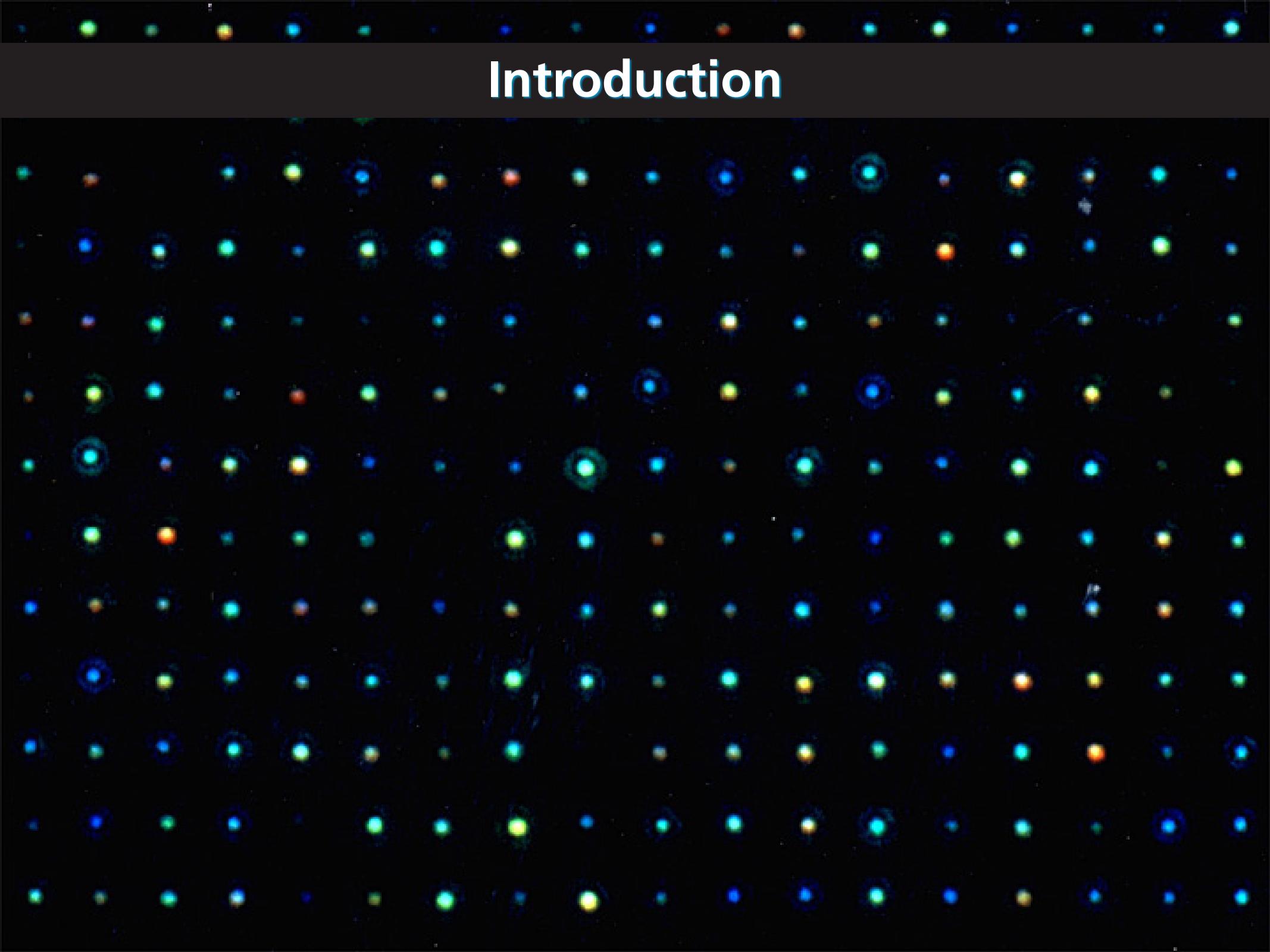
Thus far, the issue of breakdown thresholds in femtosecond laser-solid interaction has barely been touched. Very recently, Du *et al.*⁶ carried out laser-induced breakdown experiments on fused silica with pulses ranging in duration from 7 ns to as low as 150 fs. They reported an interesting dependence of the fluence threshold on pulse duration, particularly a pronounced increase of the threshold with decreasing pulse duration below 10 ps. Observations were interpreted in terms of the bulk ionization model. In related research, Stuart

Introduction

focus laser beam inside material



Introduction

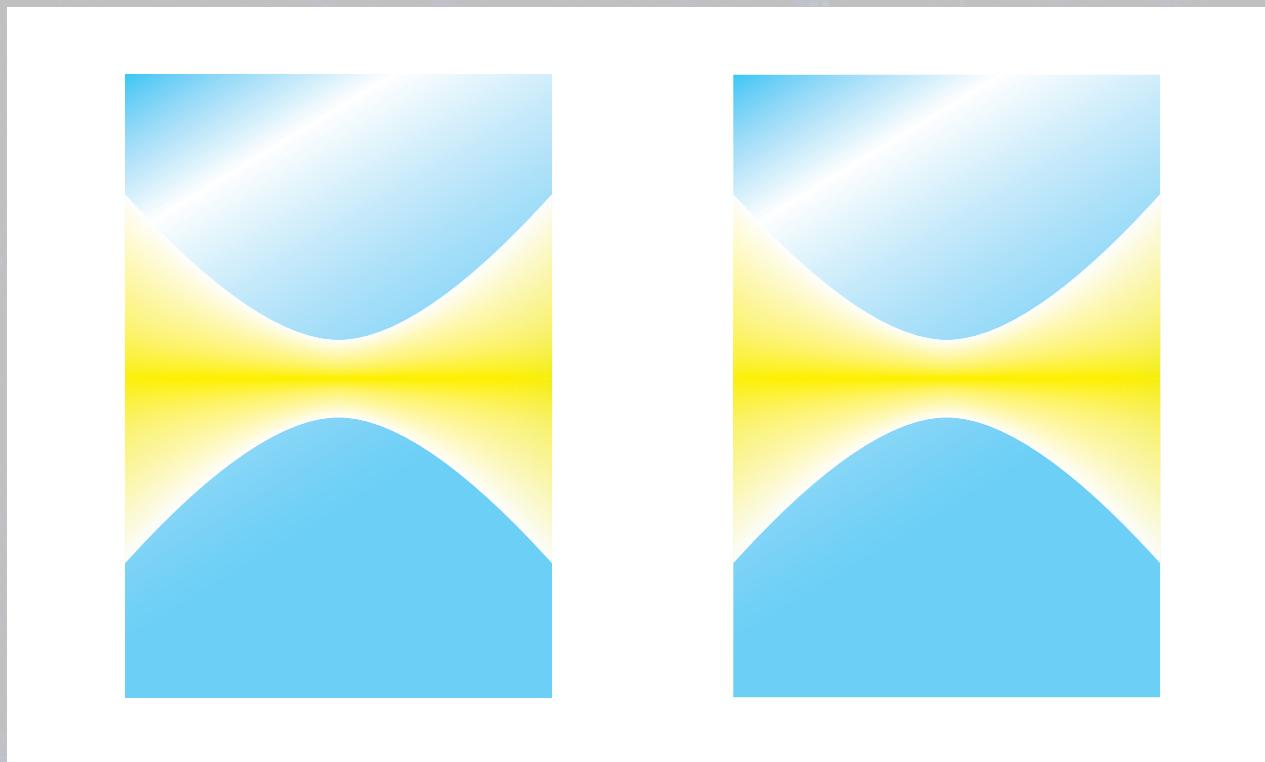


Introduction

photon energy < bandgap → nonlinear interaction

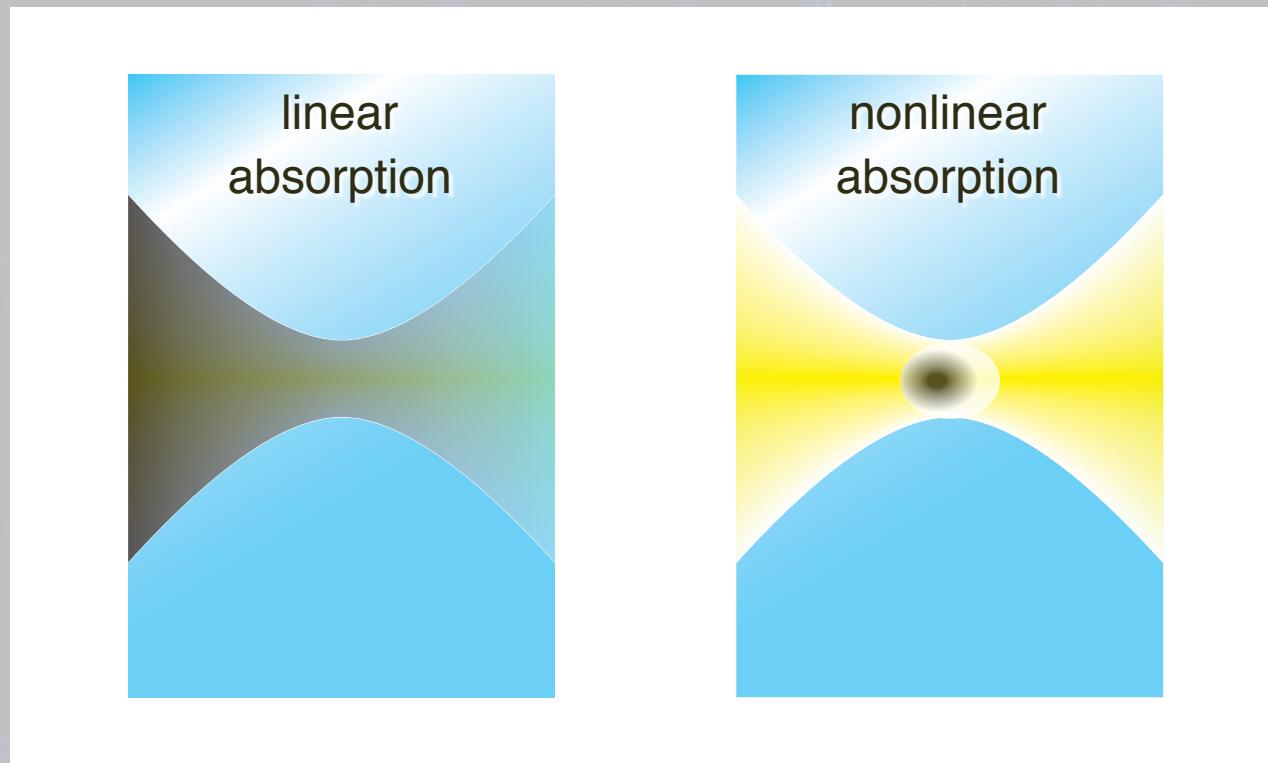
Introduction

nonlinear interaction provides bulk confinement



Introduction

nonlinear interaction provides bulk confinement

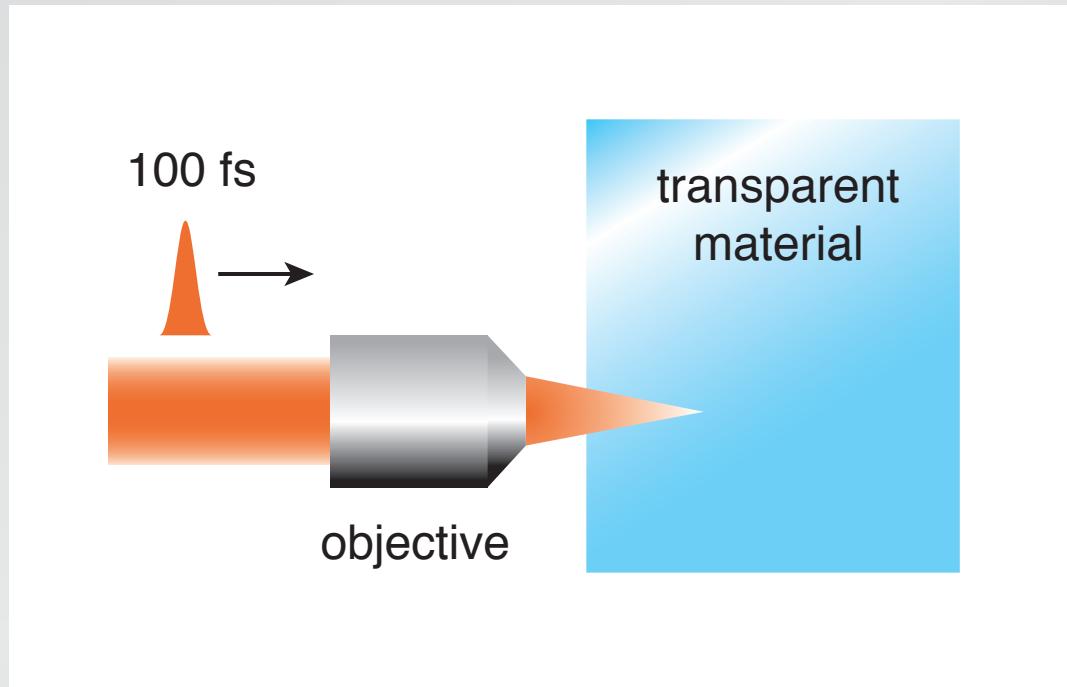


Outline

- femtosecond micromachining
- low-energy machining
- applications

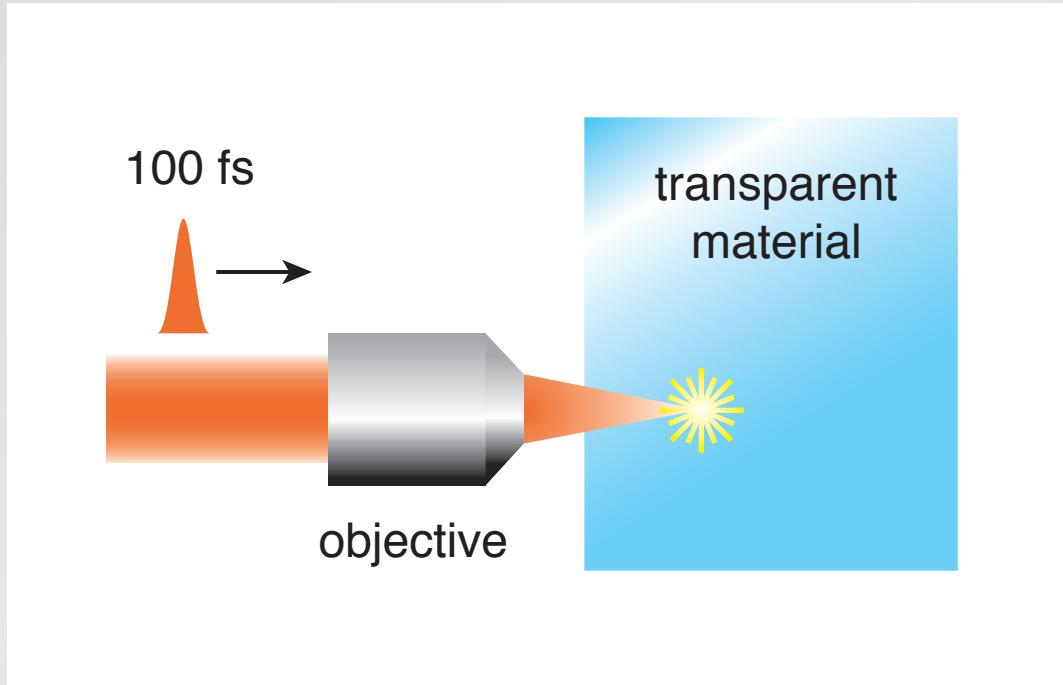
Femtosecond micromachining

high intensity at focus...



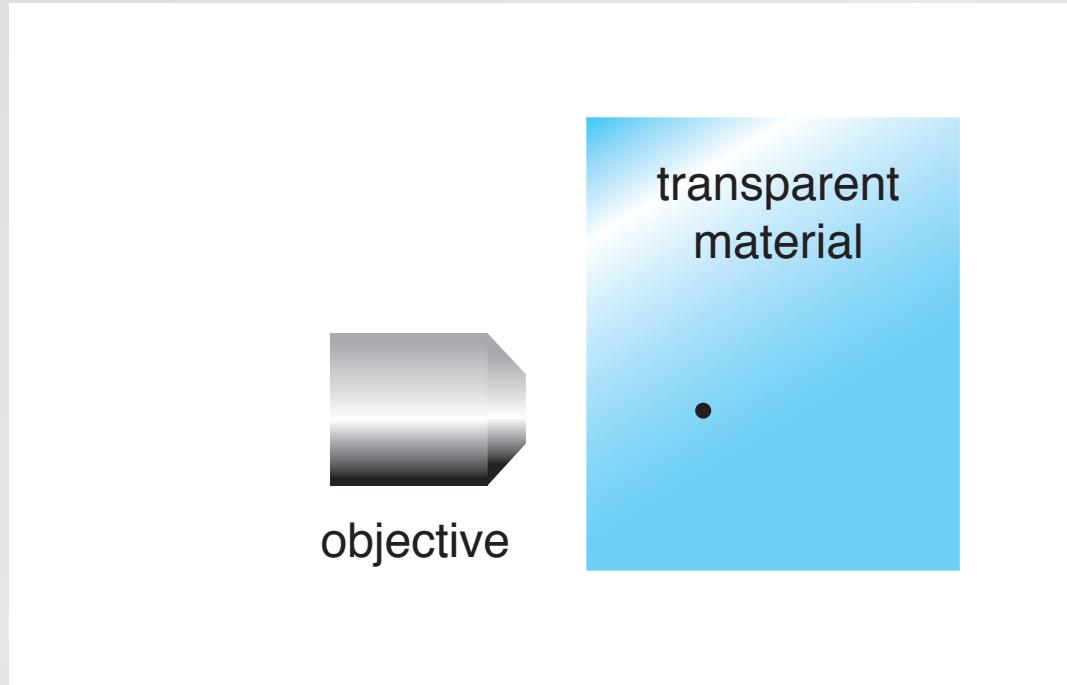
Femtosecond micromachining

...causes nonlinear ionization...



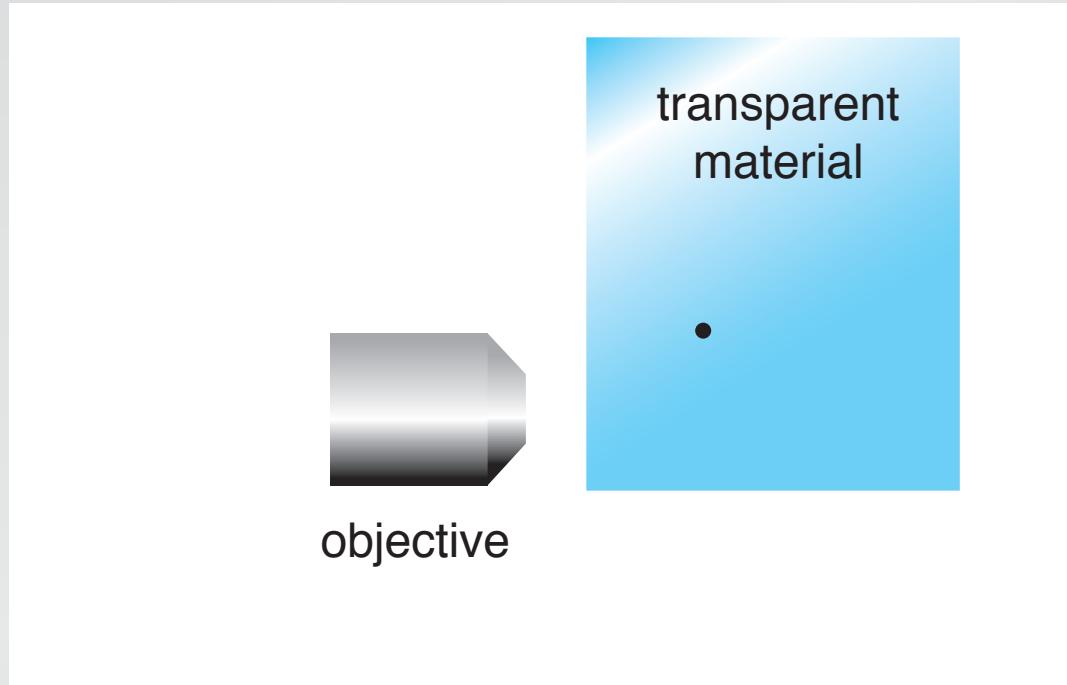
Femtosecond micromachining

and 'microexplosion' causes microscopic damage...



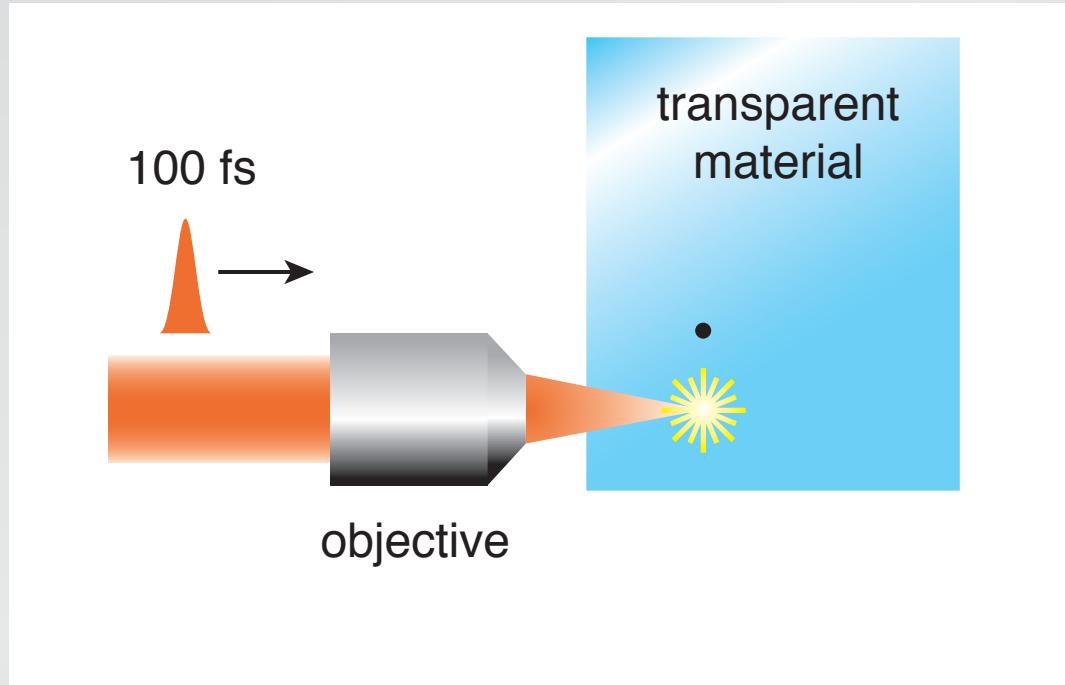
Femtosecond micromachining

translate sample



Femtosecond micromachining

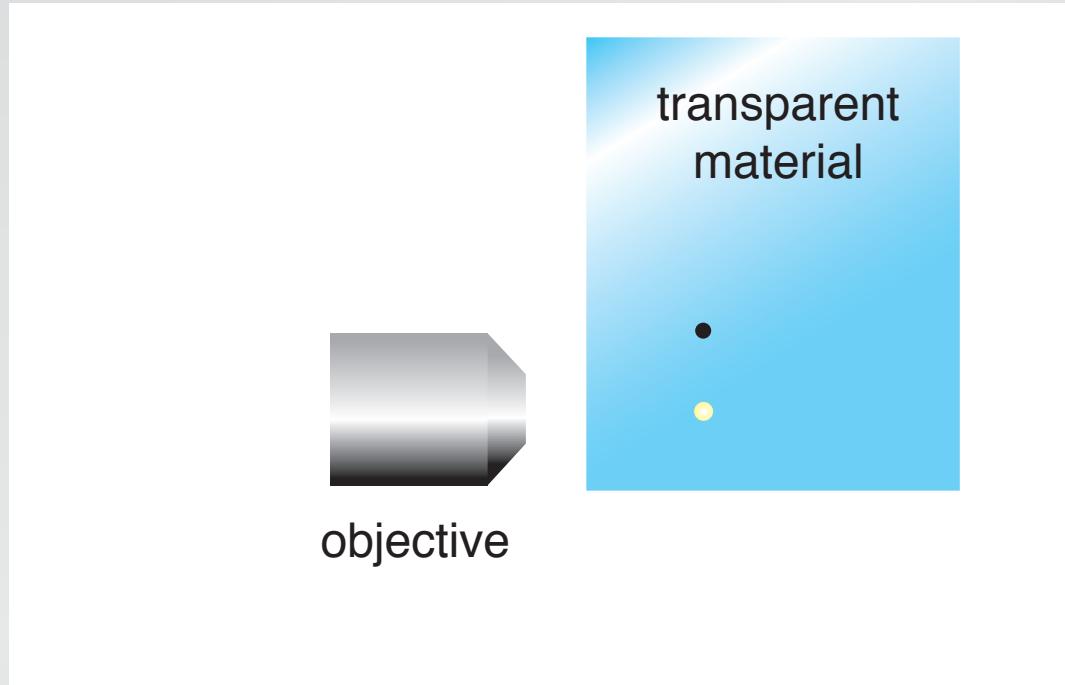
time scales



100 fs: laser energy transferred to electrons

Femtosecond micromachining

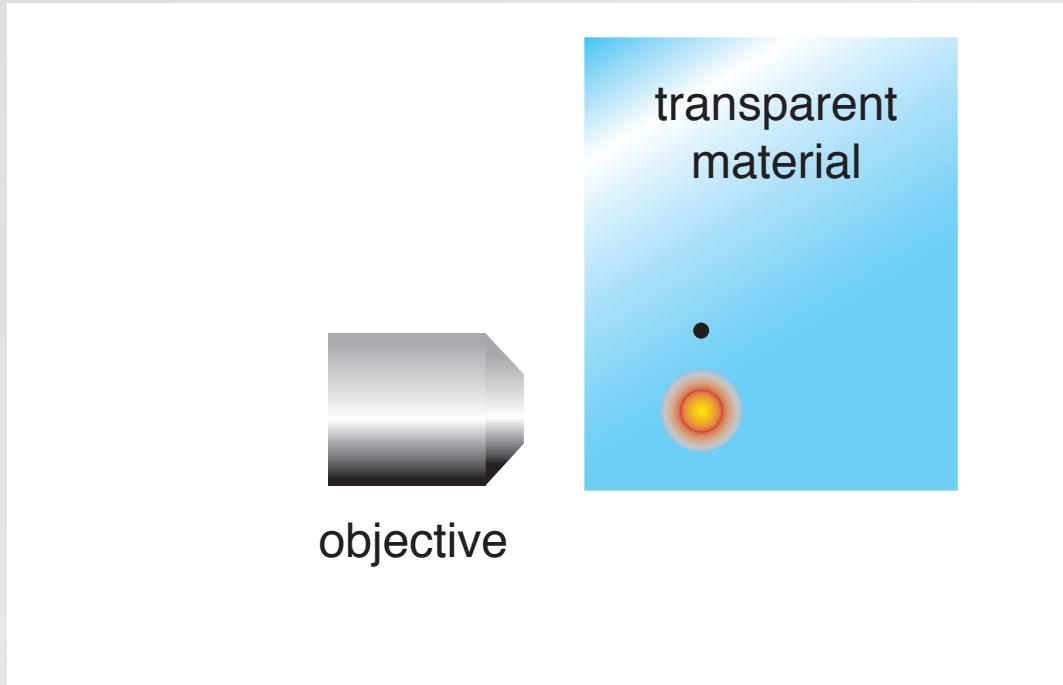
time scales



10 ps: energy transfer to ions

Femtosecond micromachining

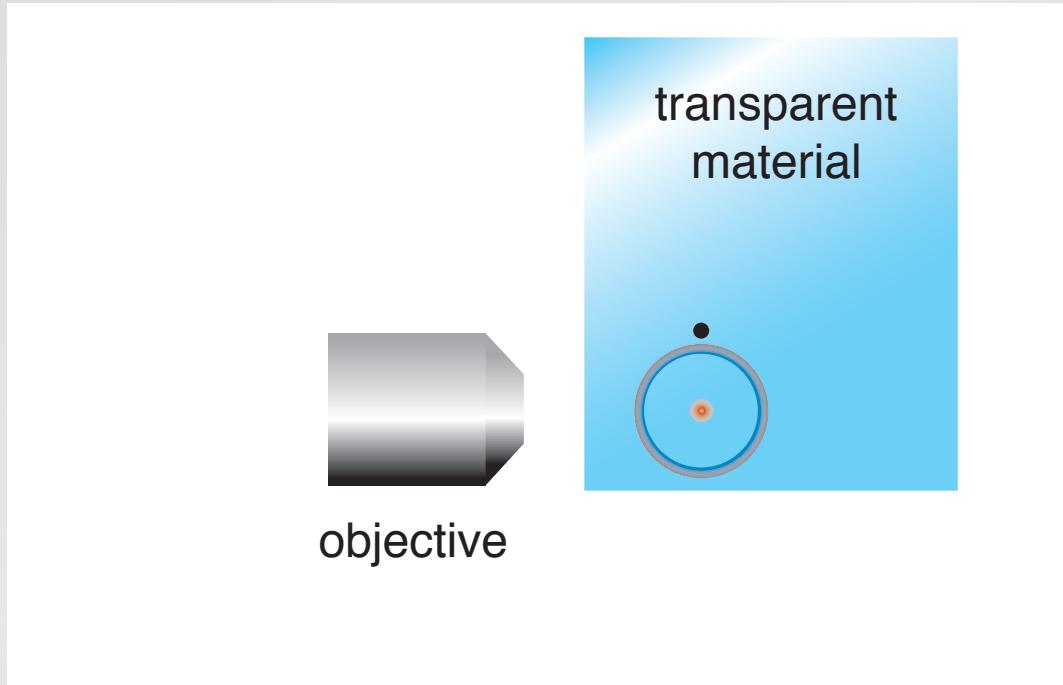
time scales



100 ps: plasma expansion

Femtosecond micromachining

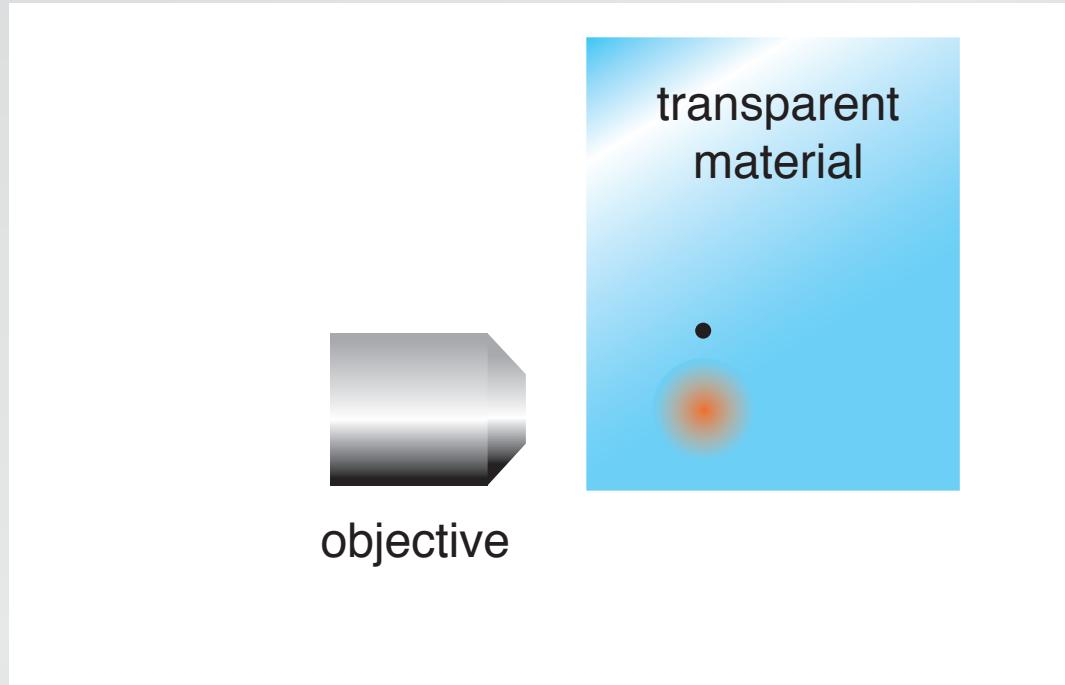
time scales



10–100 ns: shock propagation

Femtosecond micromachining

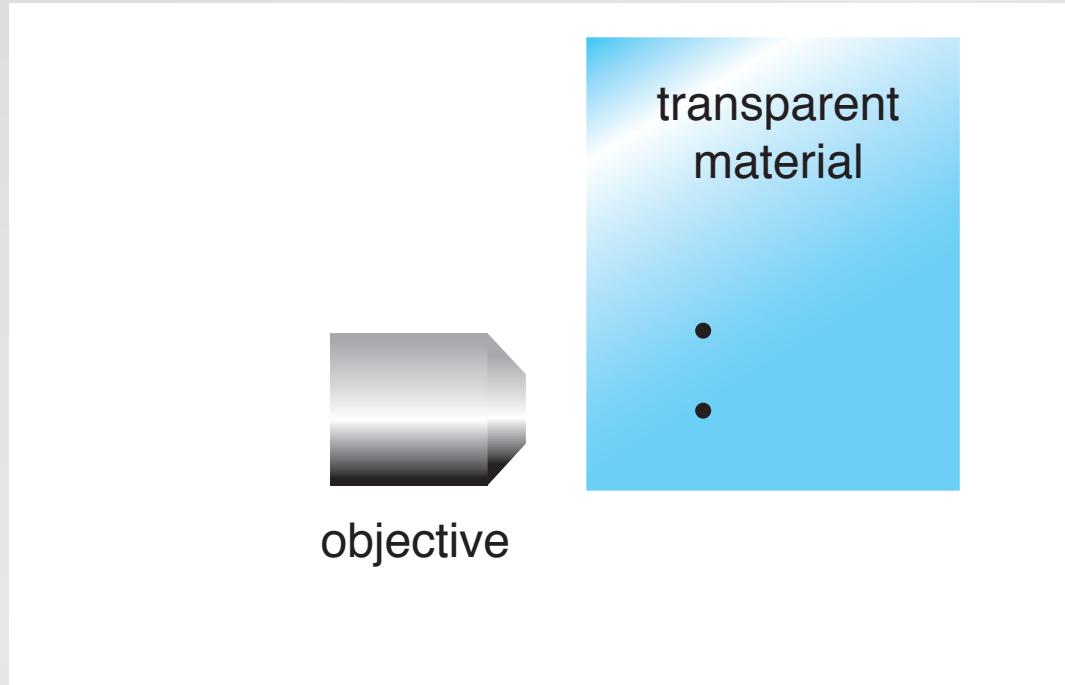
time scales



1 μ s: thermal expansion

Femtosecond micromachining

time scales

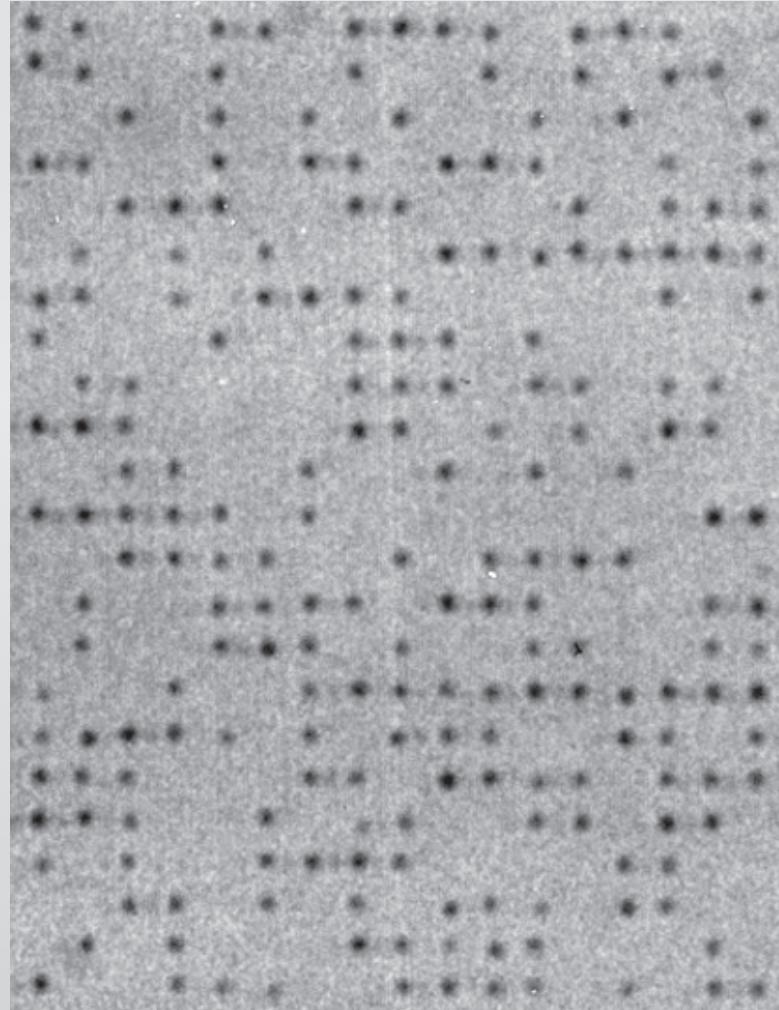


1 ms: permanent structural damage

Femtosecond micromachining

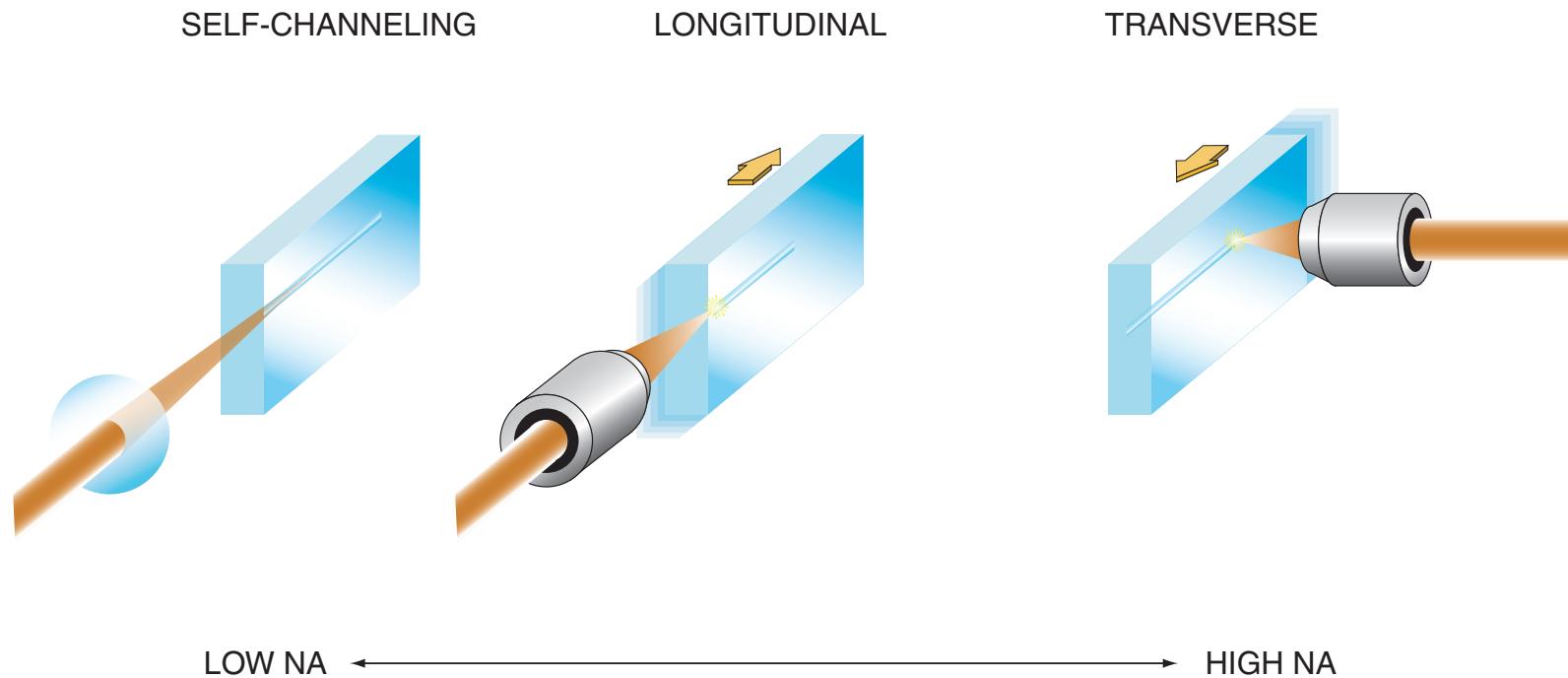
Some applications:

- data storage
- waveguides
- microfluidics



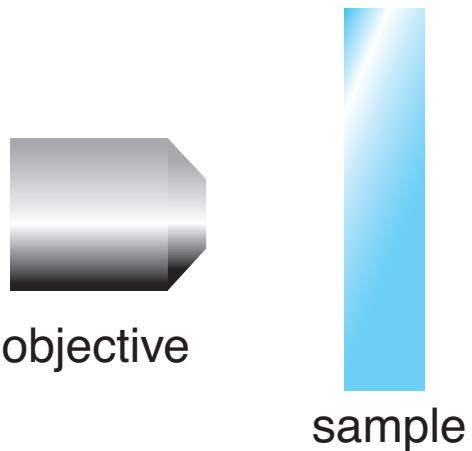
Femtosecond micromachining

waveguide micromachining geometries



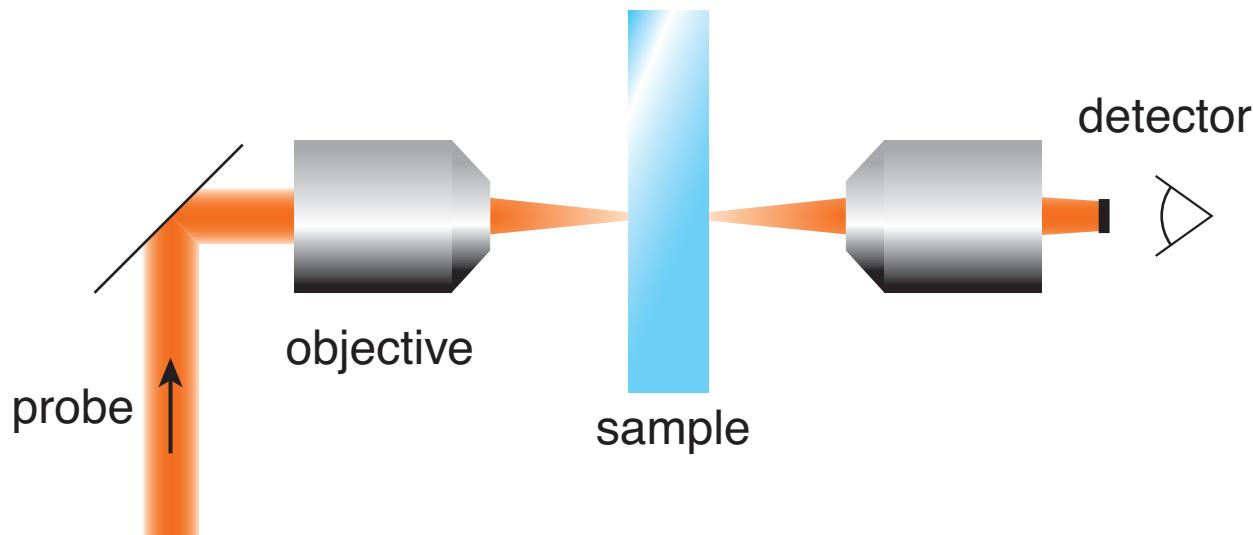
Femtosecond micromachining

Dark-field scattering



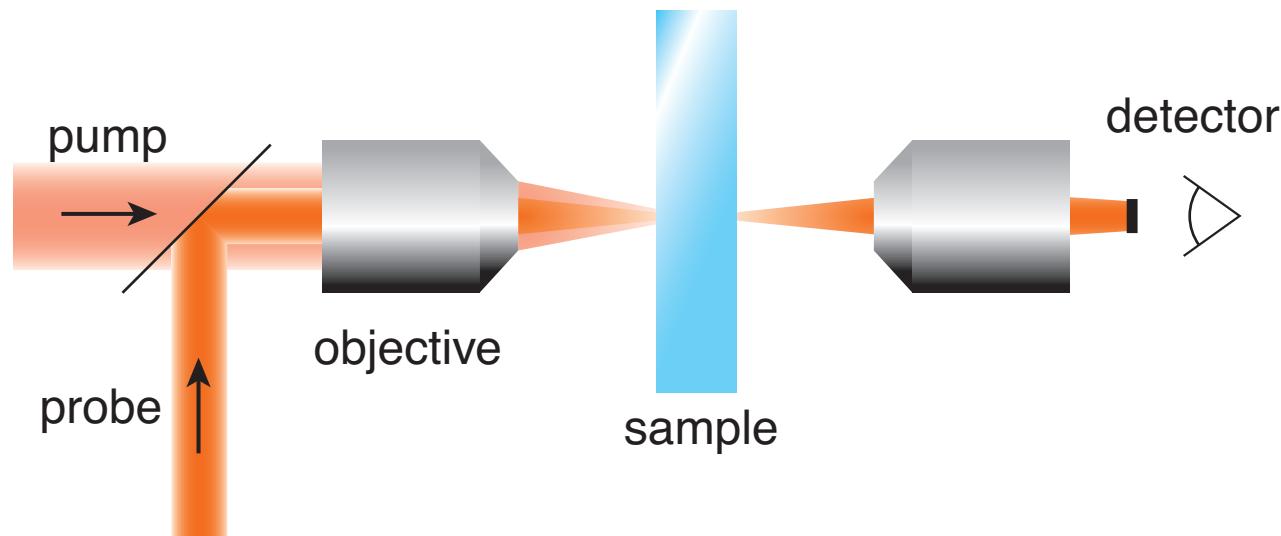
Femtosecond micromachining

block probe beam...



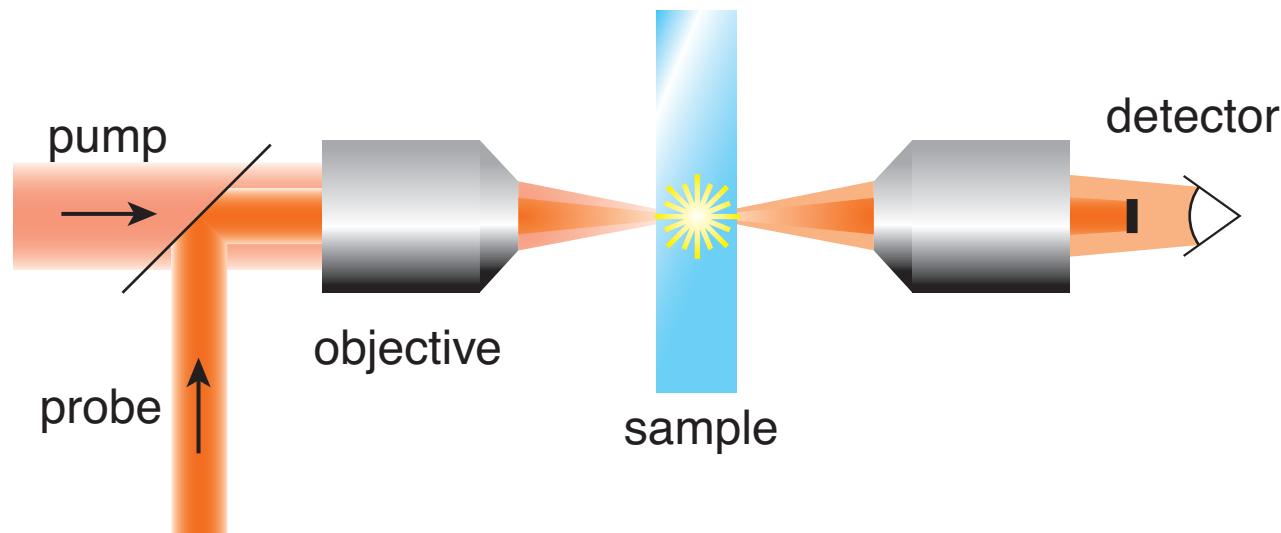
Femtosecond micromachining

... bring in pump beam...



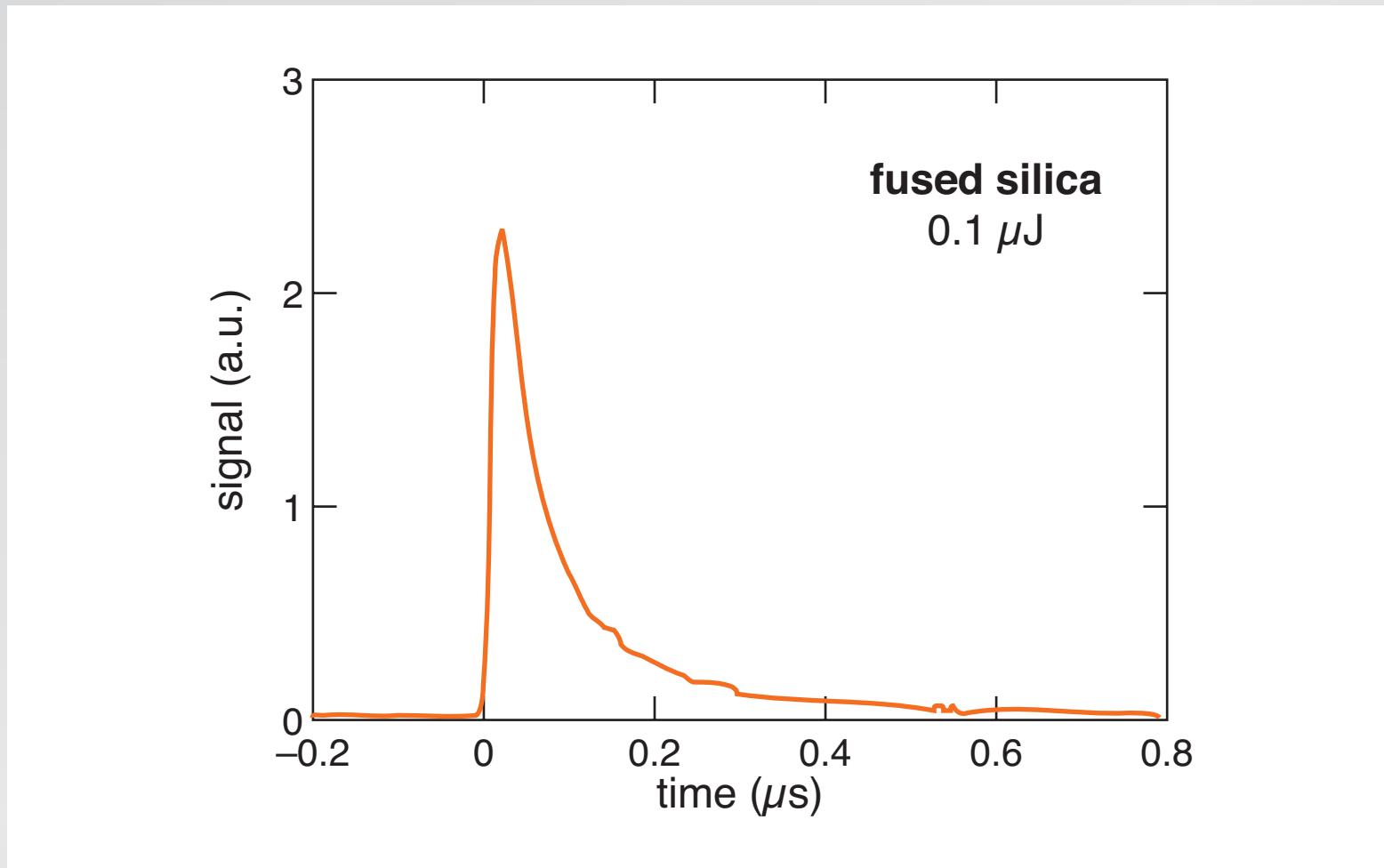
Femtosecond micromachining

... damage scatters probe beam



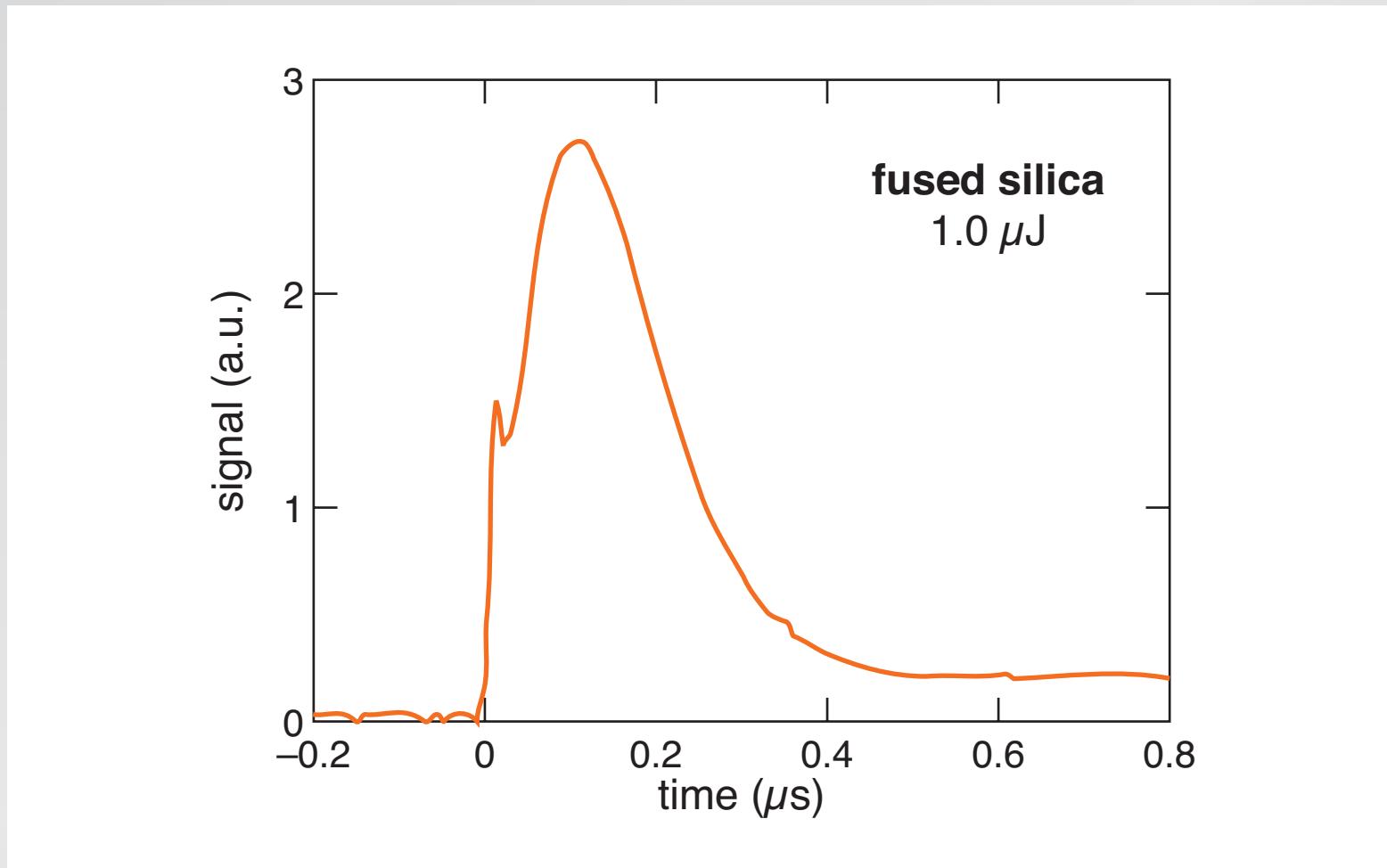
Femtosecond micromachining

scattered signal



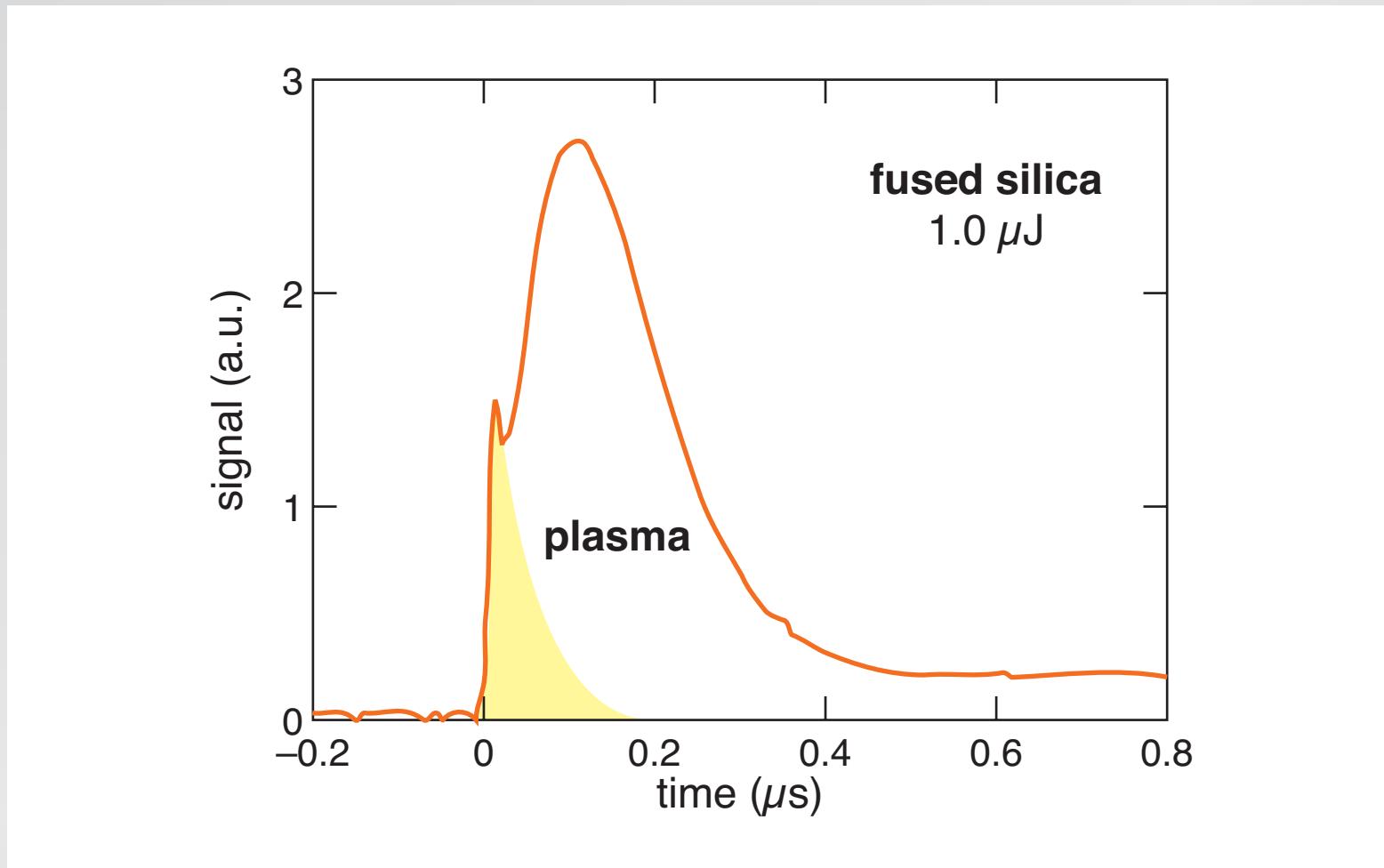
Femtosecond micromachining

scattered signal



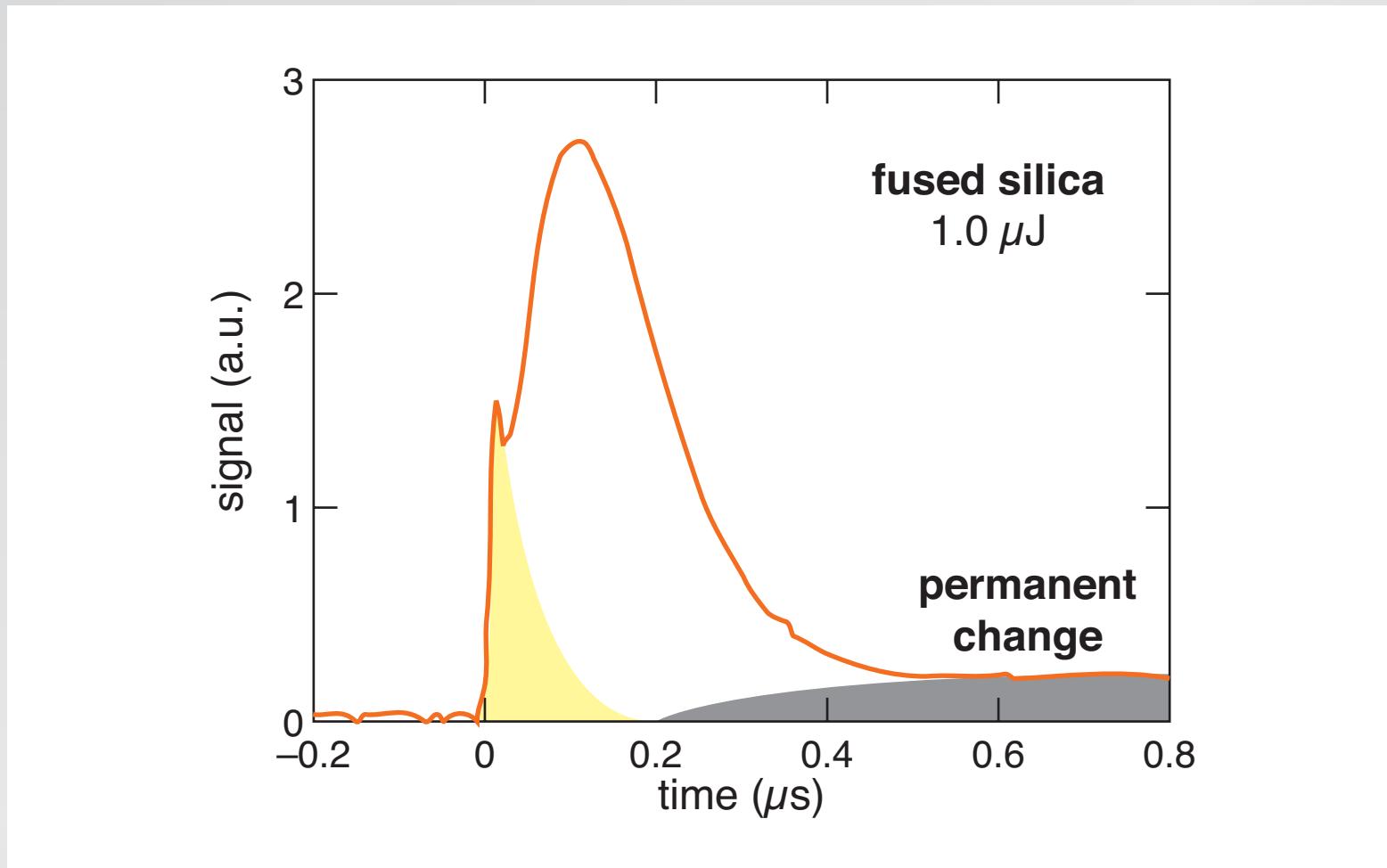
Femtosecond micromachining

scattered signal



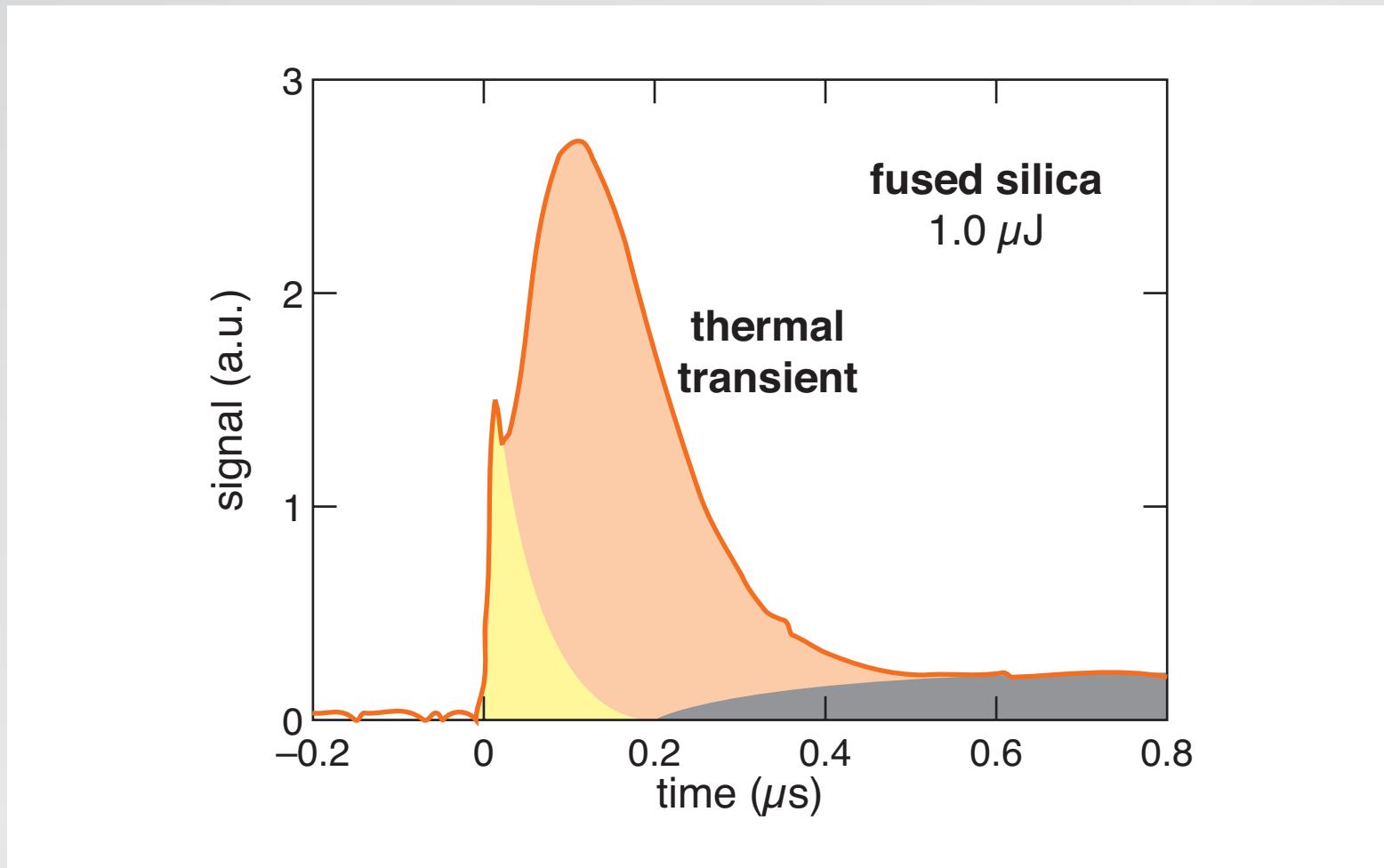
Femtosecond micromachining

scattered signal



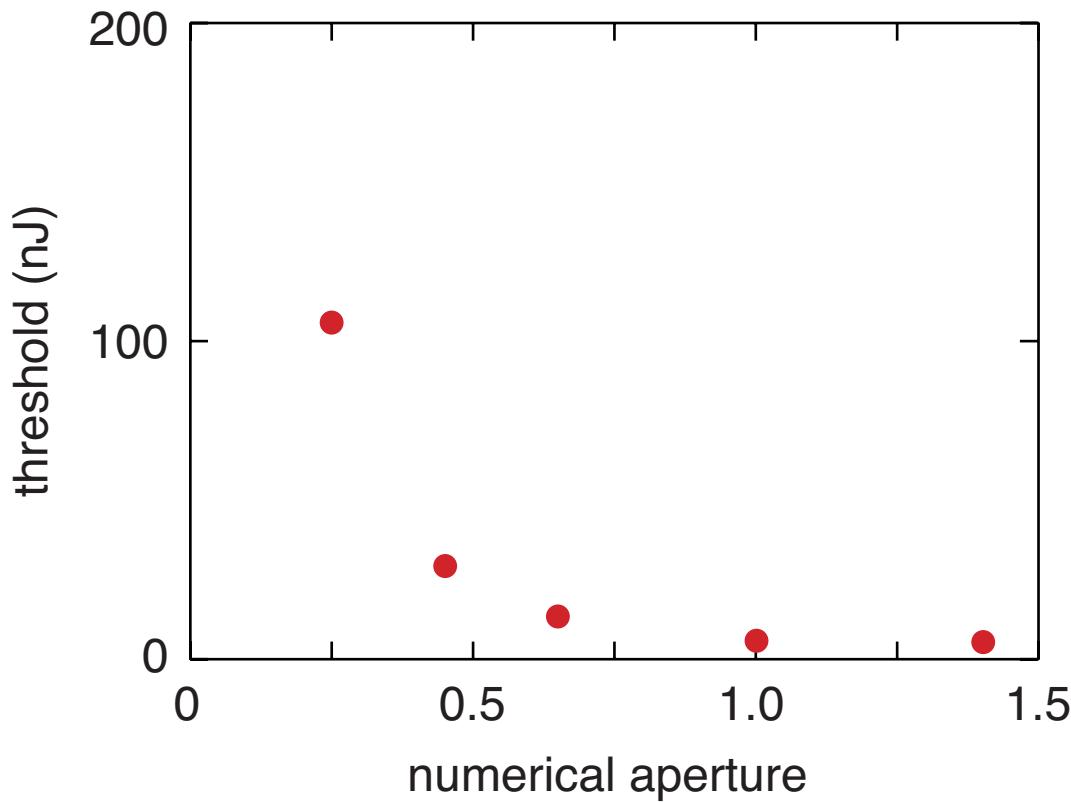
Femtosecond micromachining

scattered signal



Femtosecond micromachining

vary numerical aperture



Femtosecond micromachining

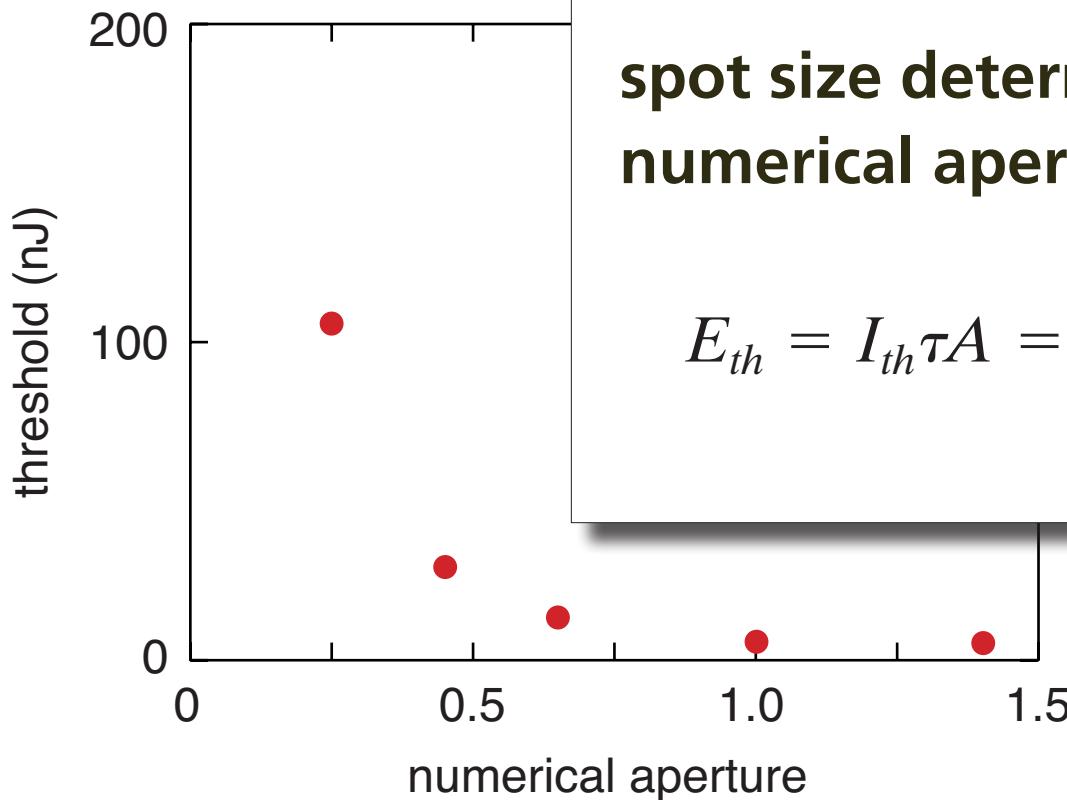
vary numerical aperture

intensity threshold:

$$E_{th} = I_{th}\tau A$$

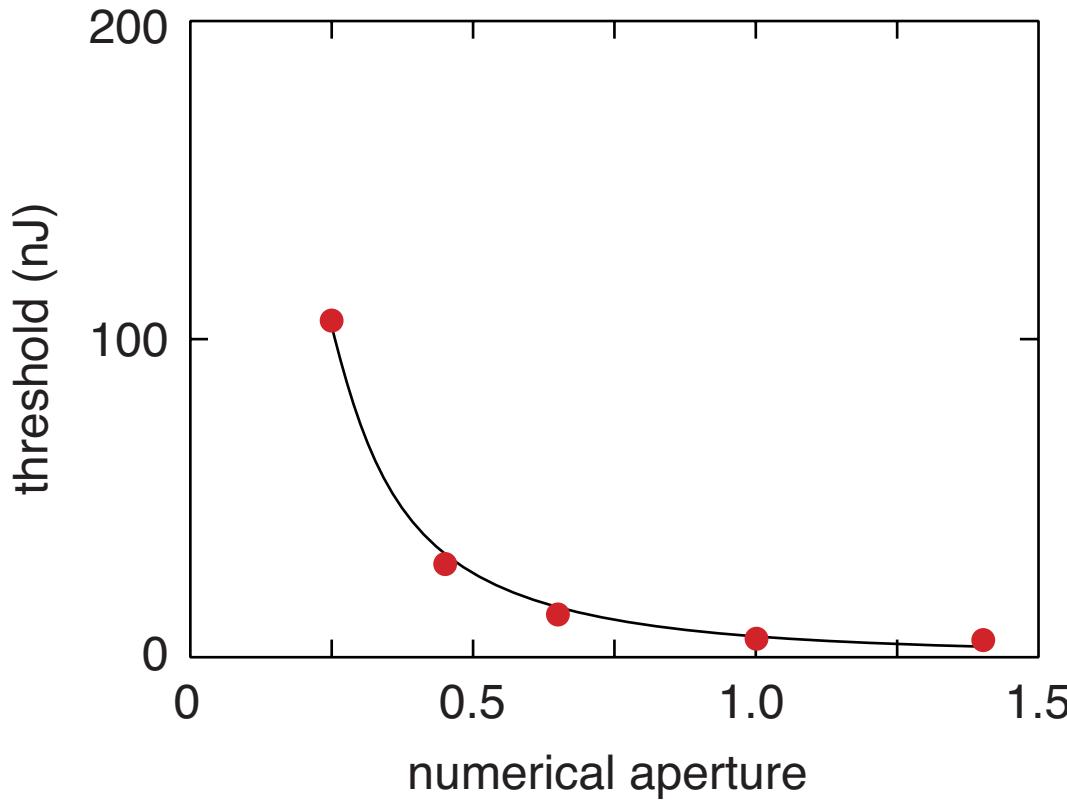
spot size determined by numerical aperture:

$$E_{th} = I_{th}\tau A = \frac{I_{th}\tau\lambda^2}{\pi(\text{NA})^2}$$



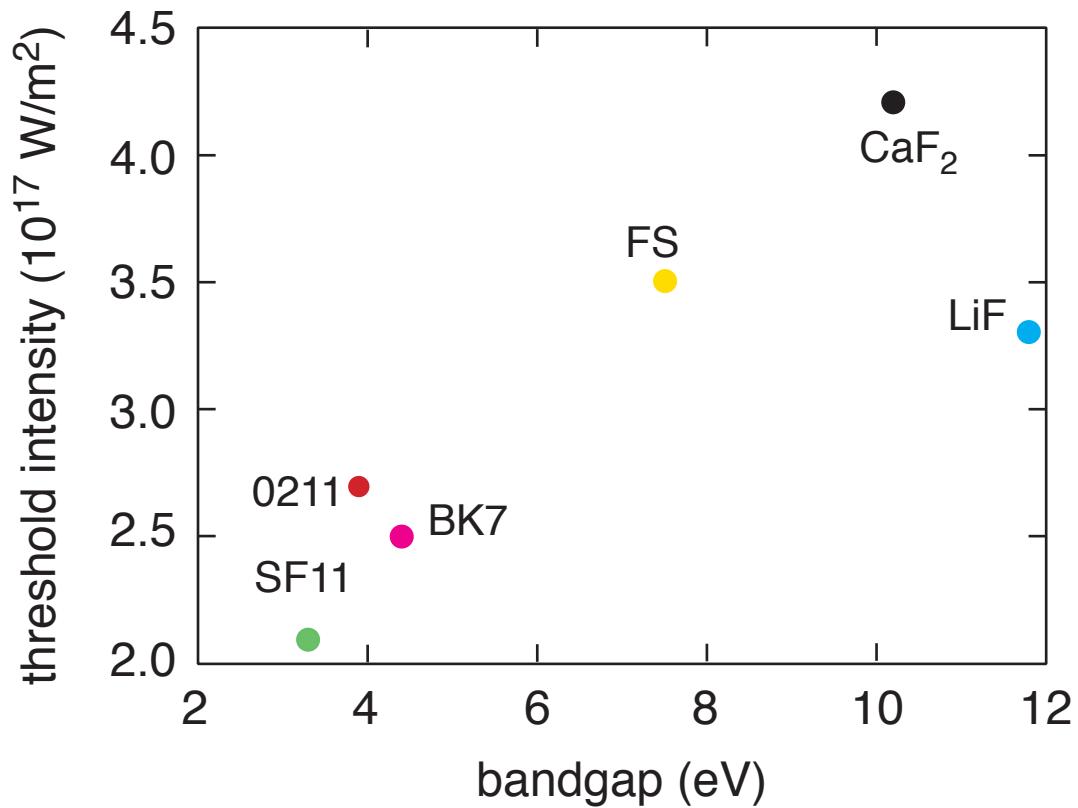
Femtosecond micromachining

fit gives threshold intensity: $I_{th} = 2.5 \times 10^{17} \text{ W/m}^2$



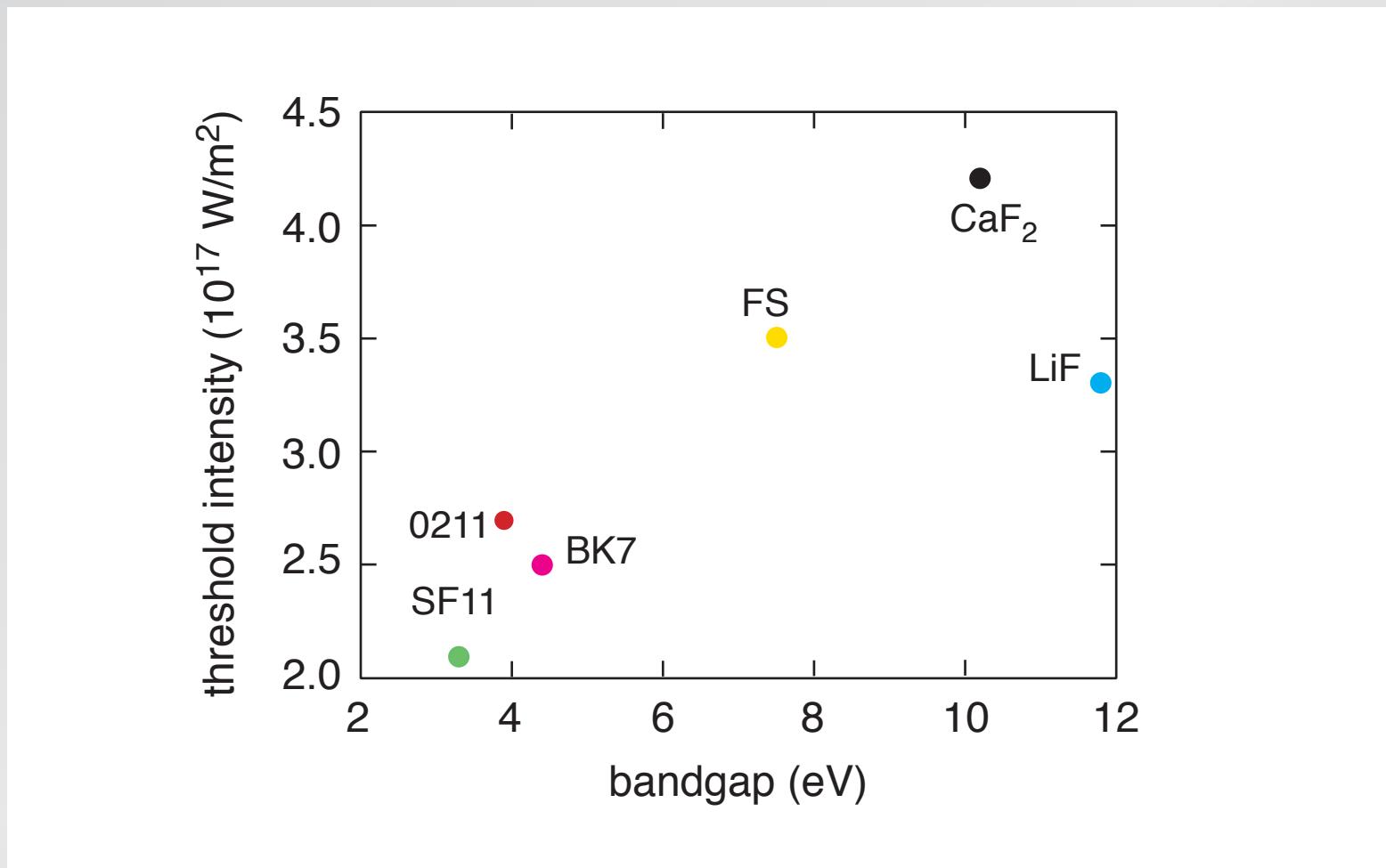
Femtosecond micromachining

vary material...



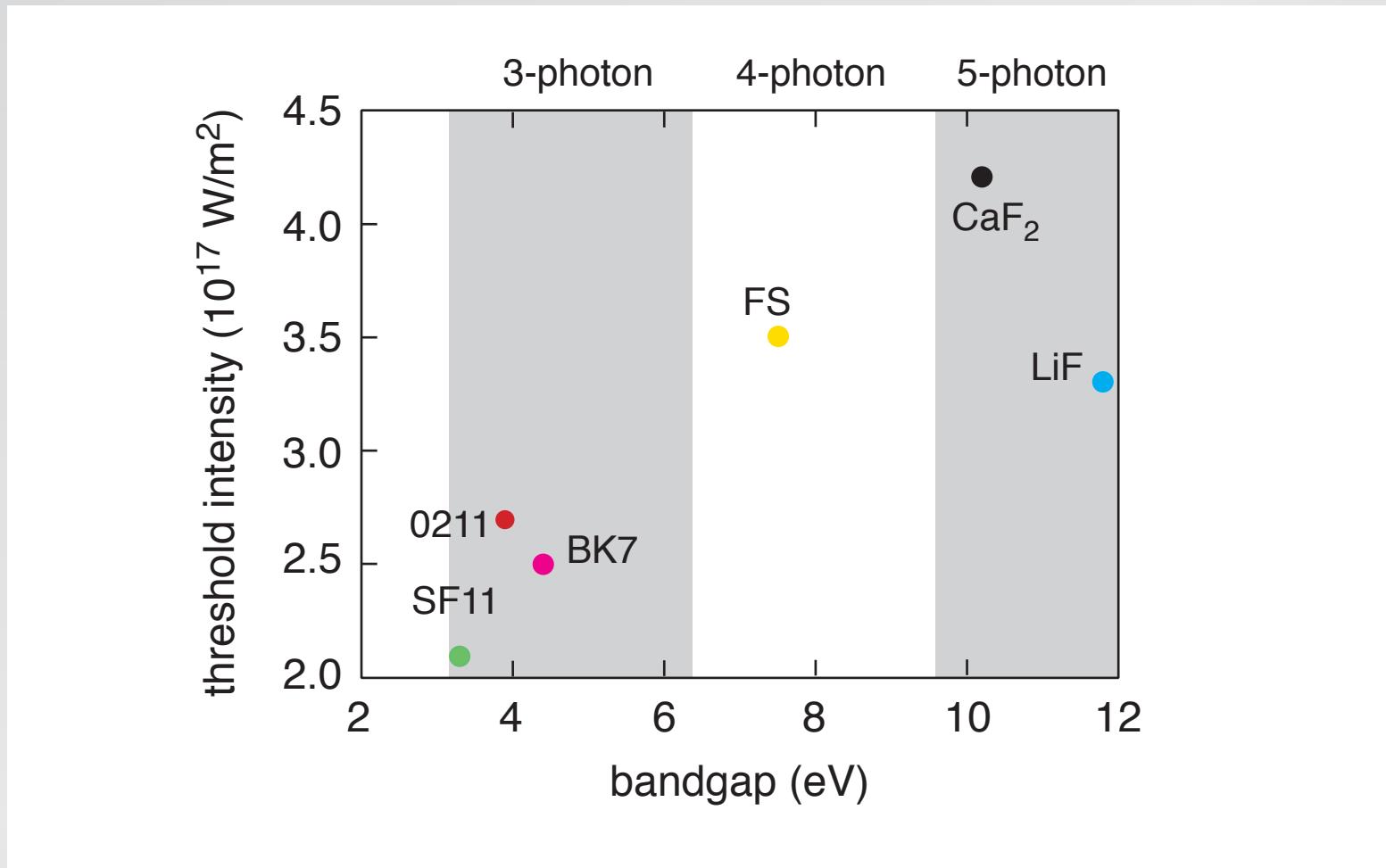
Femtosecond micromachining

...threshold varies with band gap (but not much!)



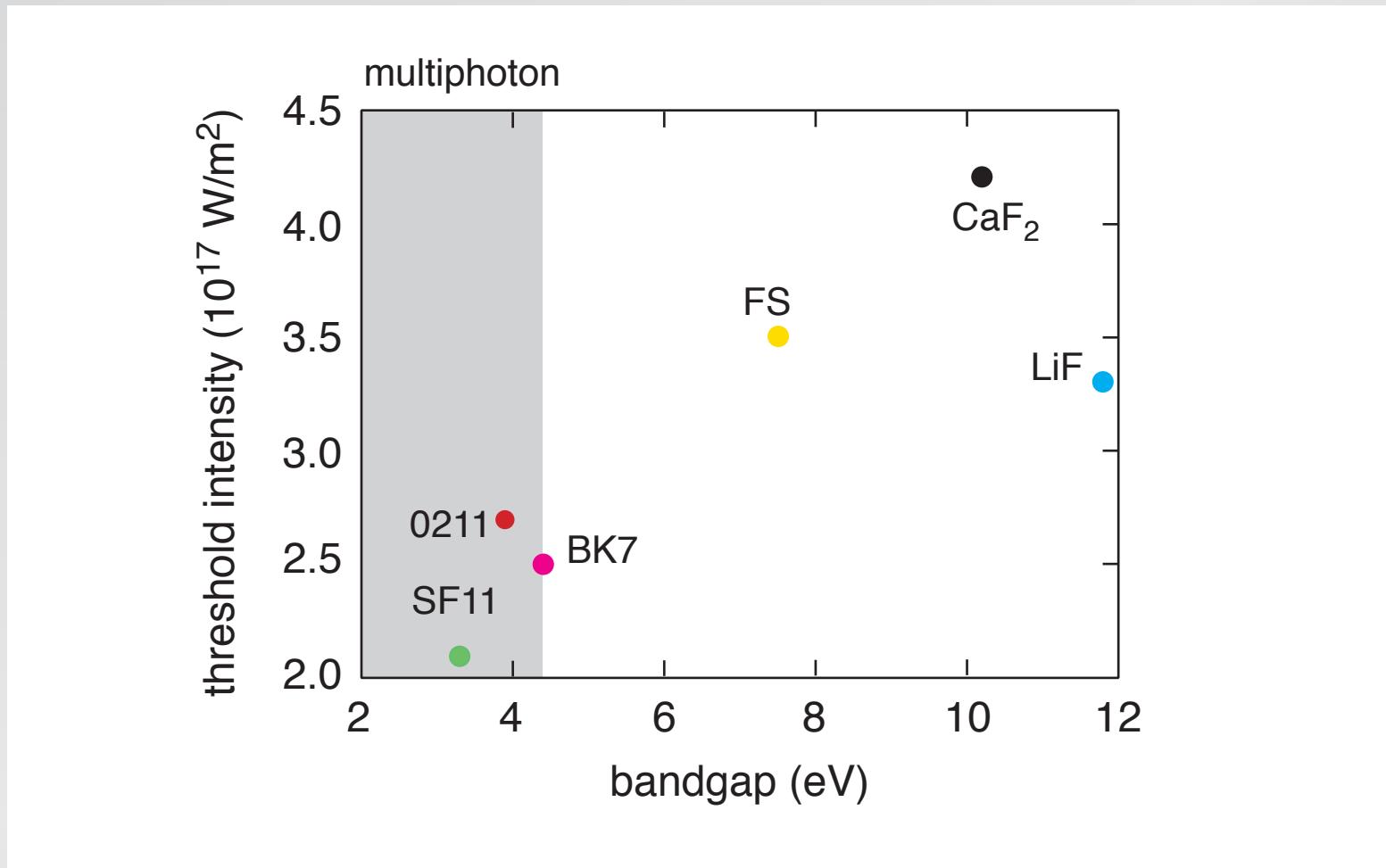
Femtosecond micromachining

would expect much more than a factor of 2



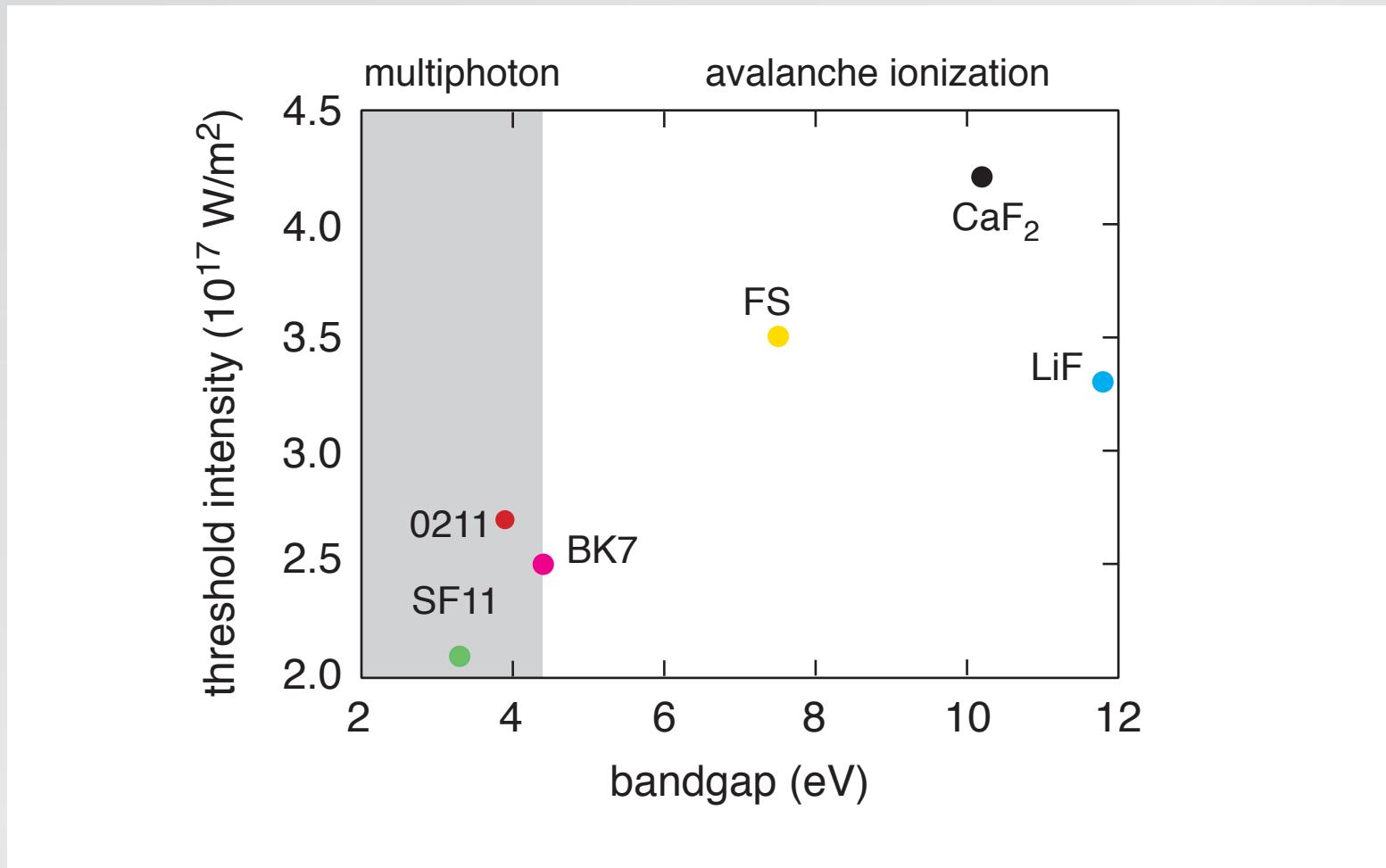
Femtosecond micromachining

critical density reached by multiphoton for low gap only



Femtosecond micromachining

avalanche ionization important at high gap



Femtosecond micromachining

what prevents damage at low NA?

Femtosecond micromachining

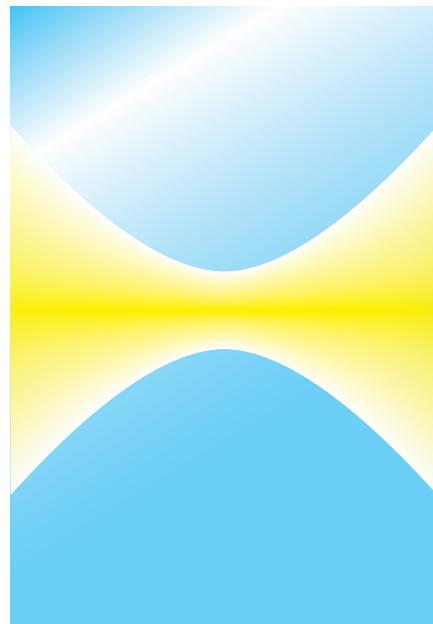
Competing nonlinear effects:

- multiphoton absorption
- supercontinuum generation
- self-focusing

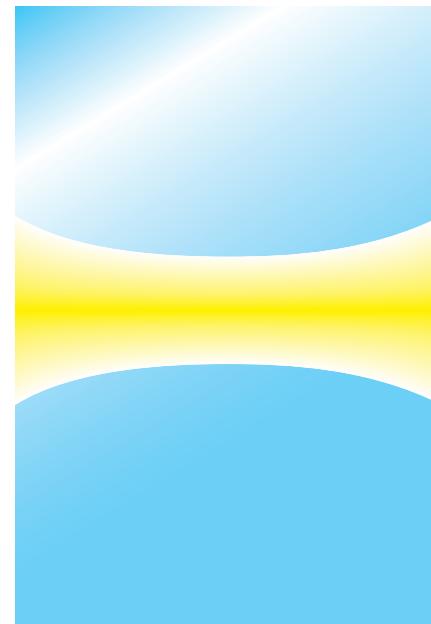
Femtosecond micromachining

why the difference?

high NA

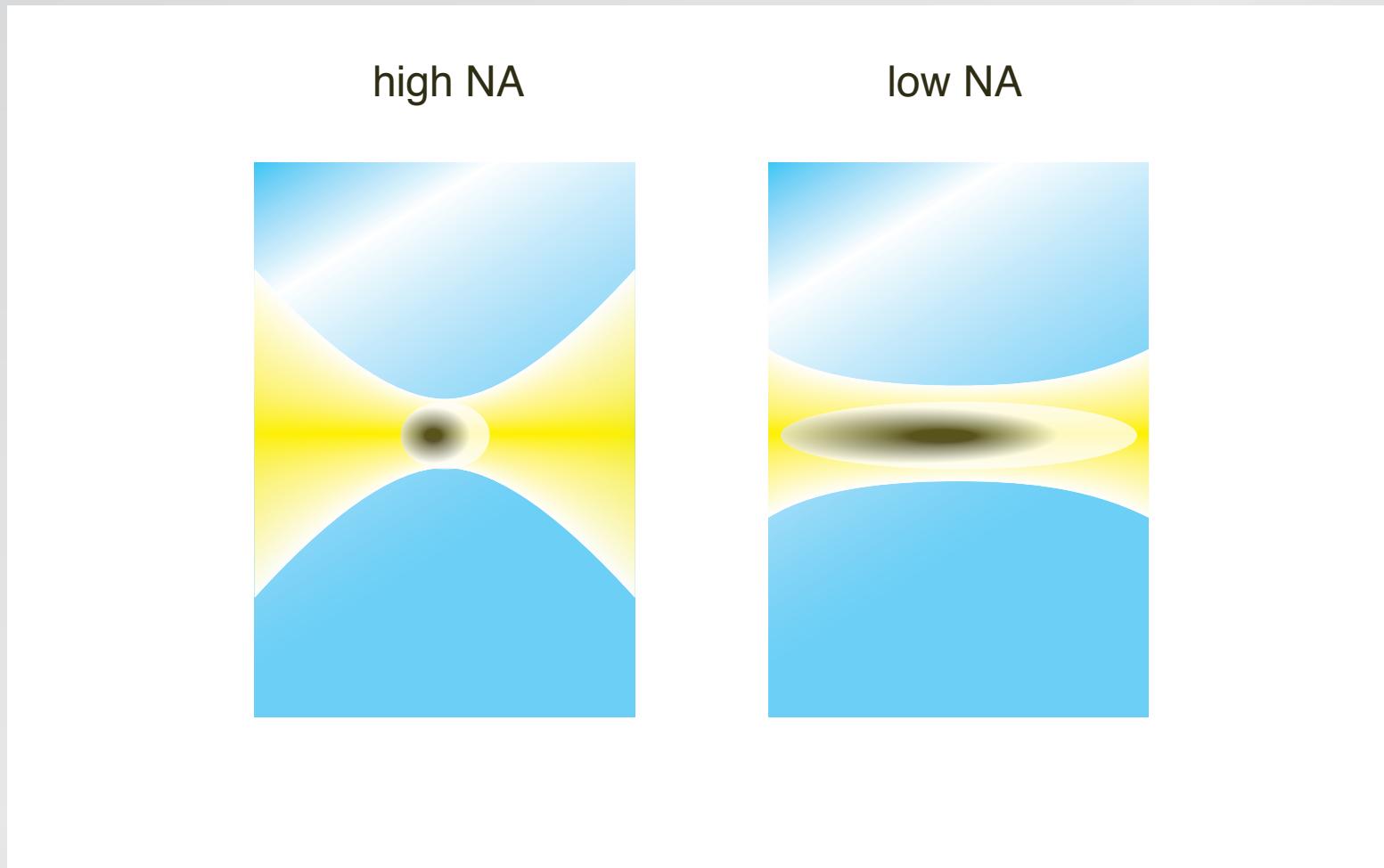


low NA



Femtosecond micromachining

very different confocal length/interaction length

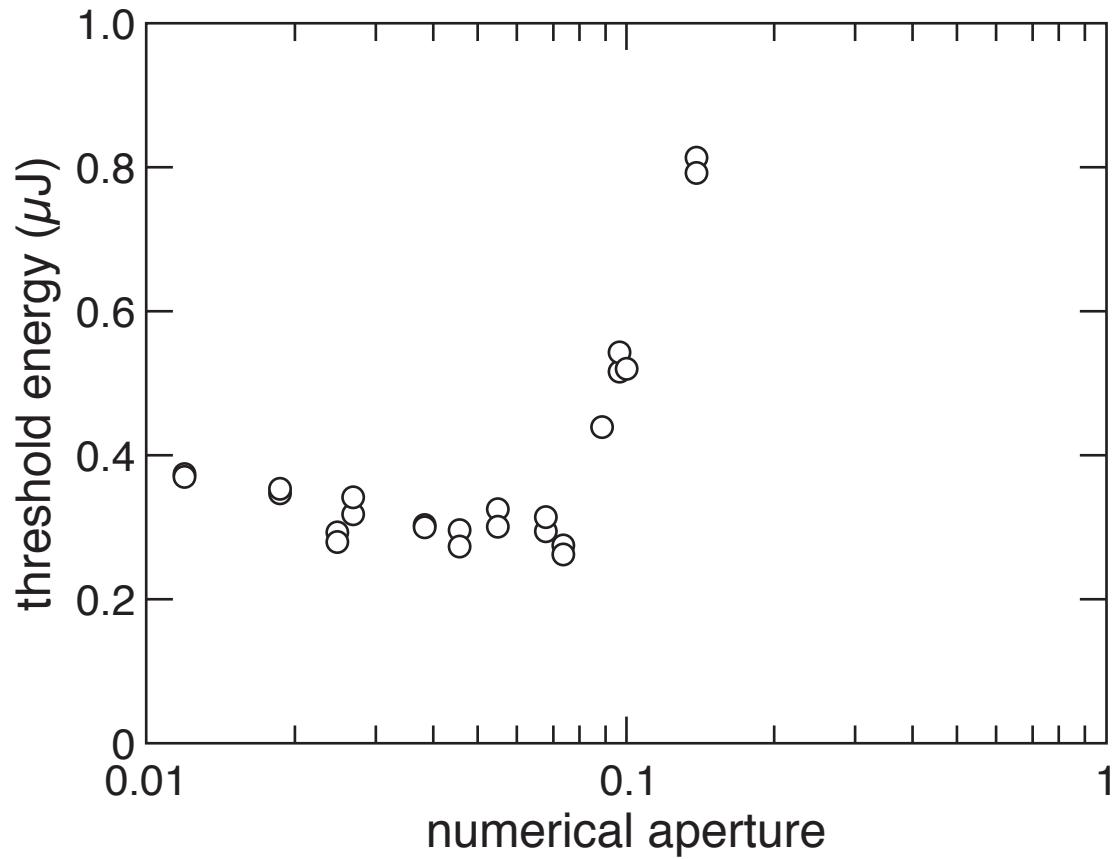


Femtosecond micromachining

high NA: interaction length too short for self-focusing

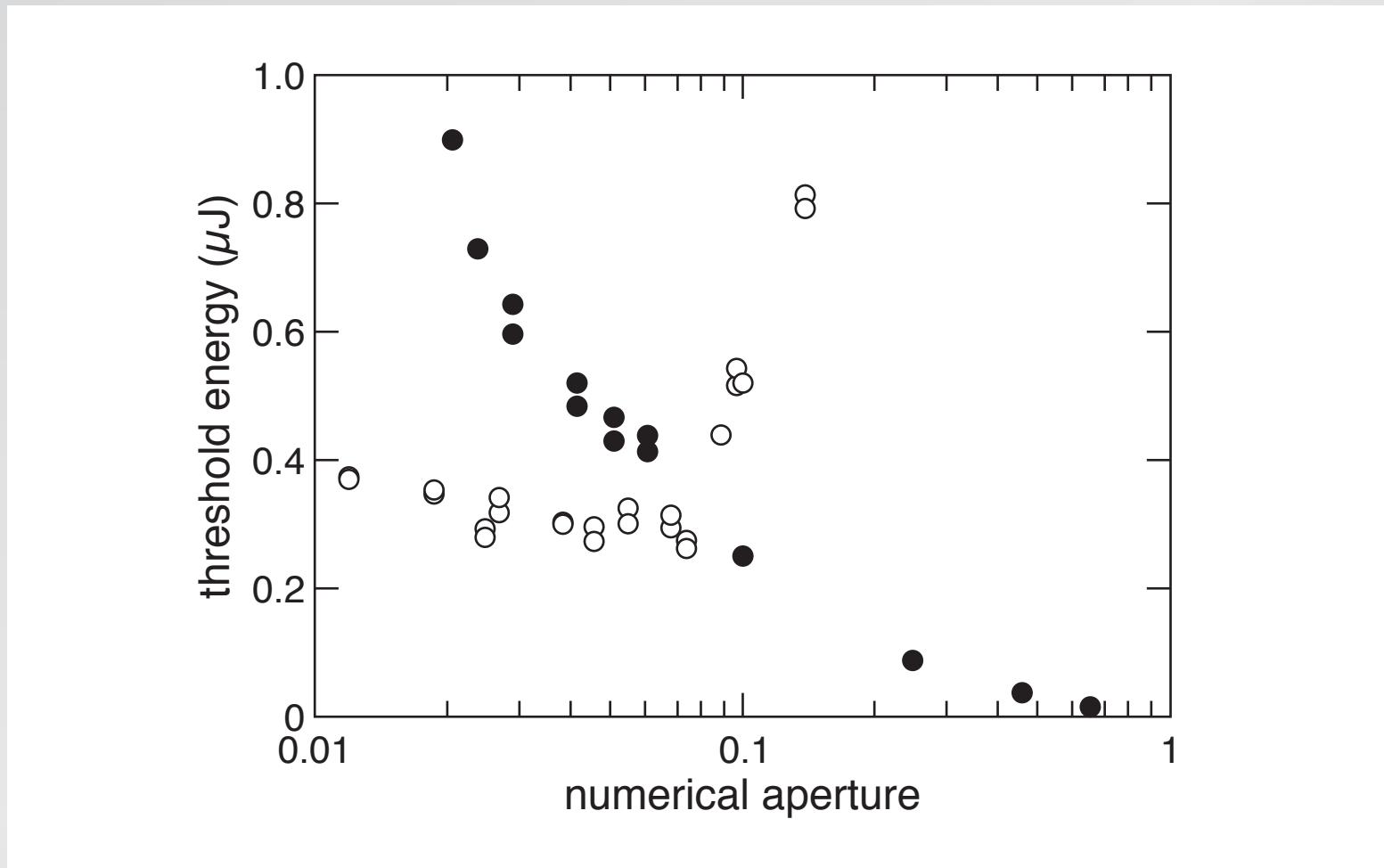
Femtosecond micromachining

threshold for supercontinuum generation



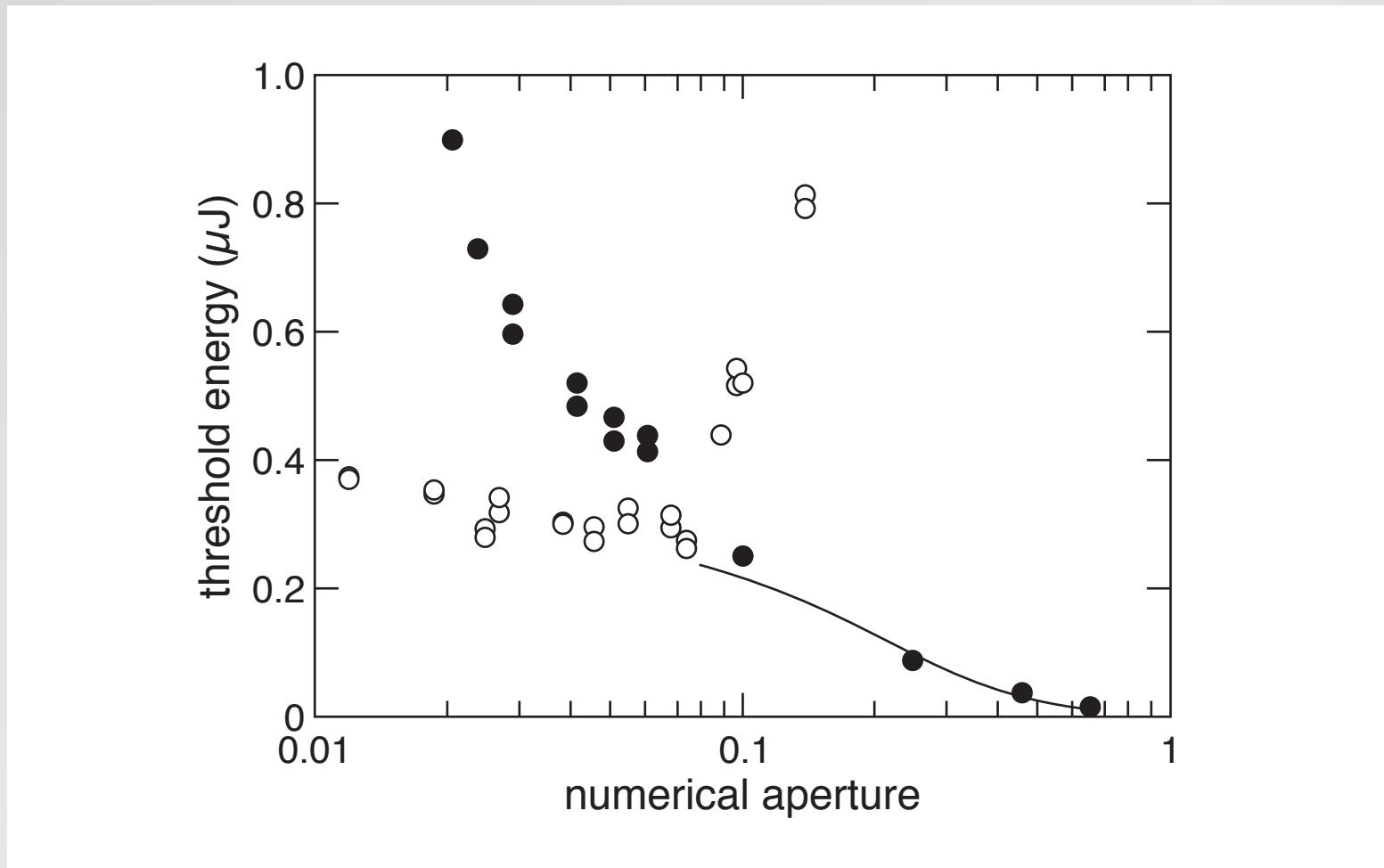
Femtosecond micromachining

threshold for damage



Femtosecond micromachining

constant intensity fit



Femtosecond micromachining

Points to keep in mind:

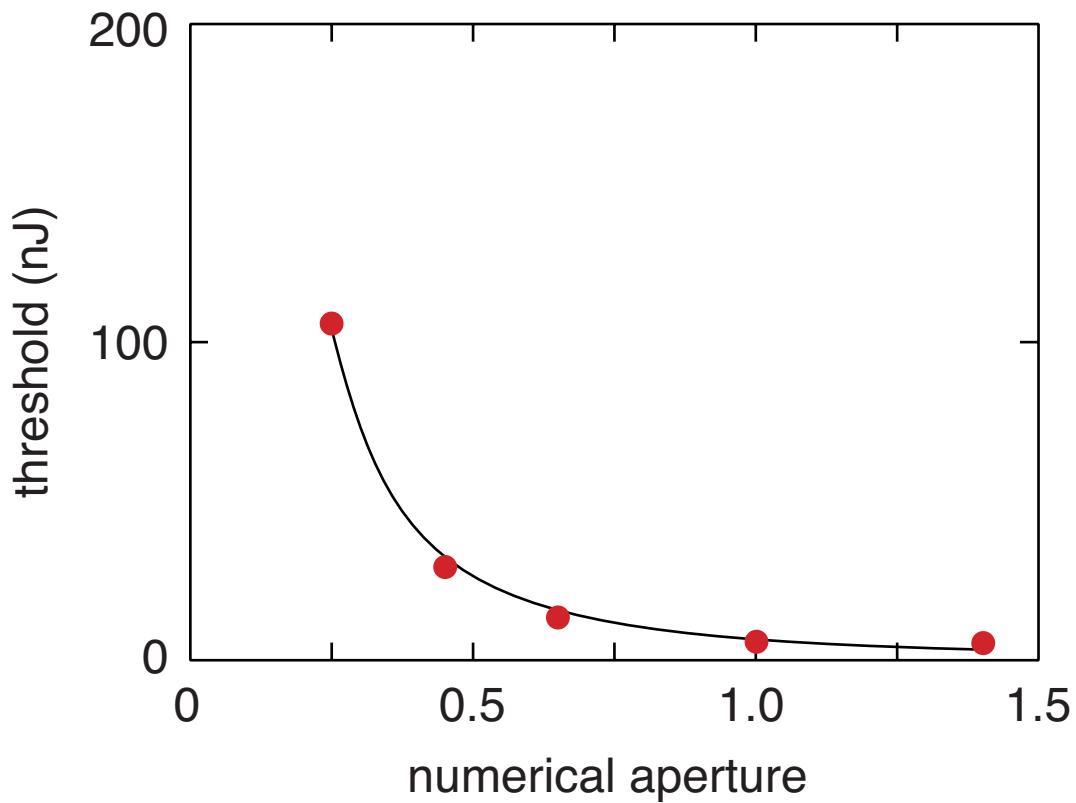
- threshold critically dependent on NA
- surprisingly little material dependence
- avalanche ionization important

Outline

- femtosecond micromachining
- low-energy machining
- applications

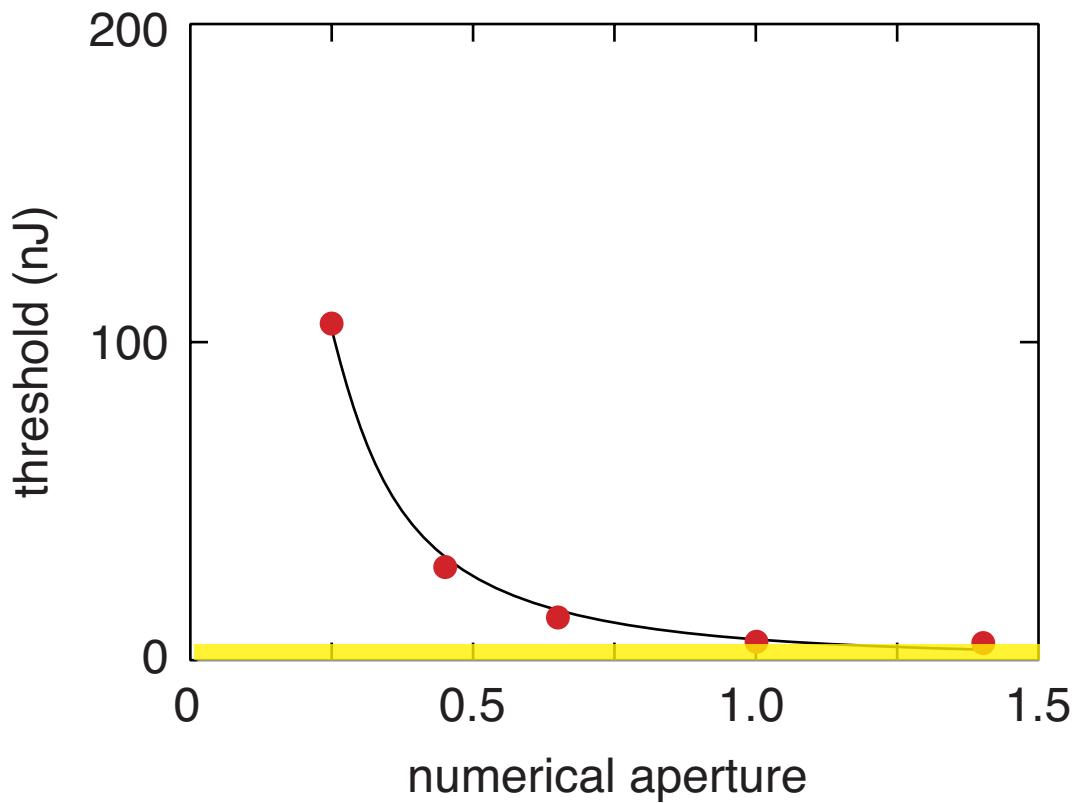
Low-energy machining

threshold decreases with increasing numerical aperture



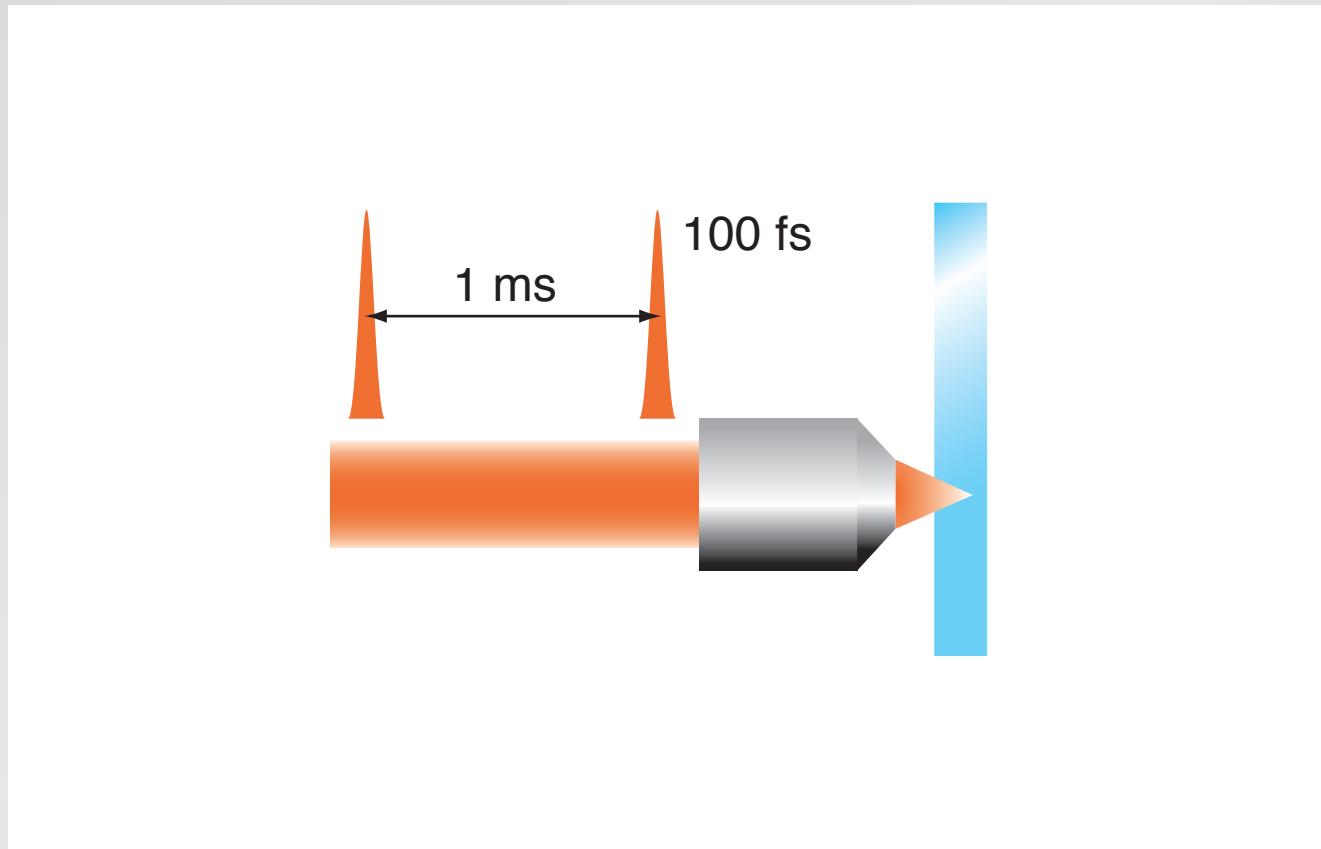
Low-energy machining

less than 10 nJ at high numerical aperture!



Low-energy machining

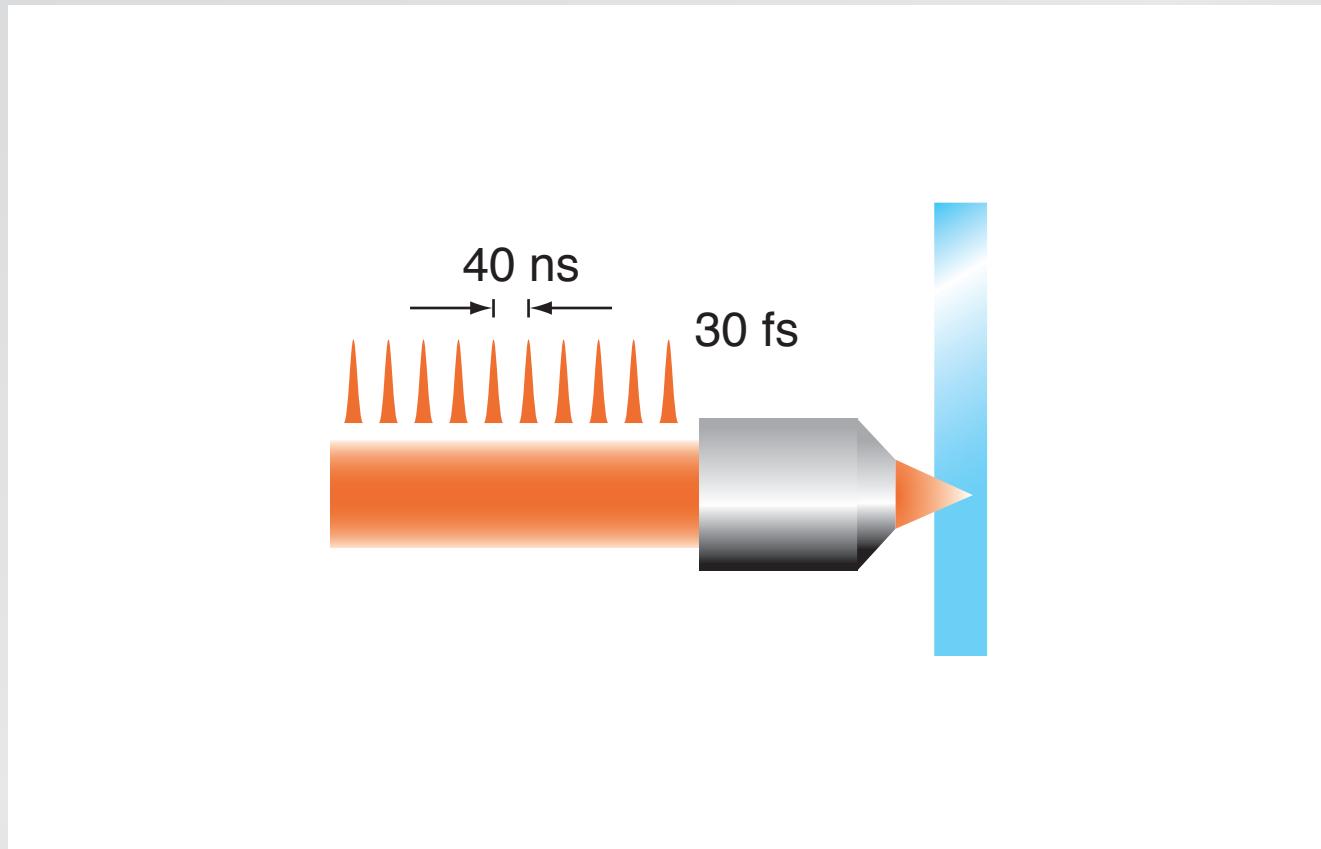
amplified laser: 1 kHz, 1 mJ



heat diffusion time: $\tau_{diff} \approx 1 \mu\text{s}$

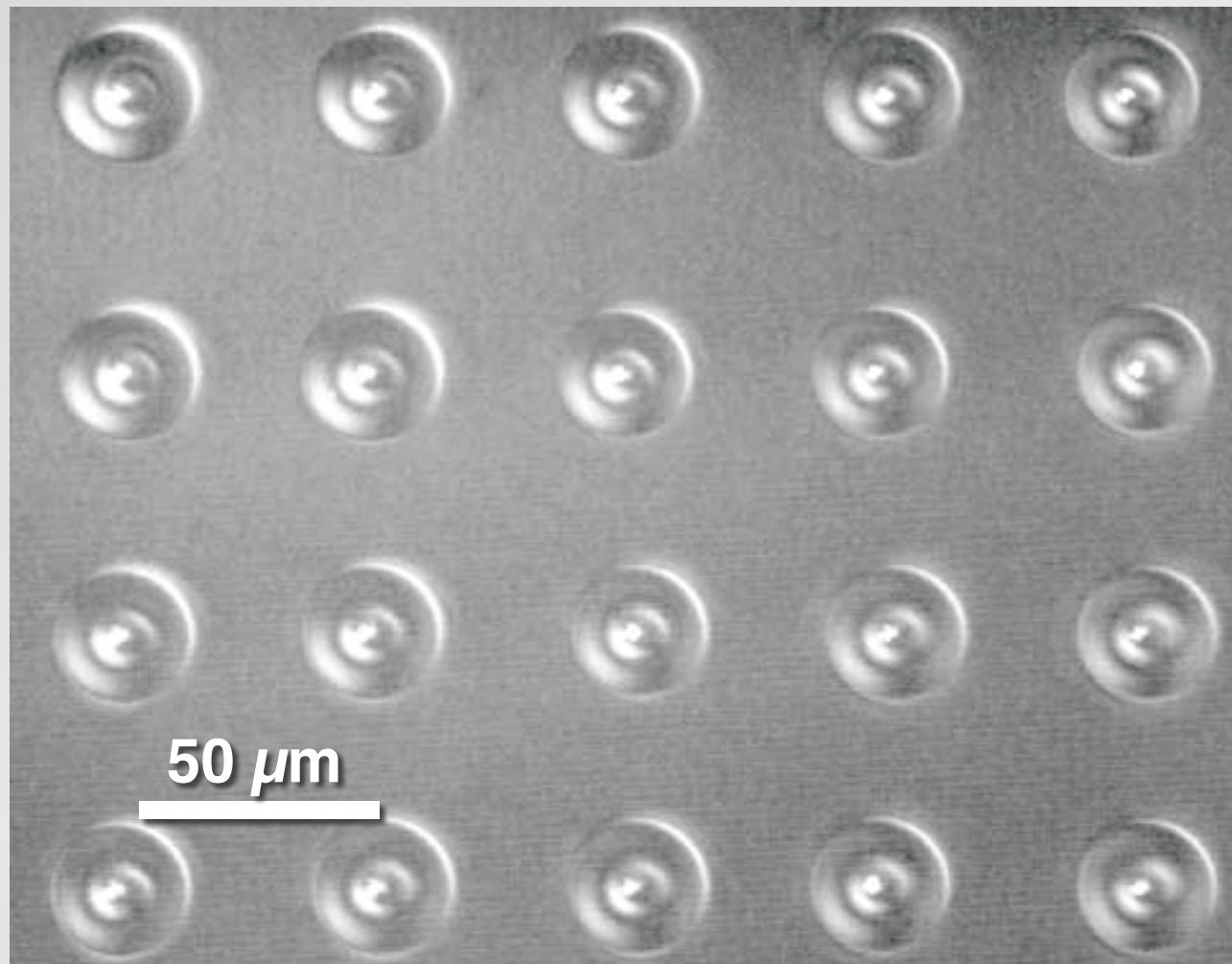
Low-energy machining

long cavity oscillator: 25 MHz, 25 nJ



heat diffusion time: $\tau_{diff} \approx 1 \mu\text{s}$

Low-energy machining



Low-energy machining

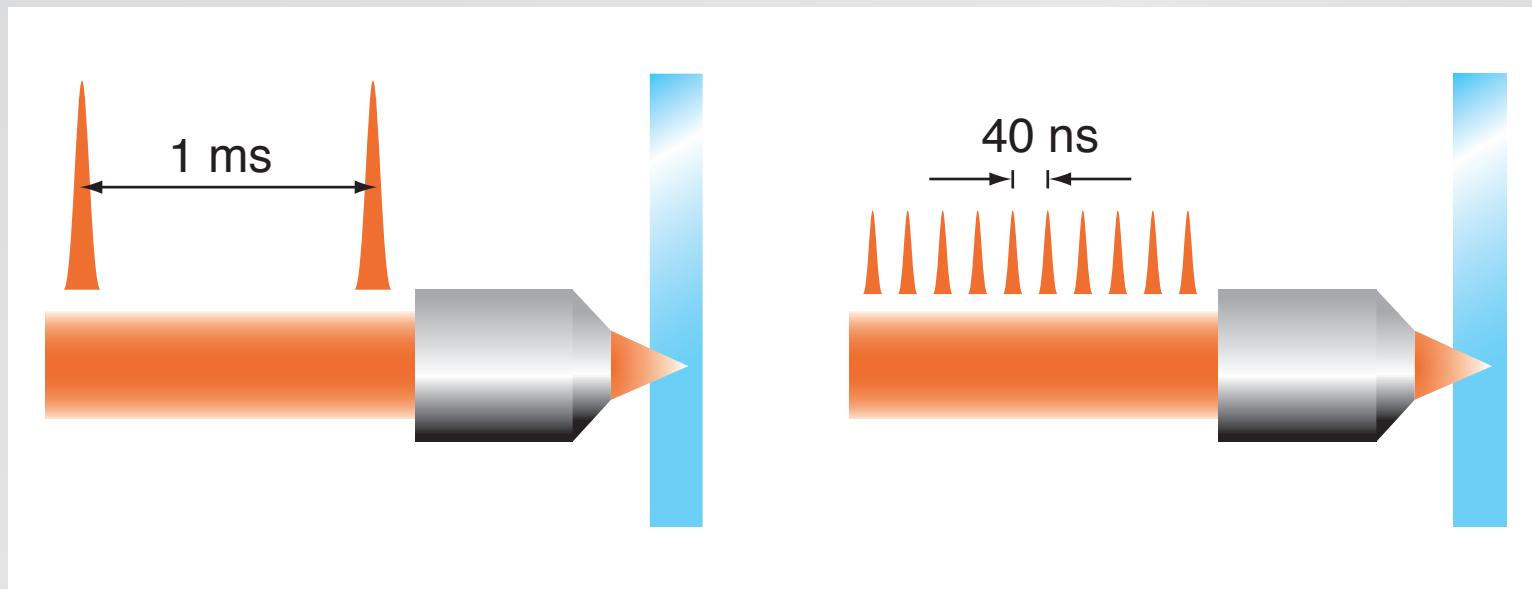
High repetition-rate micromachining:

- structural changes exceed focal volume
- spherical structures
- density change caused by melting

Low-energy machining

amplified laser

oscillator



repetitive

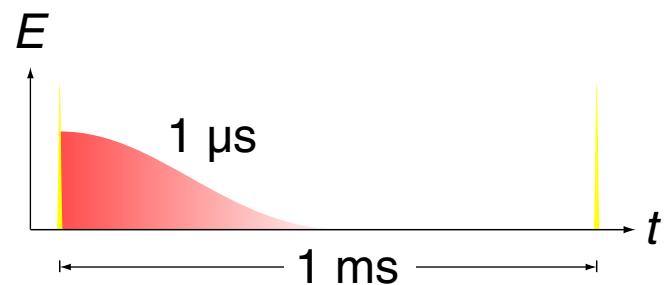
cumulative

Low-energy machining

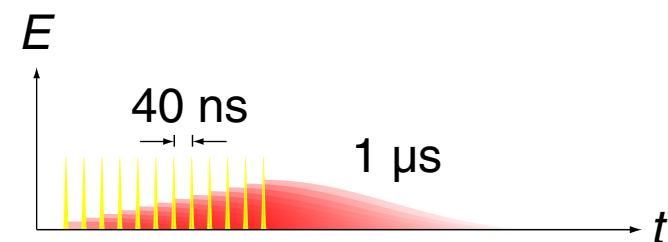
amplified laser

oscillator

low repetition rate



high repetition rate

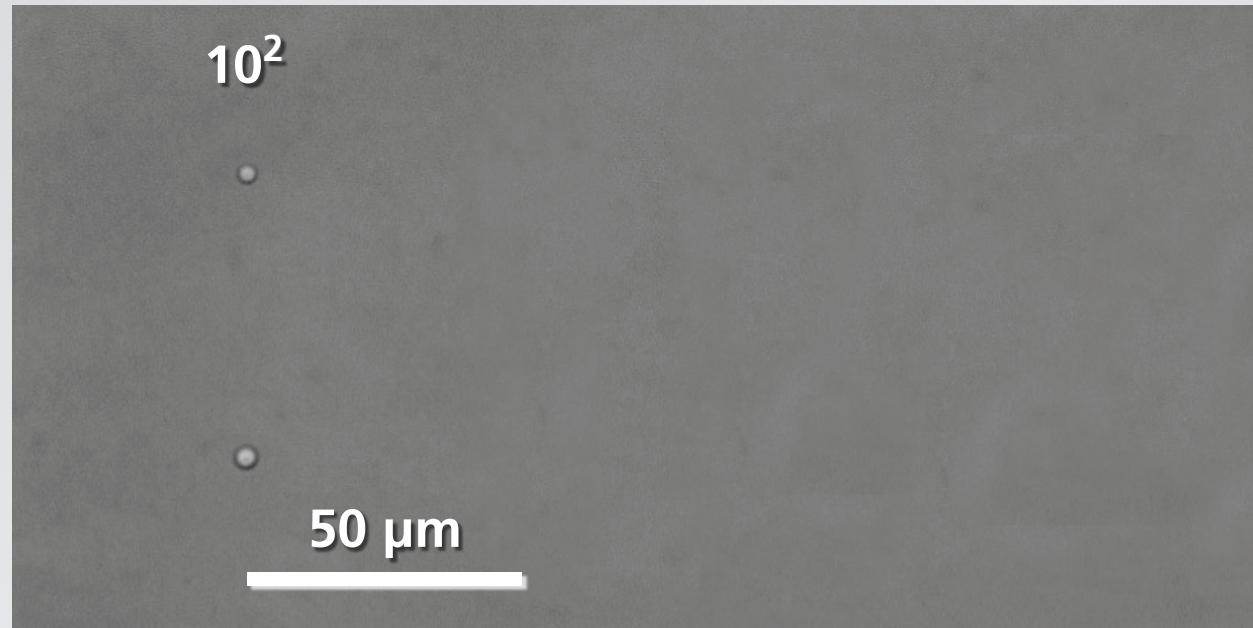


repetitive

cumulative

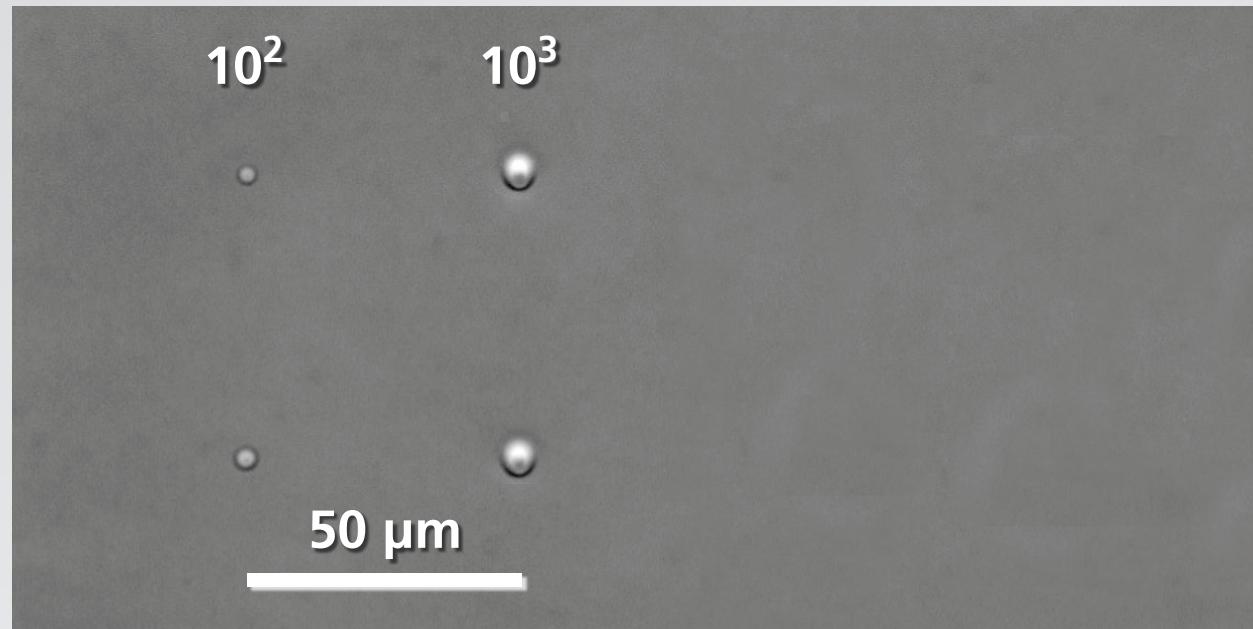
Low-energy machining

the longer the irradiation...



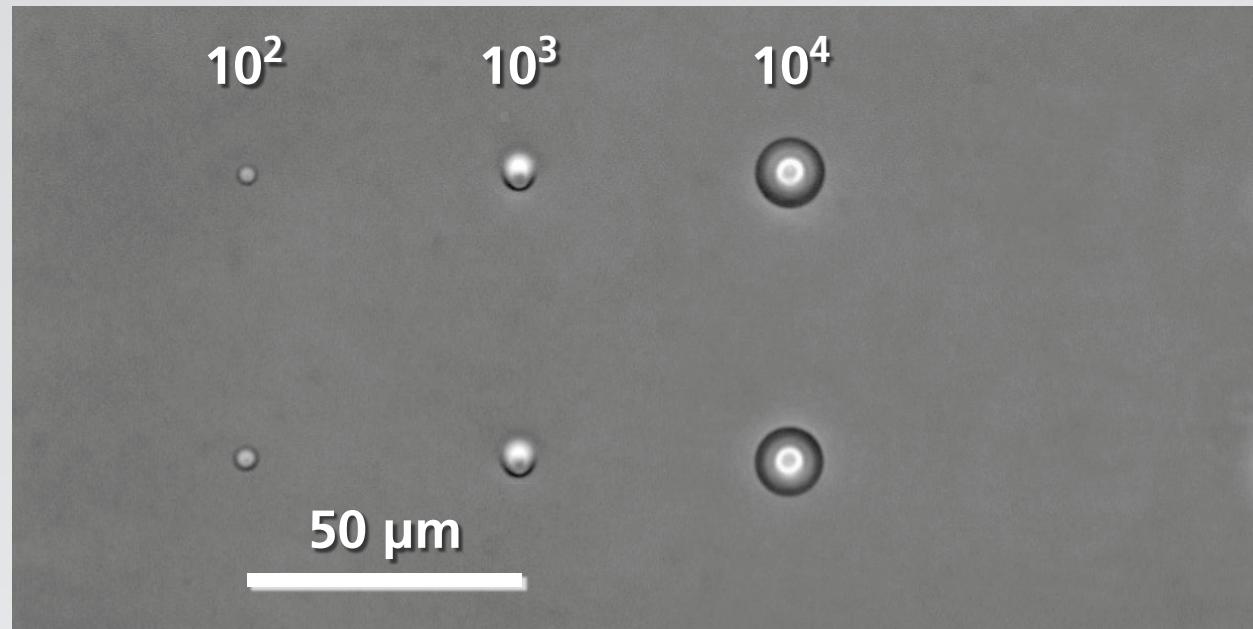
Low-energy machining

the longer the irradiation...



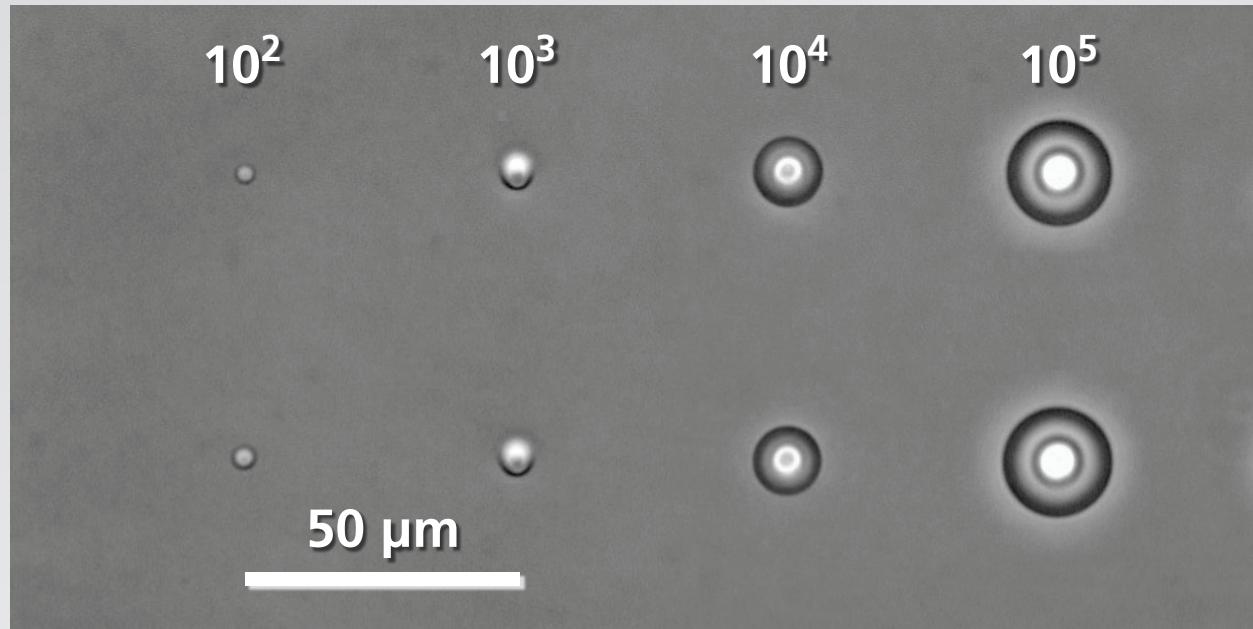
Low-energy machining

the longer the irradiation...



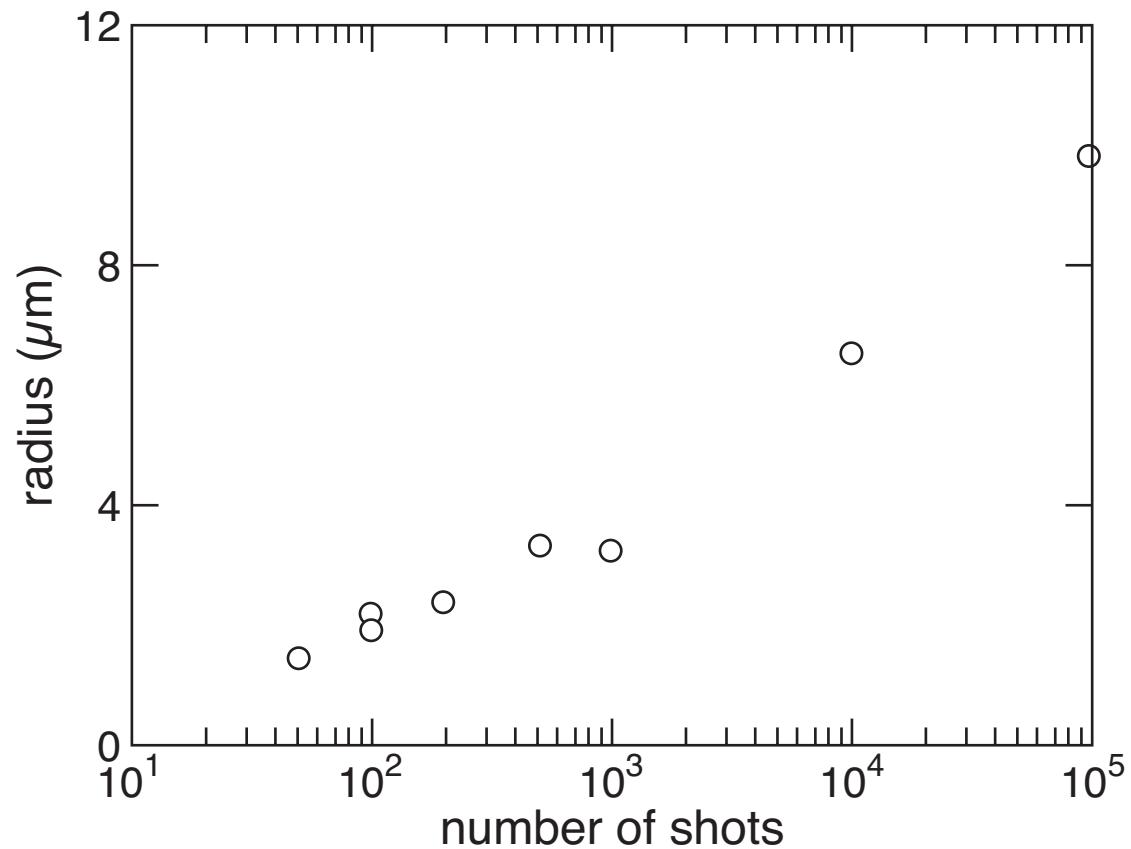
Low-energy machining

the longer the irradiation...



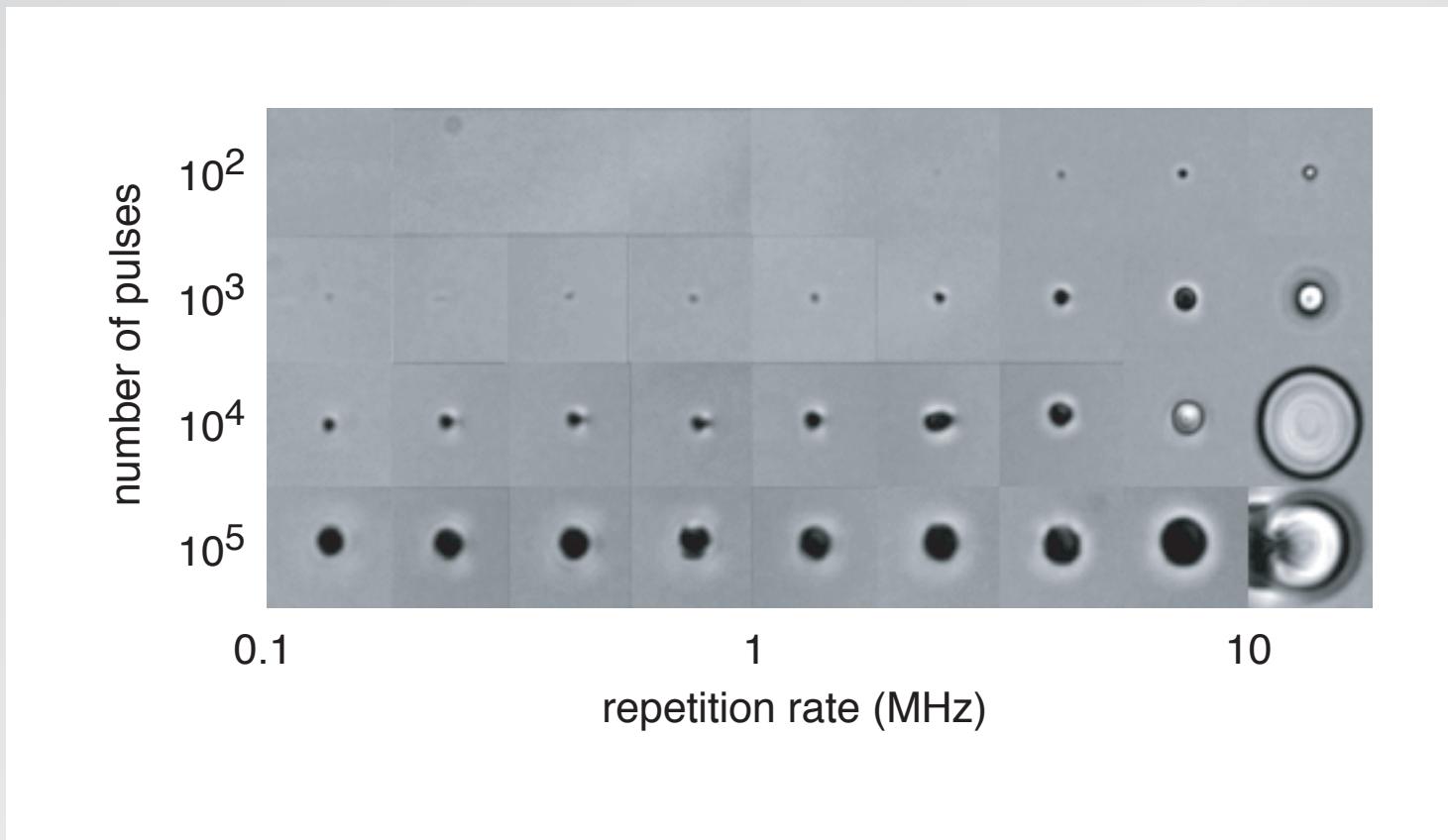
... the larger the radius

Low-energy machining



Low-energy machining

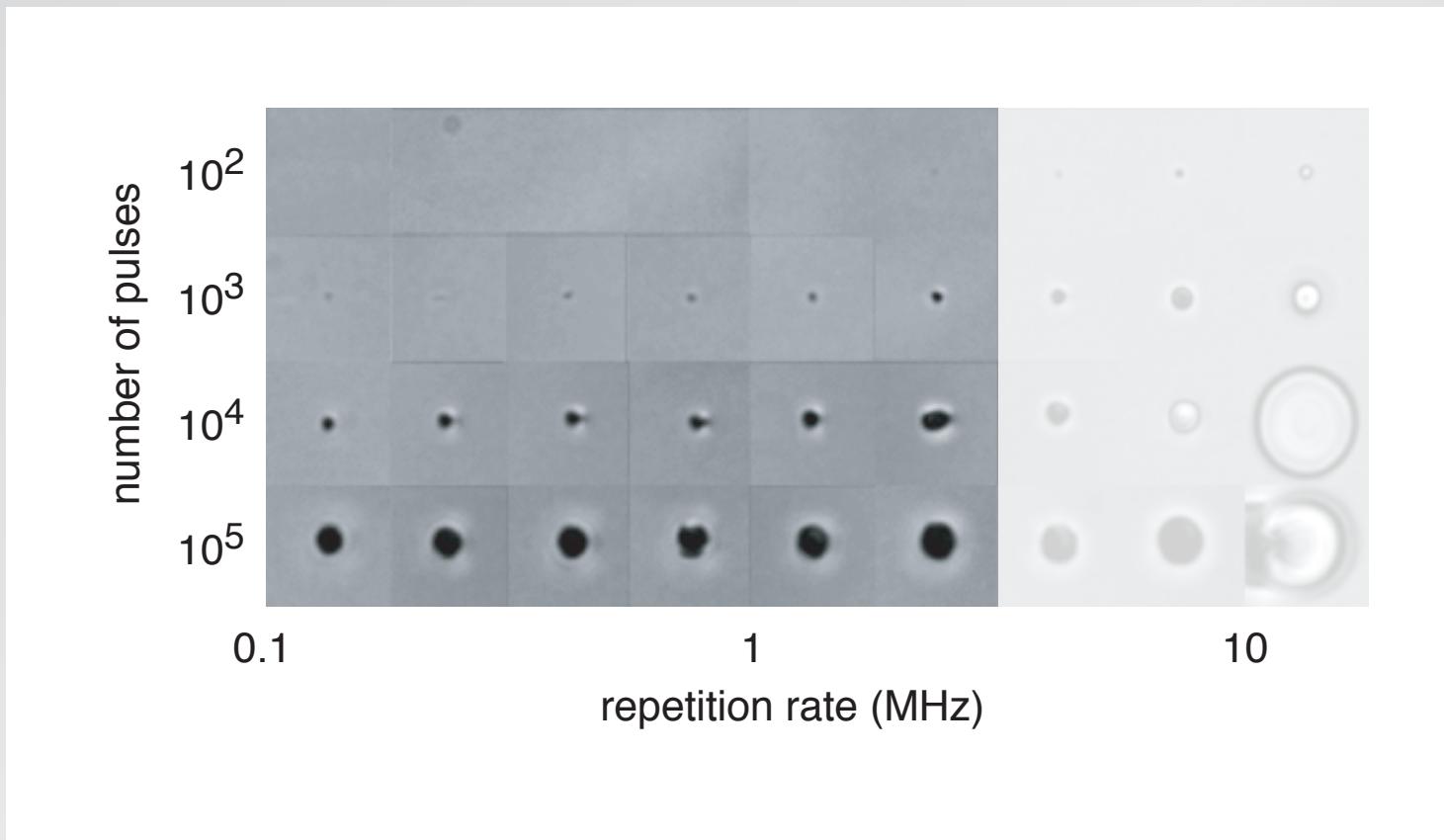
repetition-rate dependence



As_2S_3 , 100 fs, 7 nJ

Low-energy machining

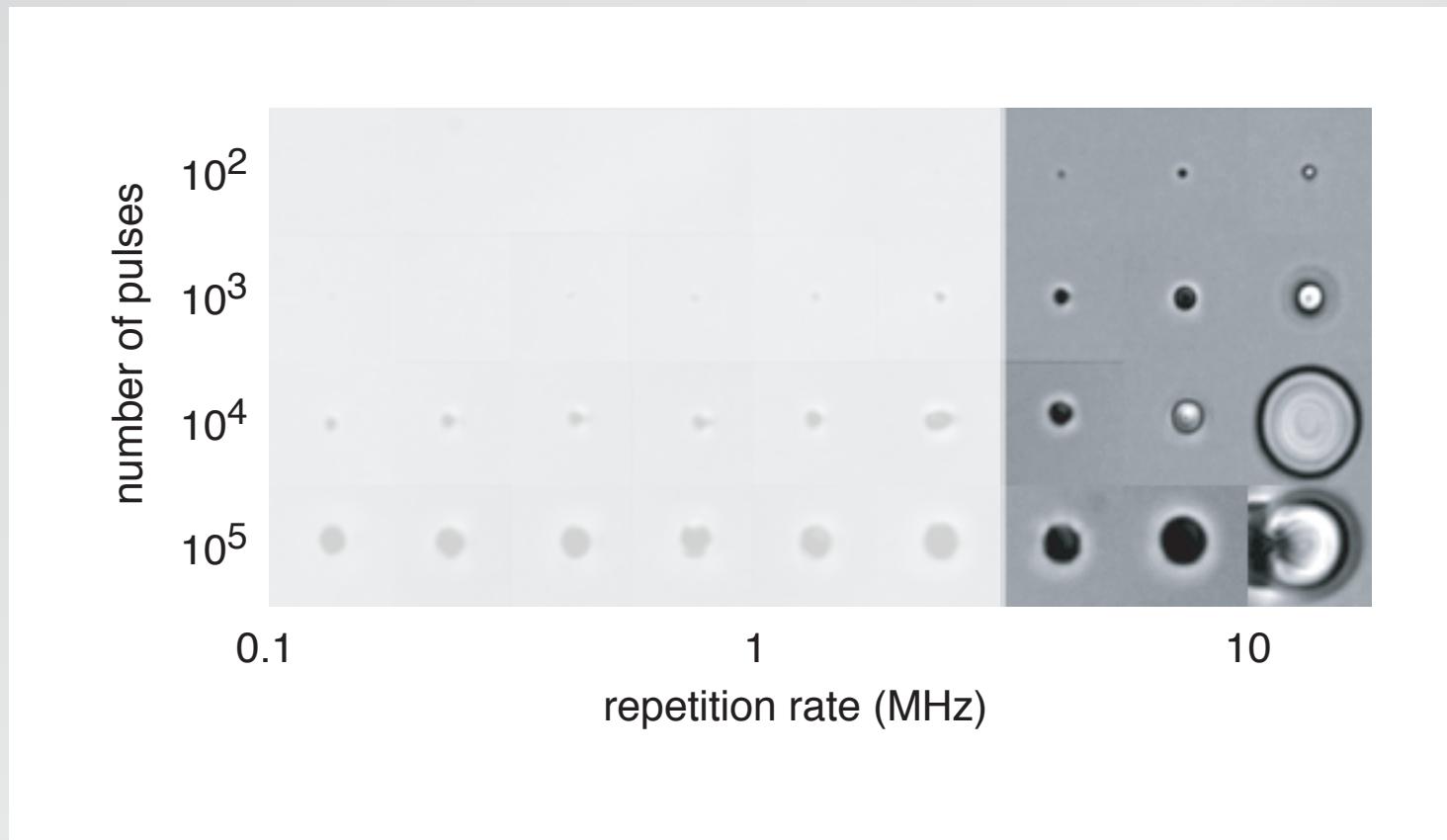
repetition-rate dependence



As_2S_3 , 100 fs, 7 nJ

Low-energy machining

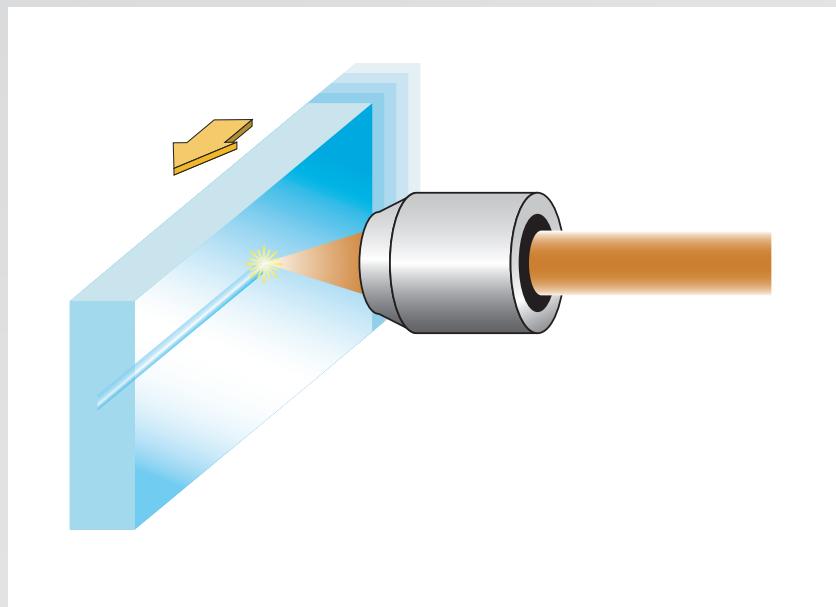
repetition-rate dependence



As_2S_3 , 100 fs, 7 nJ

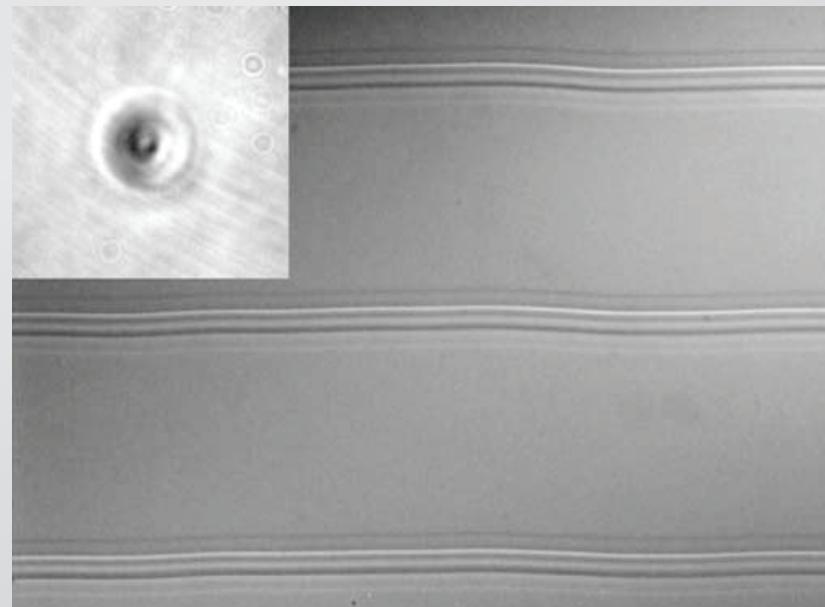
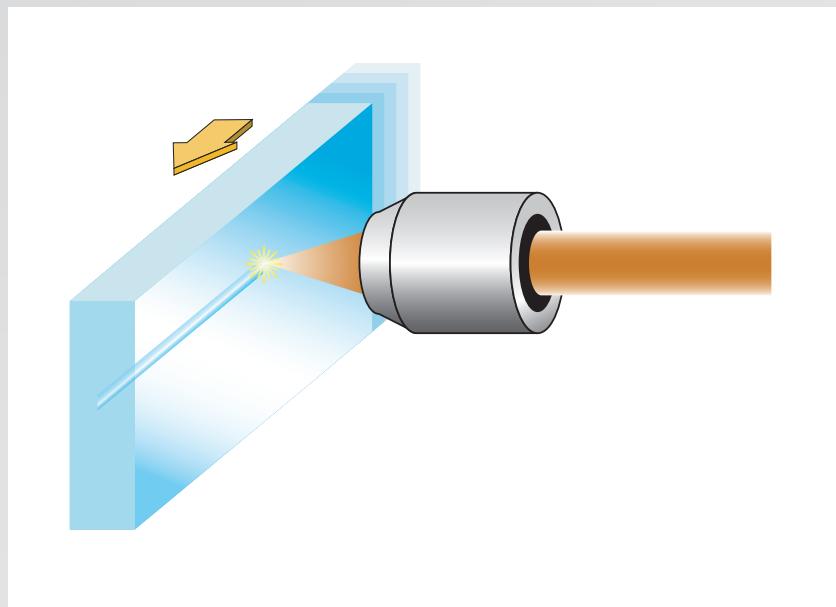
Low-energy machining

waveguide micromachining



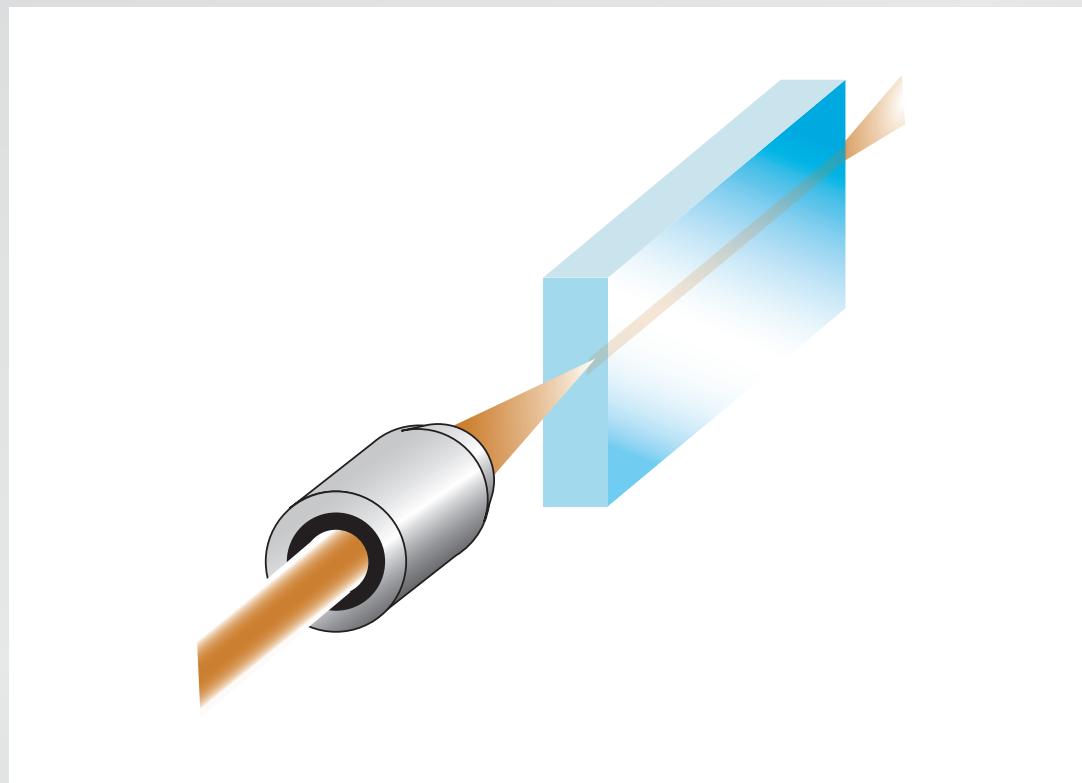
Low-energy machining

waveguide micromachining



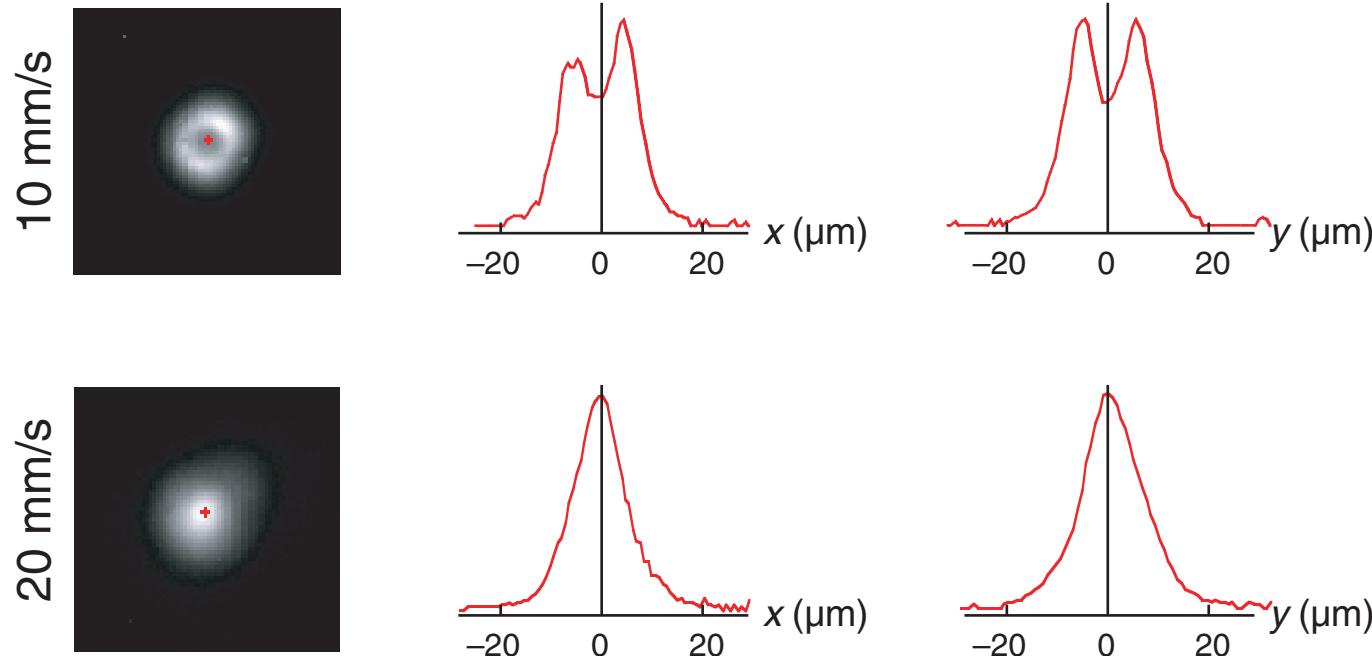
Low-energy machining

structures guide light



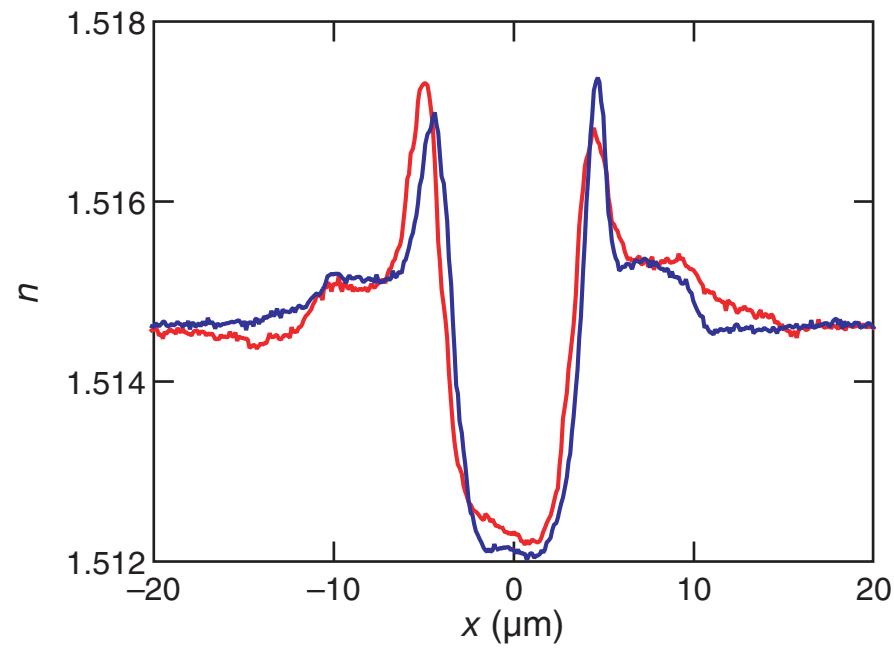
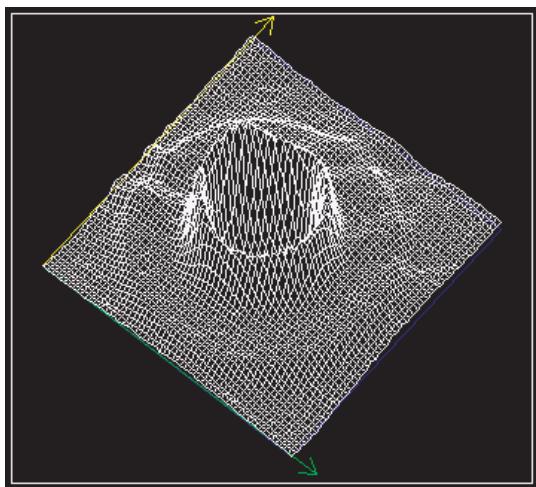
Low-energy machining

near-field profiles



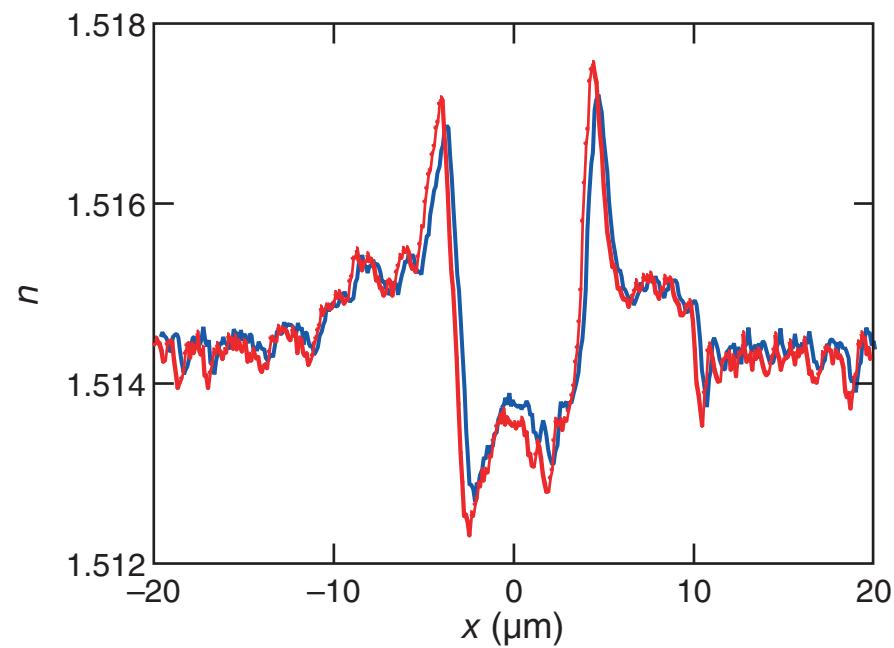
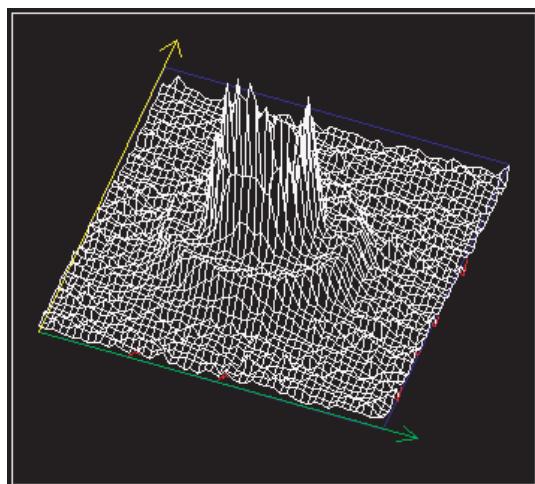
Low-energy machining

index profile at 2.5 mm/s



Low-energy machining

index profile at 10 mm/s



Outline

- femtosecond micromachining
- low-energy machining
- applications

Applications

loss measurement



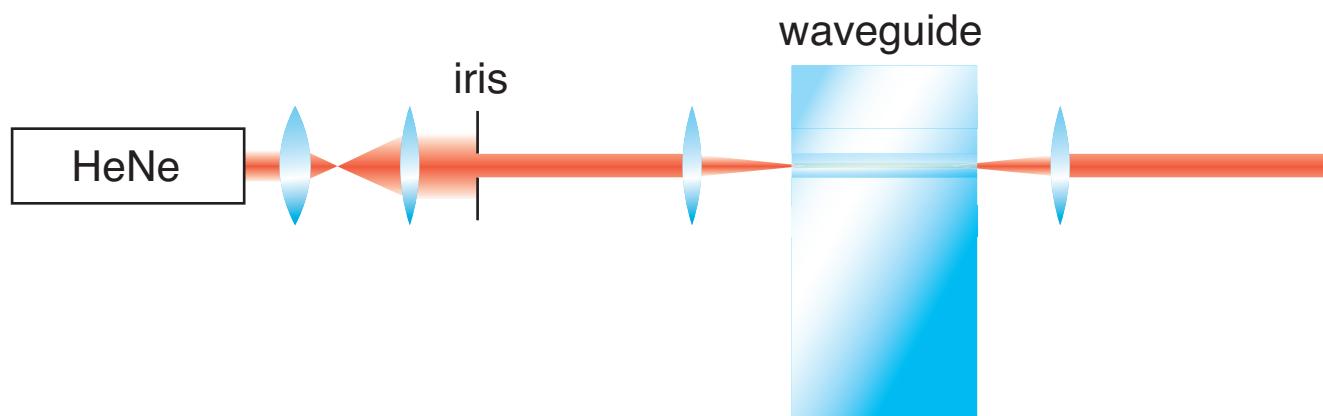
Applications

loss measurement



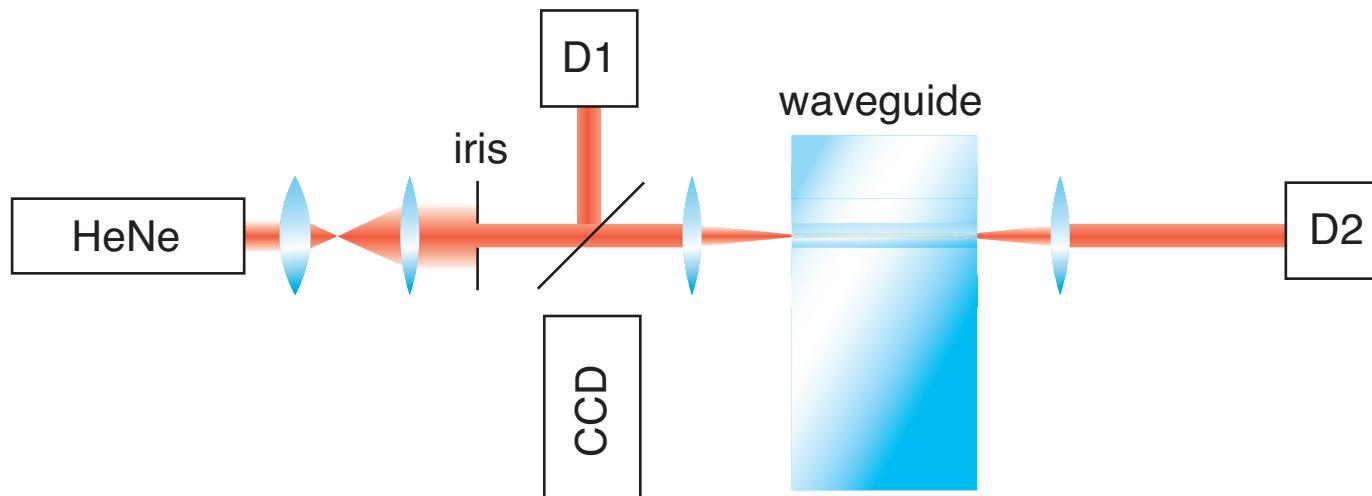
Applications

loss measurement



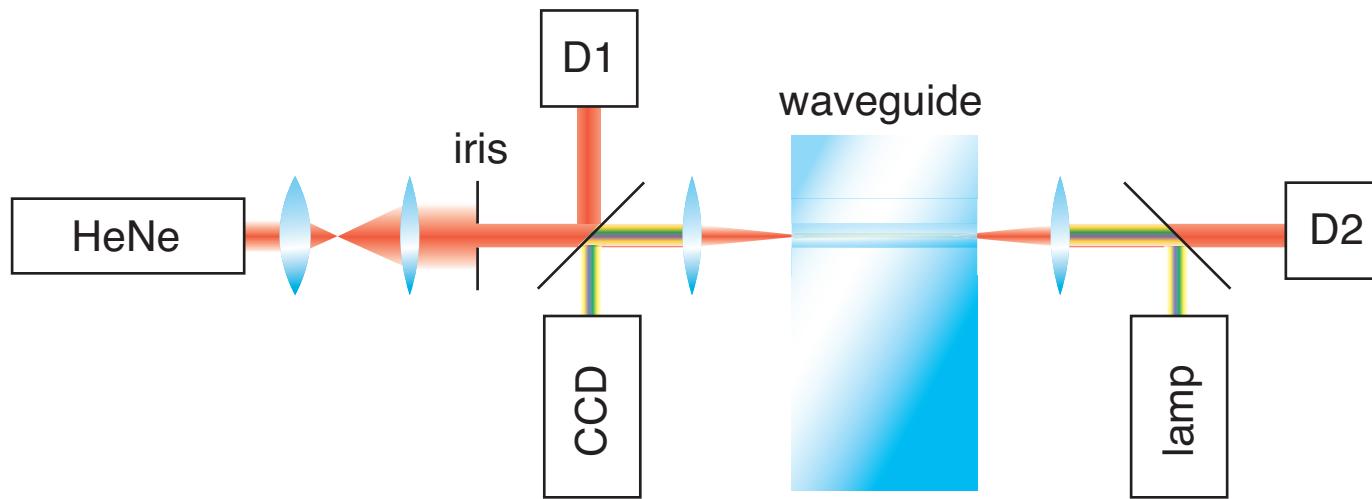
Applications

loss measurement



Applications

loss measurement

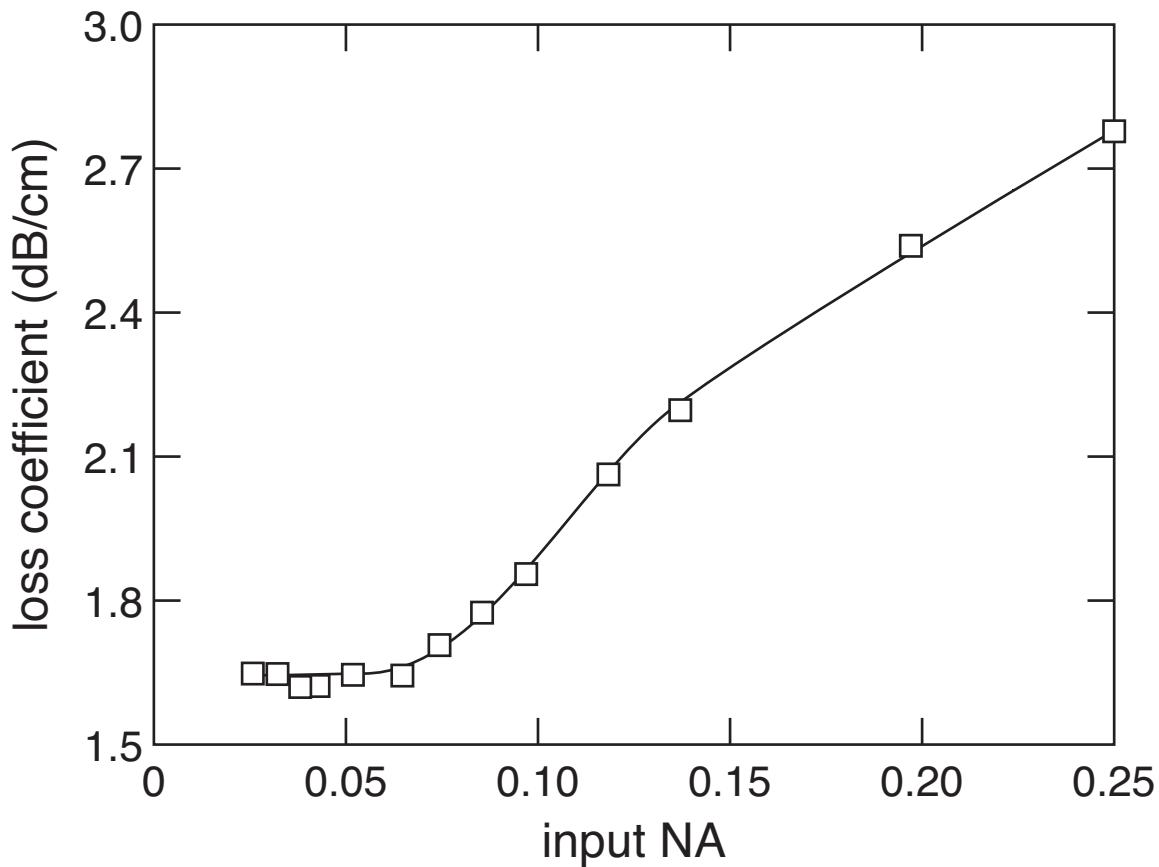


Applications

- at low NA: loss ≈ 2 dB/cm
- at 1550 nm: loss < 0.5 dB/cm
- no polarization dependence
- losses mostly due to scattering

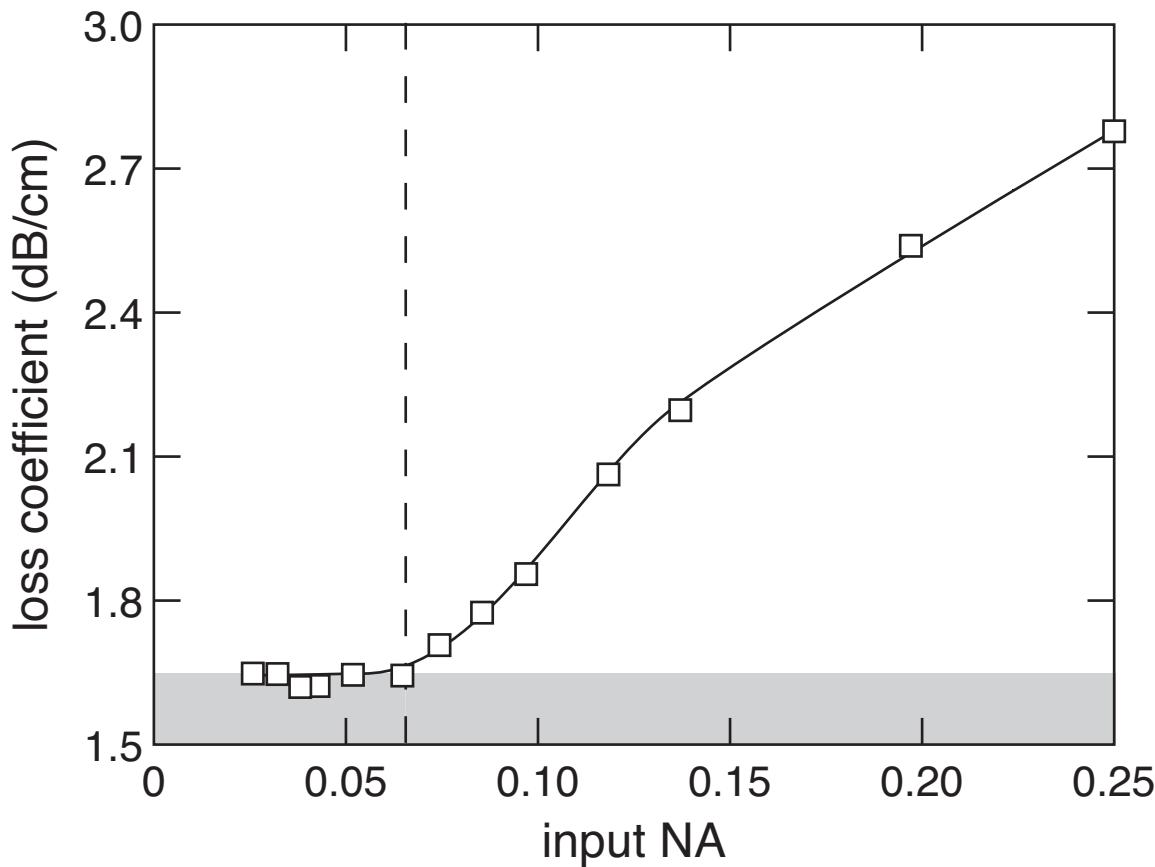
Applications

numerical aperture of waveguide



Applications

numerical aperture of waveguide



Applications

numerical aperture of waveguide

$$NA = \sqrt{n_1^2 - n_2^2} = 0.065$$

Applications

numerical aperture of waveguide

$$NA = \sqrt{n_1^2 - n_2^2} = 0.065$$

$$n_2 = 1.52$$

Applications

numerical aperture of waveguide

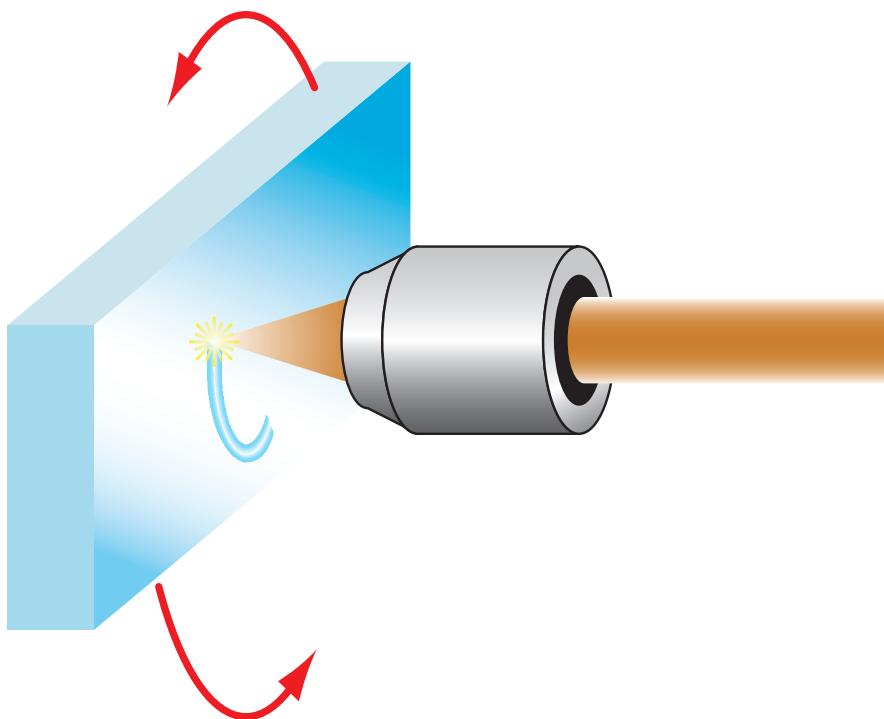
$$NA = \sqrt{n_1^2 - n_2^2} = 0.065$$

$$n_2 = 1.52$$

$$\Delta n = 1.4 \times 10^{-3}$$

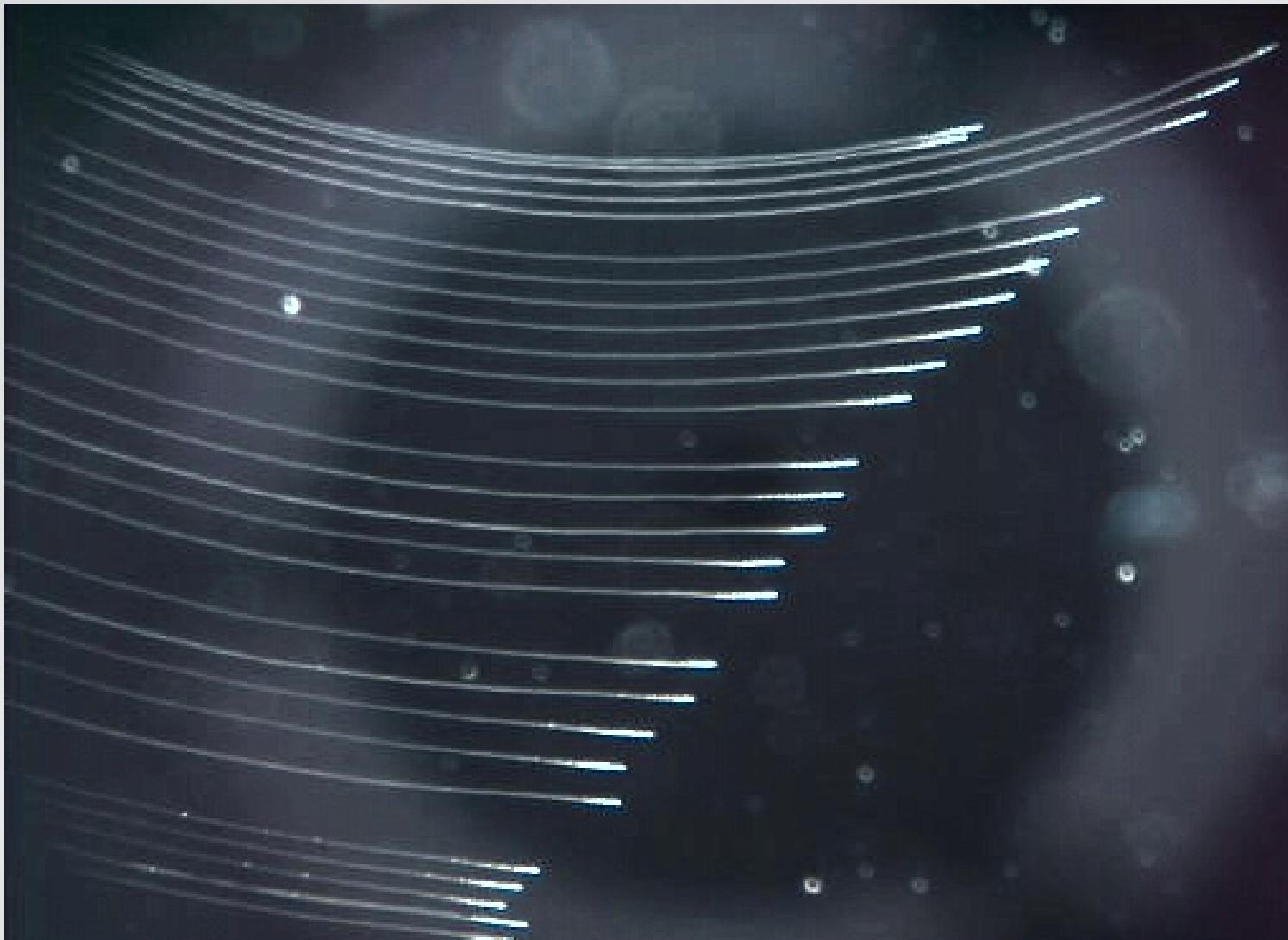
Applications

curved waveguides



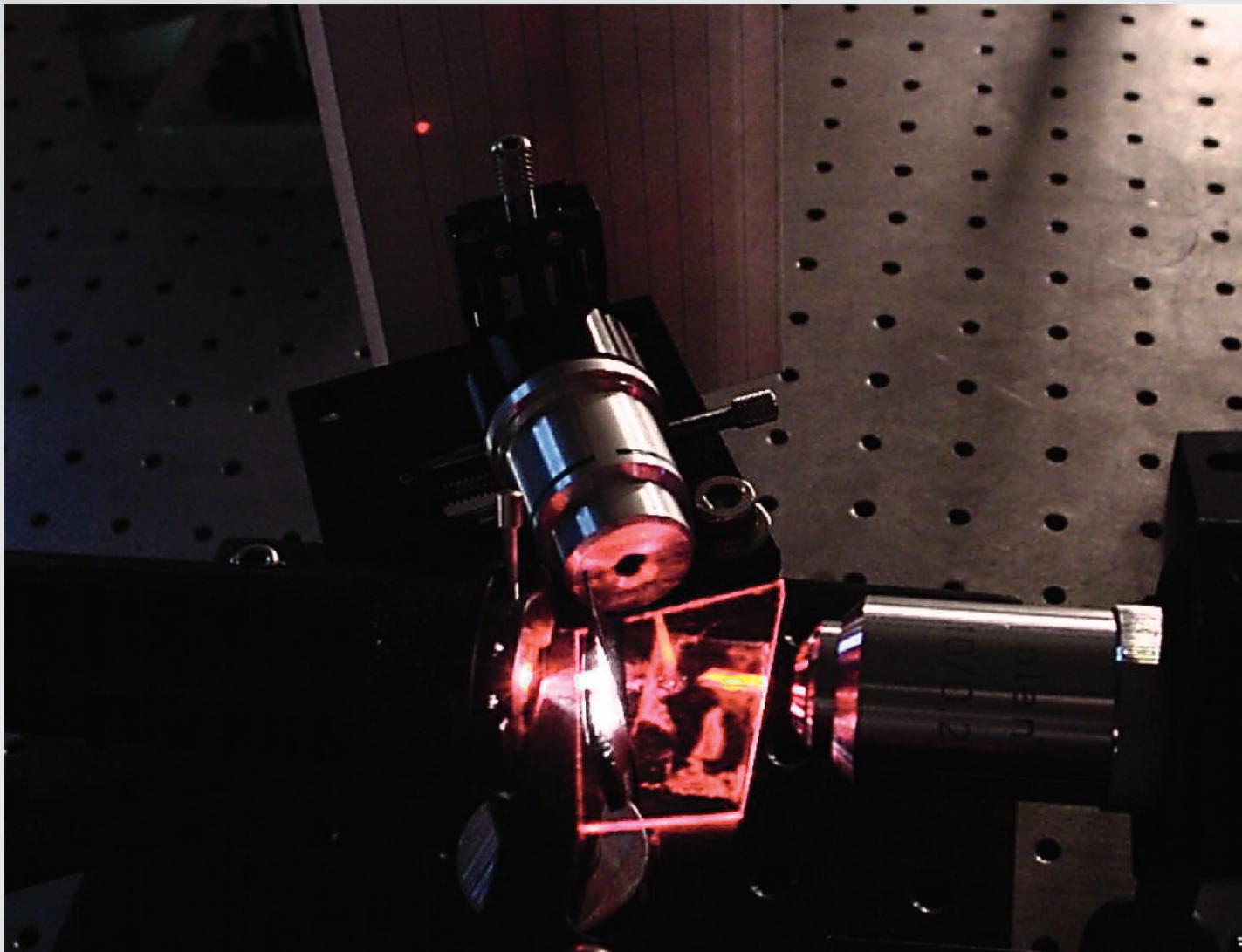
Applications

curved waveguides



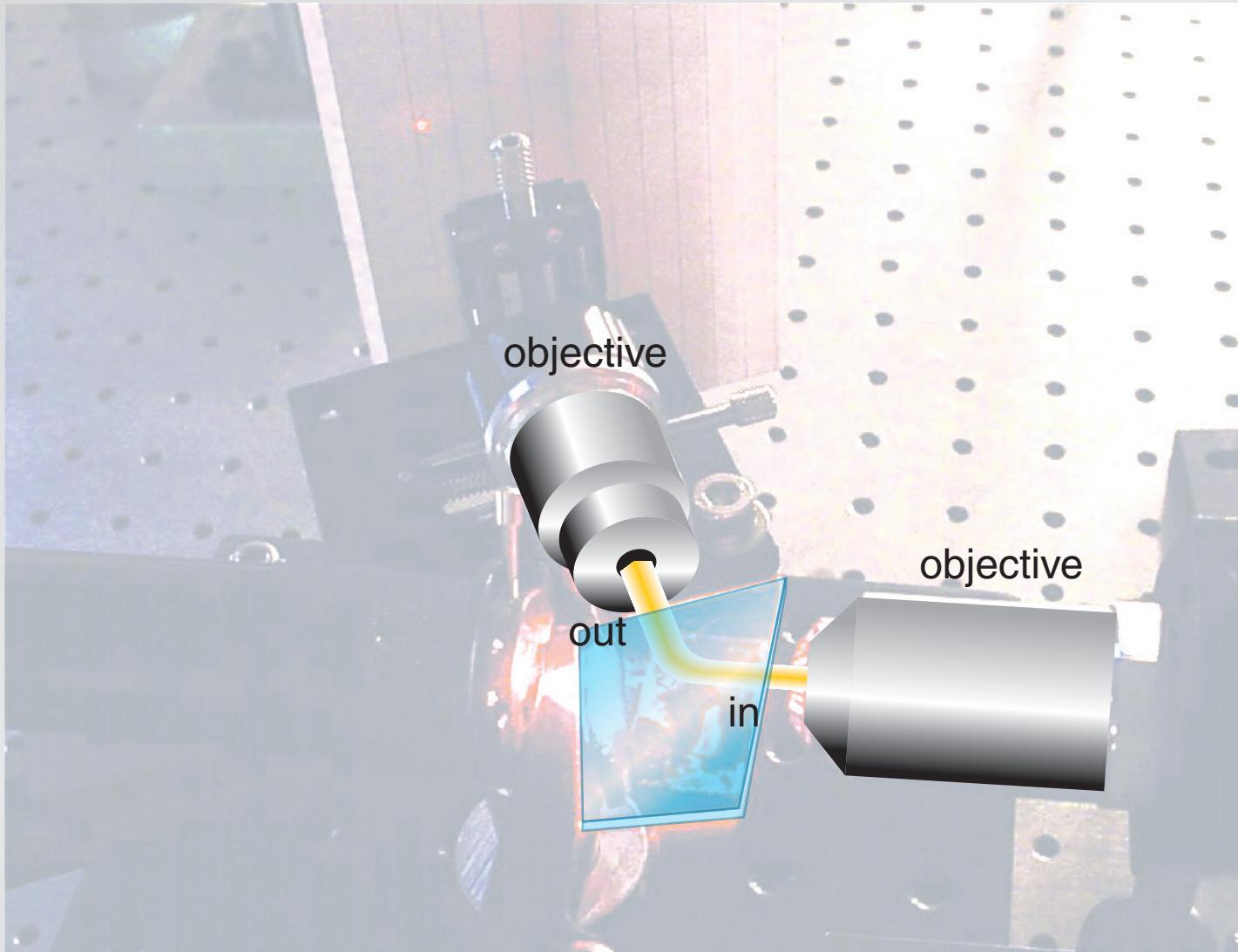
Applications

curved waveguides



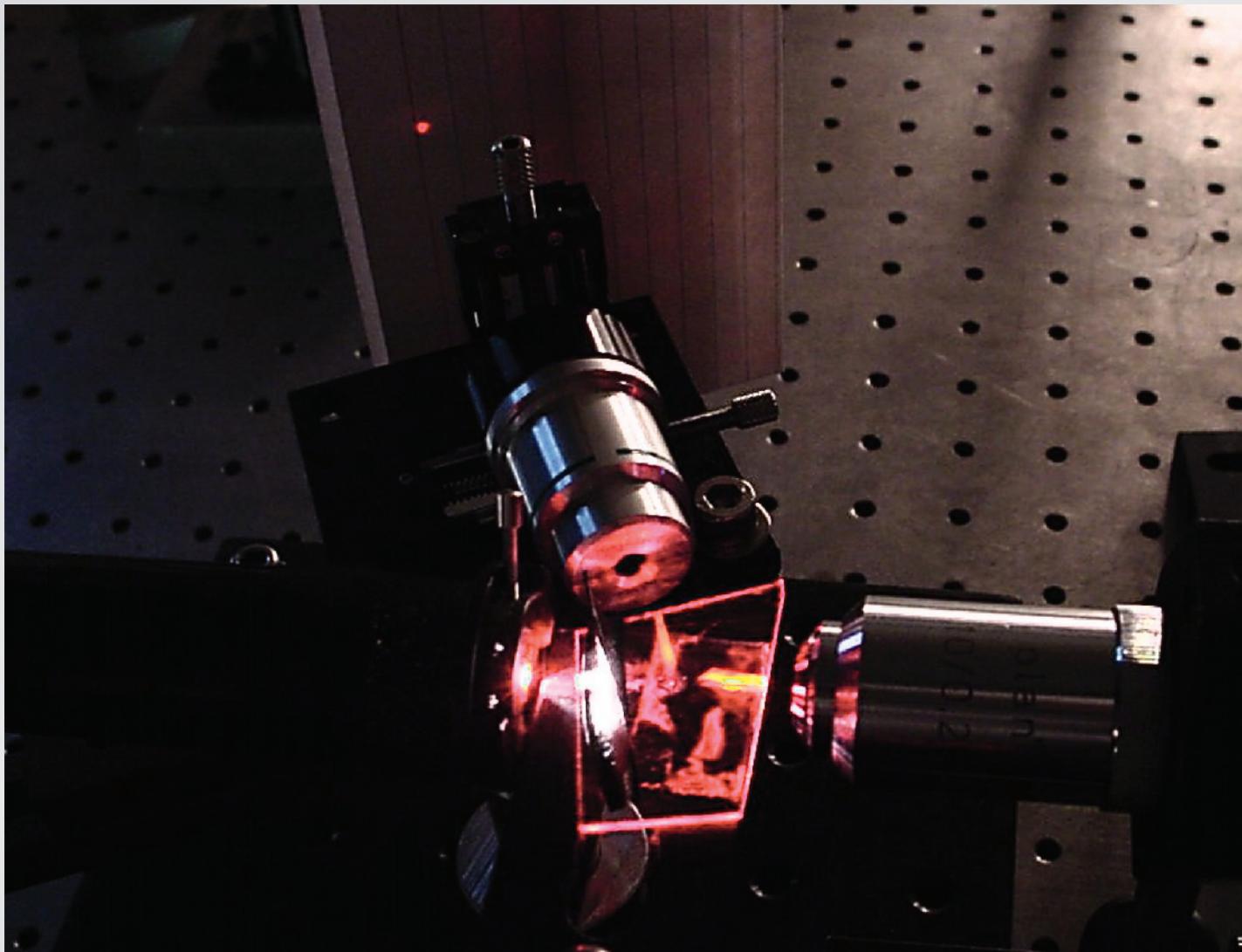
Applications

curved waveguides



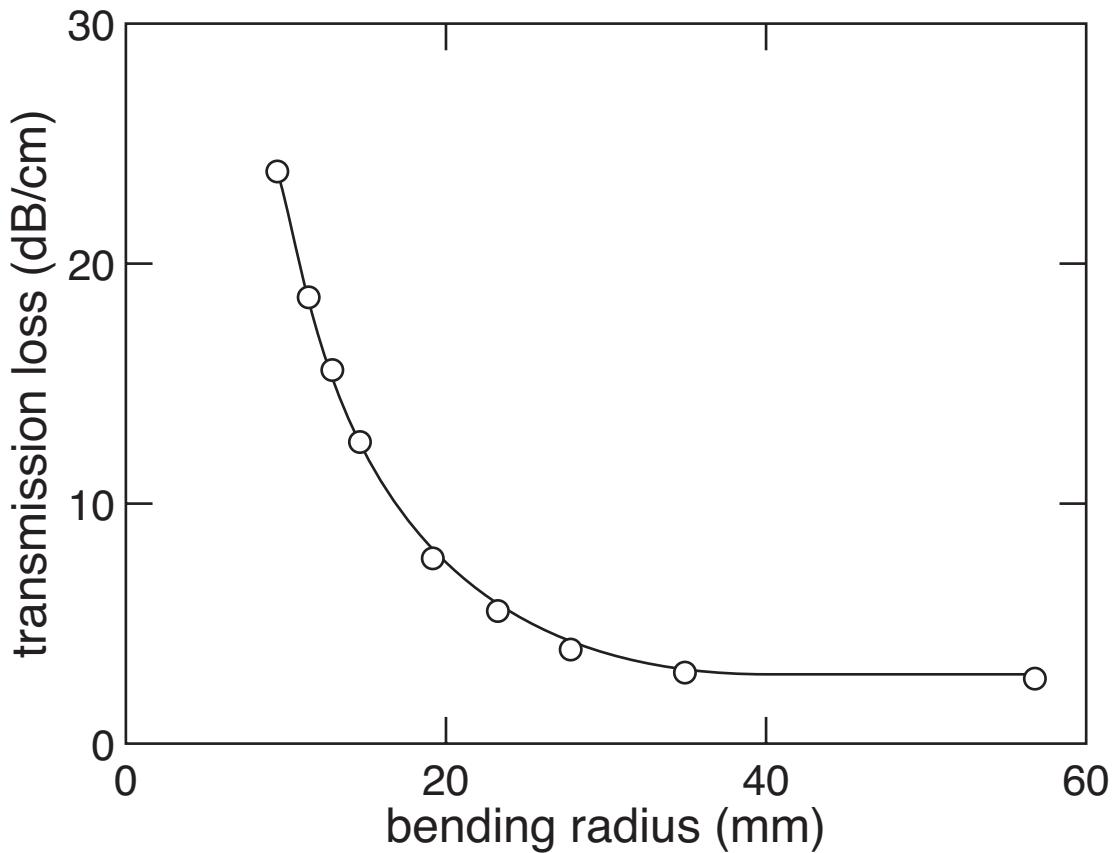
Applications

curved waveguides



Applications

curved waveguides



Applications

photonic fabrication techniques

	fs micromachining	other
loss (dB/cm)	< 3	0.1–3
bending radius	36 mm	30–40 mm
Δn	2×10^{-3}	$10^{-4} – 0.5$
3D integration	Y	N

Applications

photonic devices

3D splitter



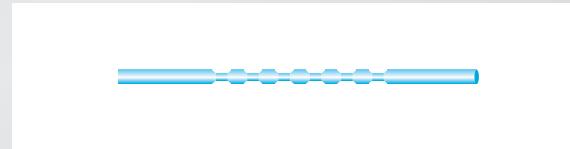
Applications

photonic devices

3D splitter

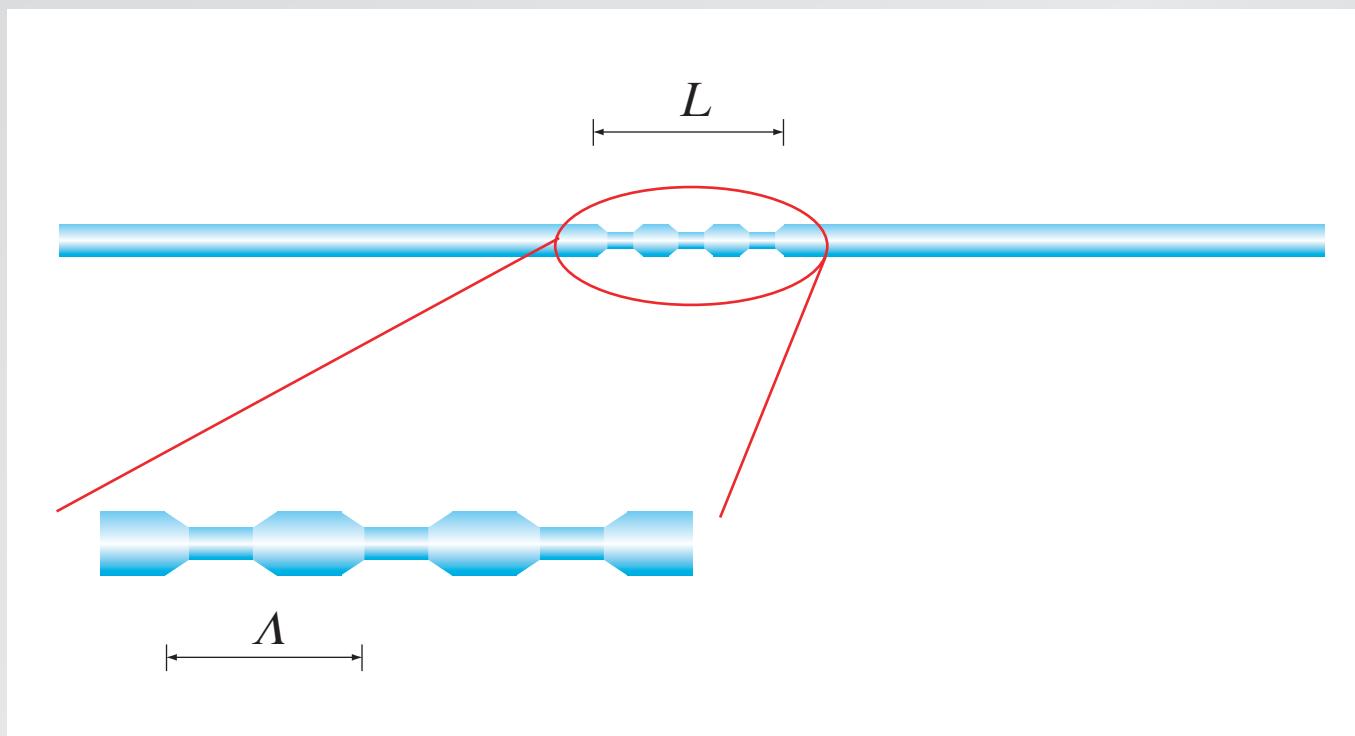


Bragg grating



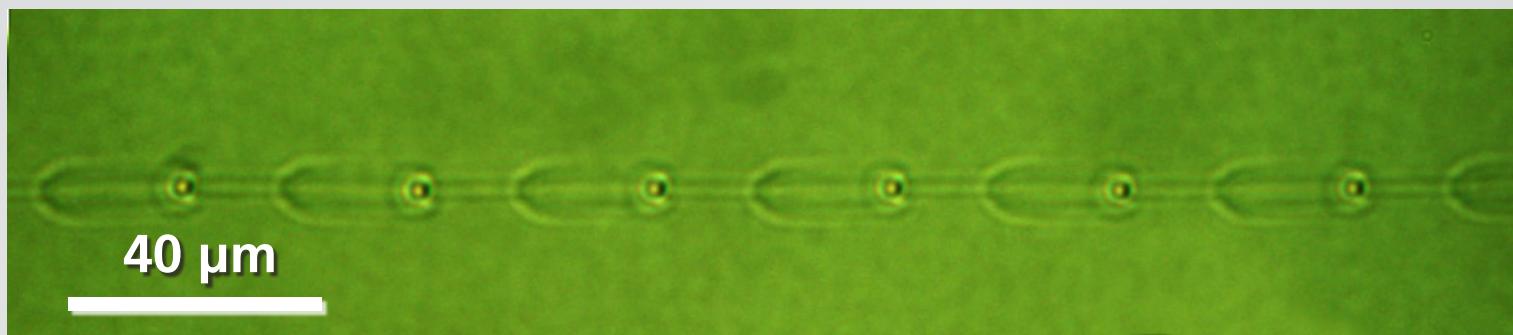
Applications

Bragg grating



Applications

Bragg grating



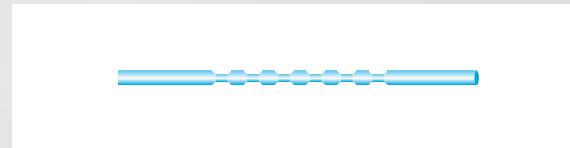
Applications

photonic devices

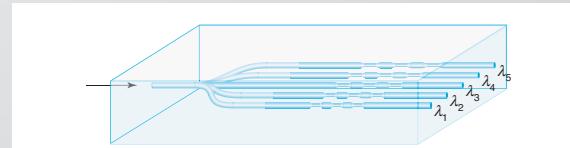
3D splitter



Bragg grating



demultiplexer



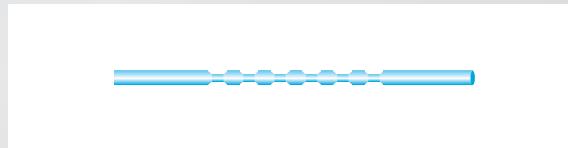
Applications

photonic devices

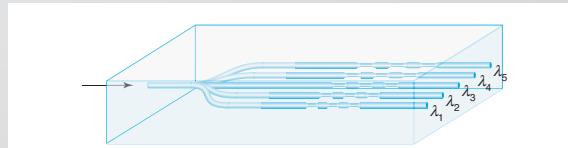
3D splitter



Bragg grating



demultiplexer



amplifier



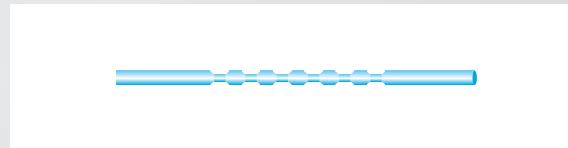
Applications

photonic devices

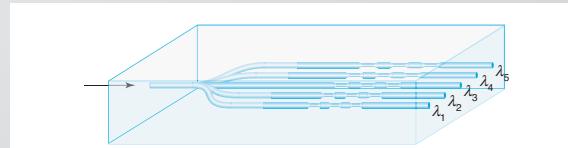
3D splitter



Bragg grating



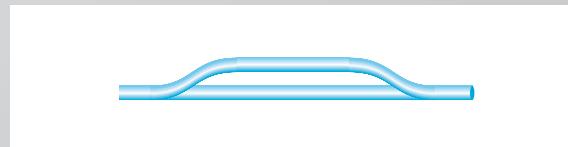
demultiplexer



amplifier

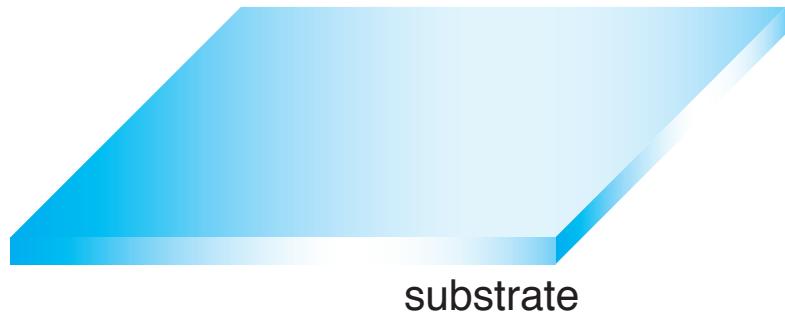


interferometer



Applications

all-optical sensor



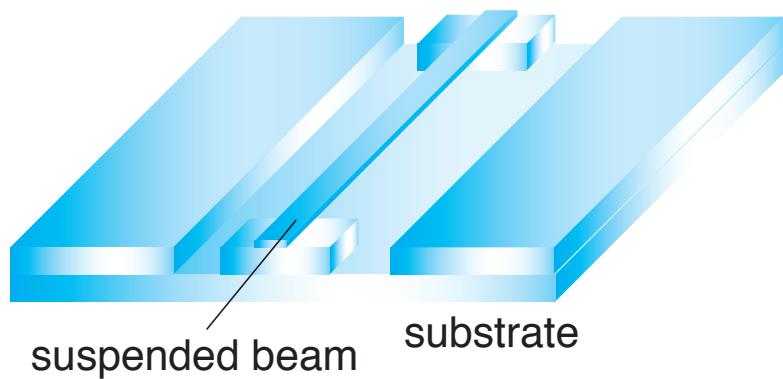
Applications

all-optical sensor



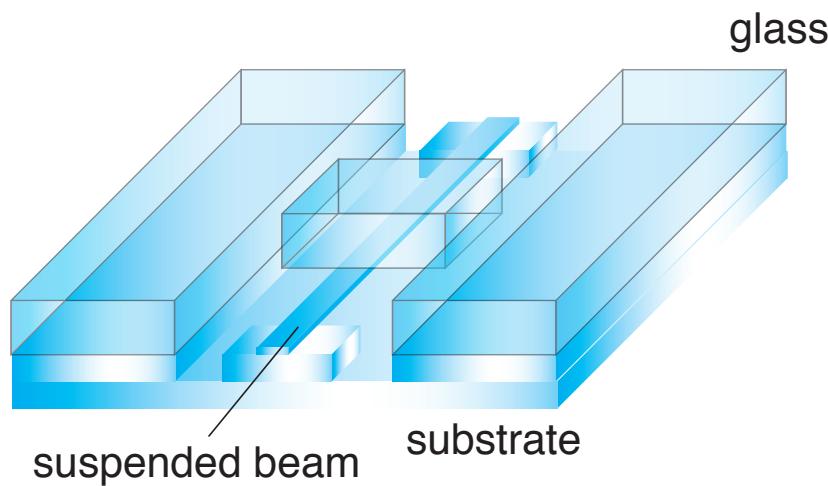
Applications

all-optical sensor



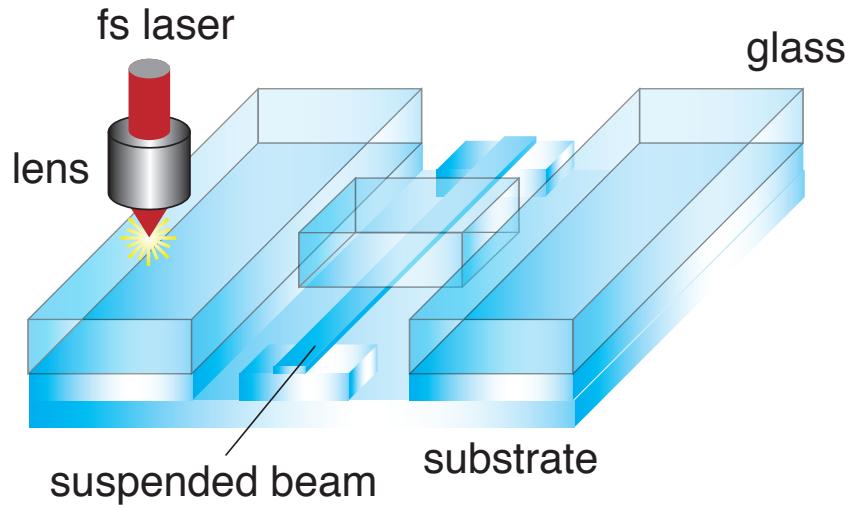
Applications

all-optical sensor



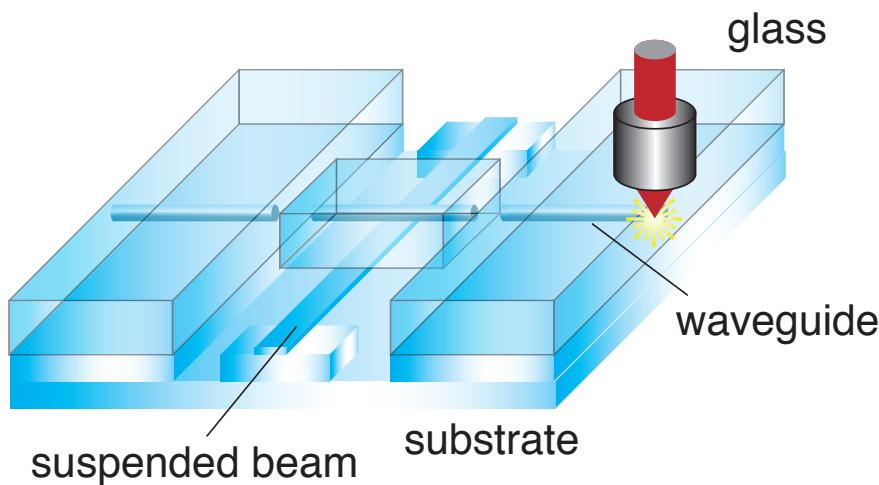
Applications

all-optical sensor



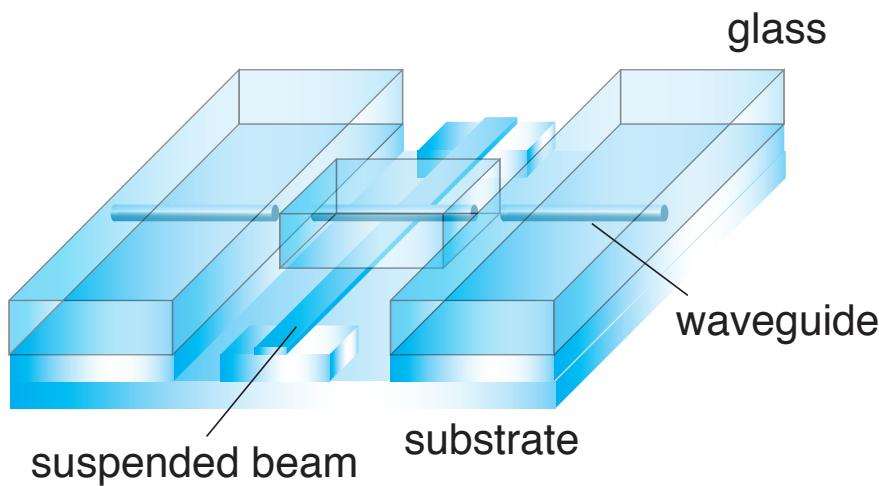
Applications

all-optical sensor



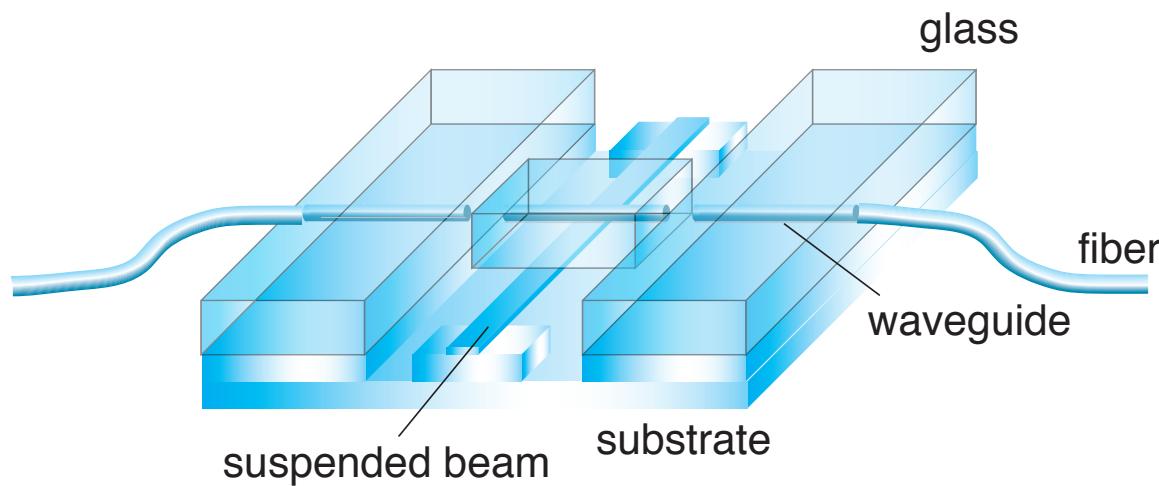
Applications

all-optical sensor

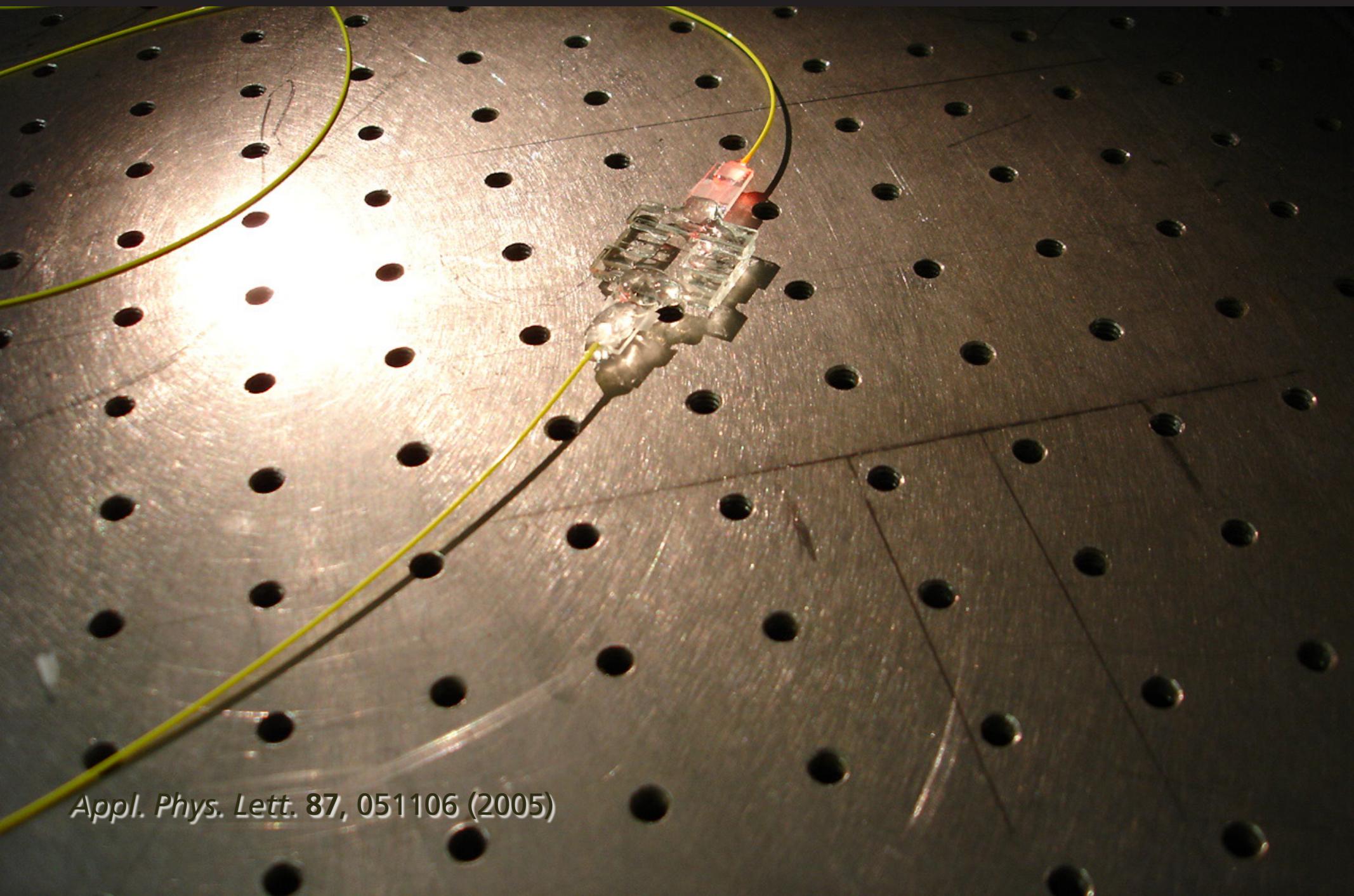


Applications

all-optical sensor



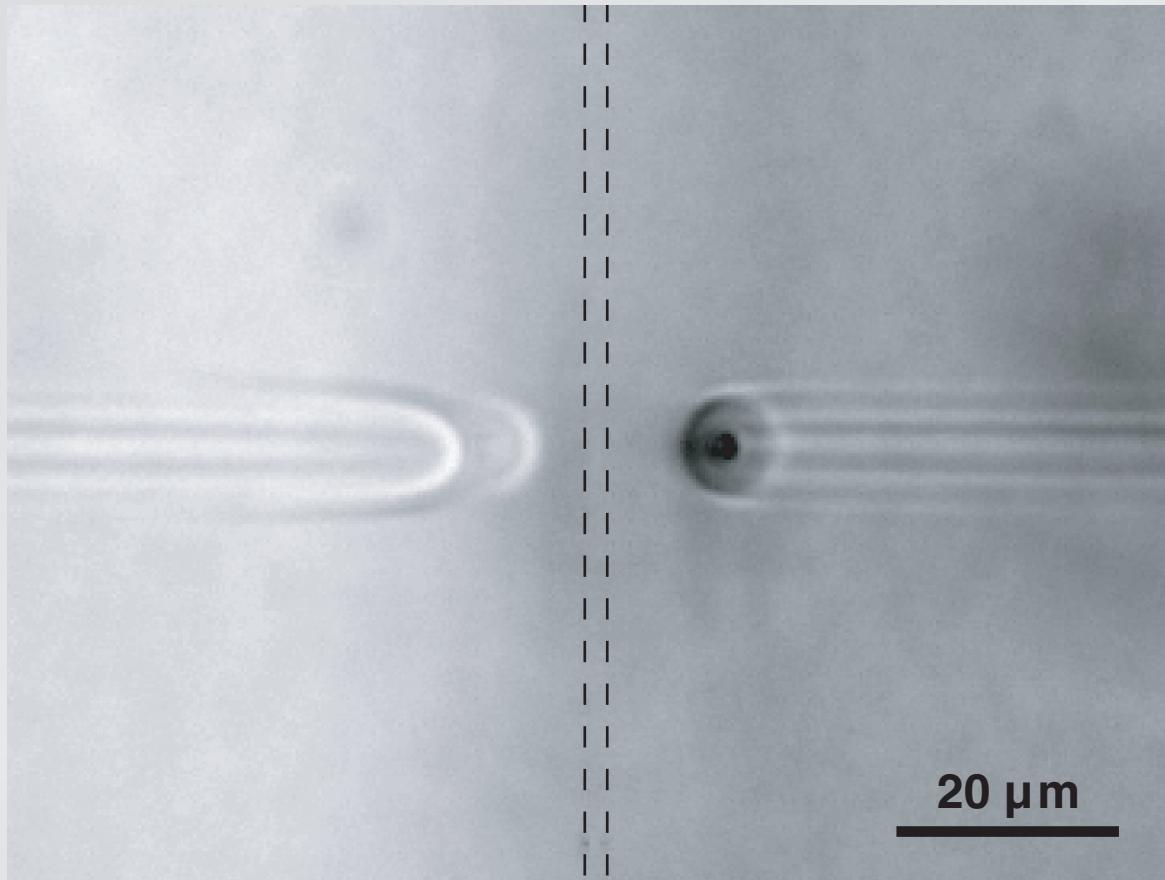
Applications



Appl. Phys. Lett. **87**, 051106 (2005)

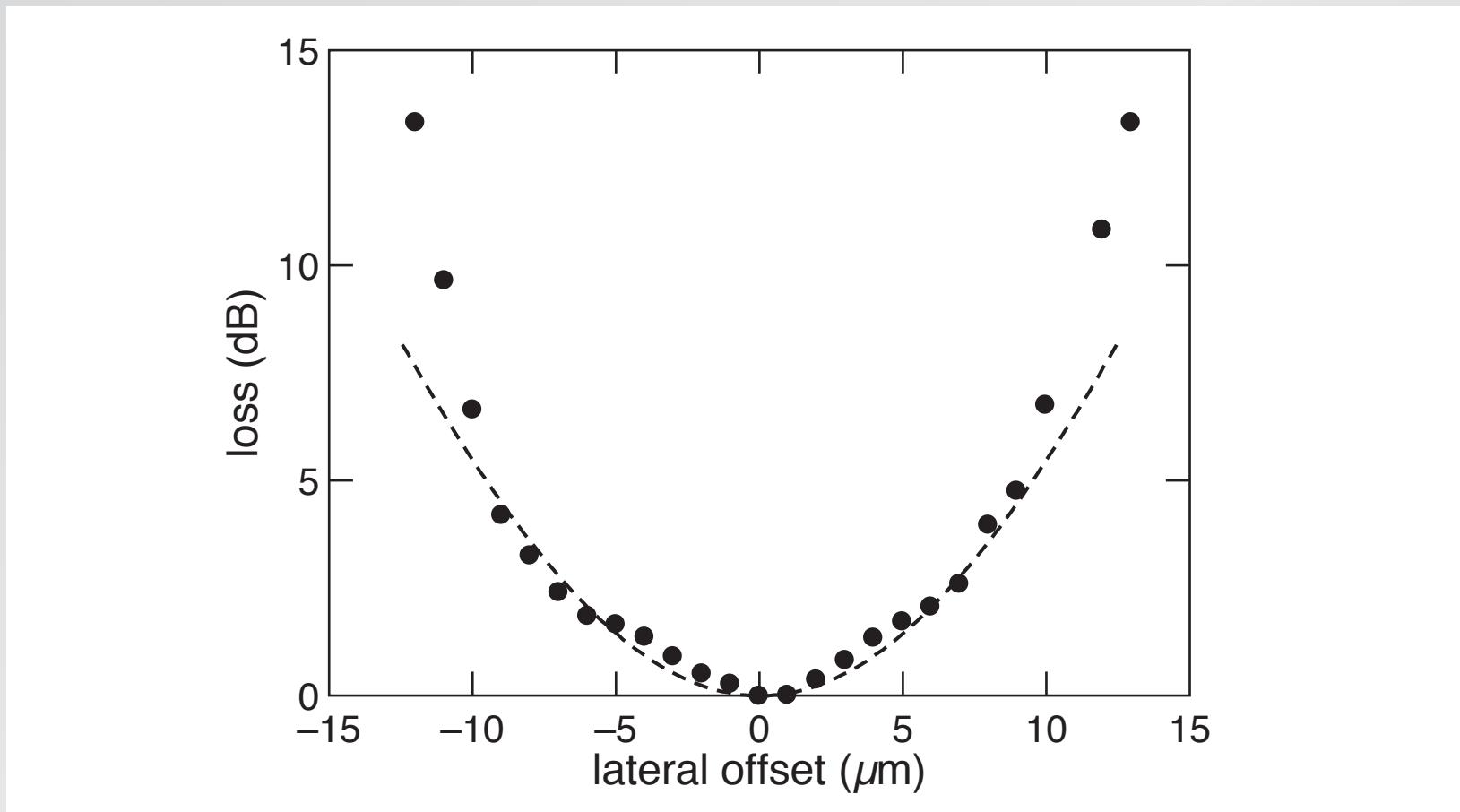
Applications

sensor gap



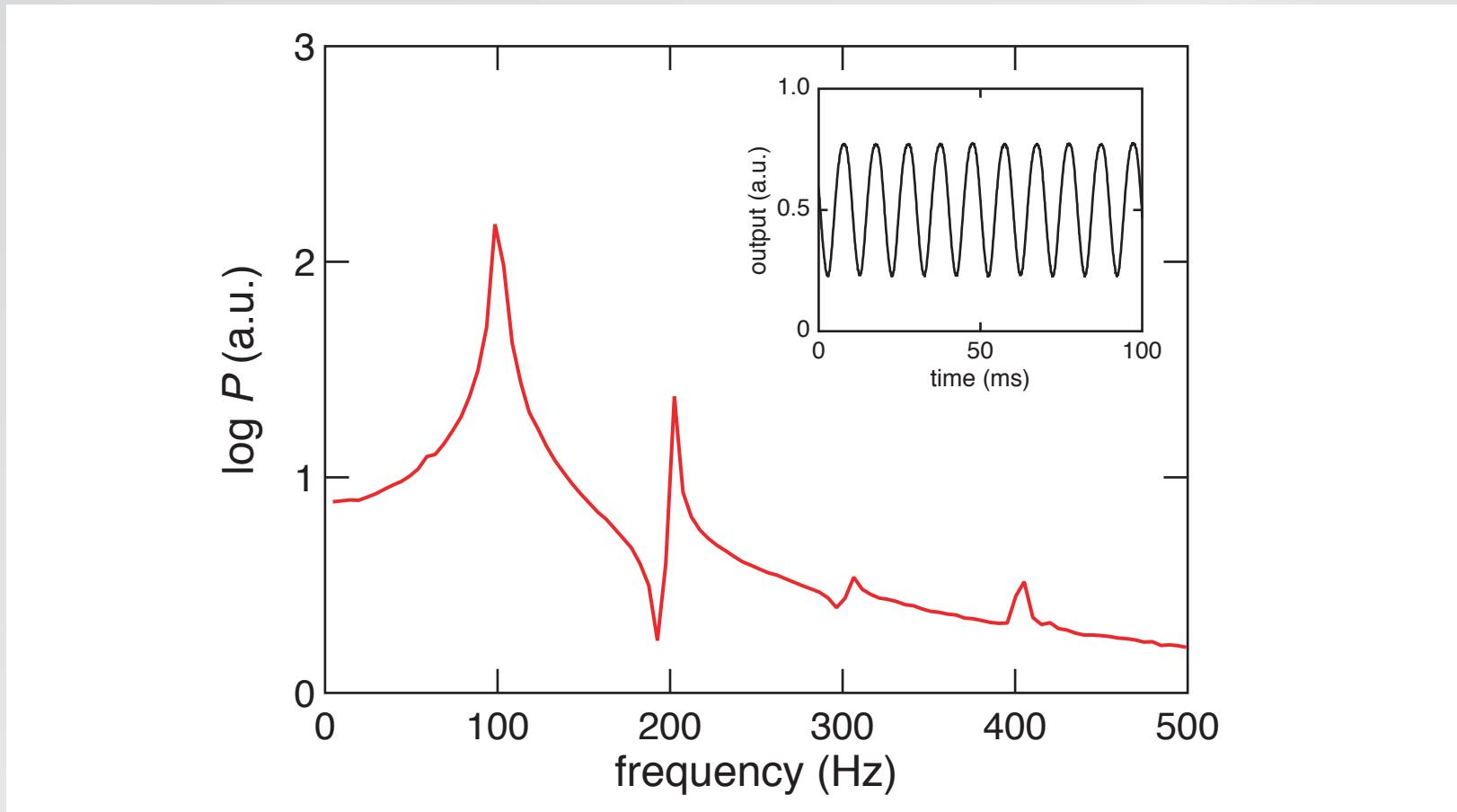
Applications

calibration



Applications

sensor response to 100 Hz acoustic wave



Applications

ideal tool for ablating (living) tissue

Applications

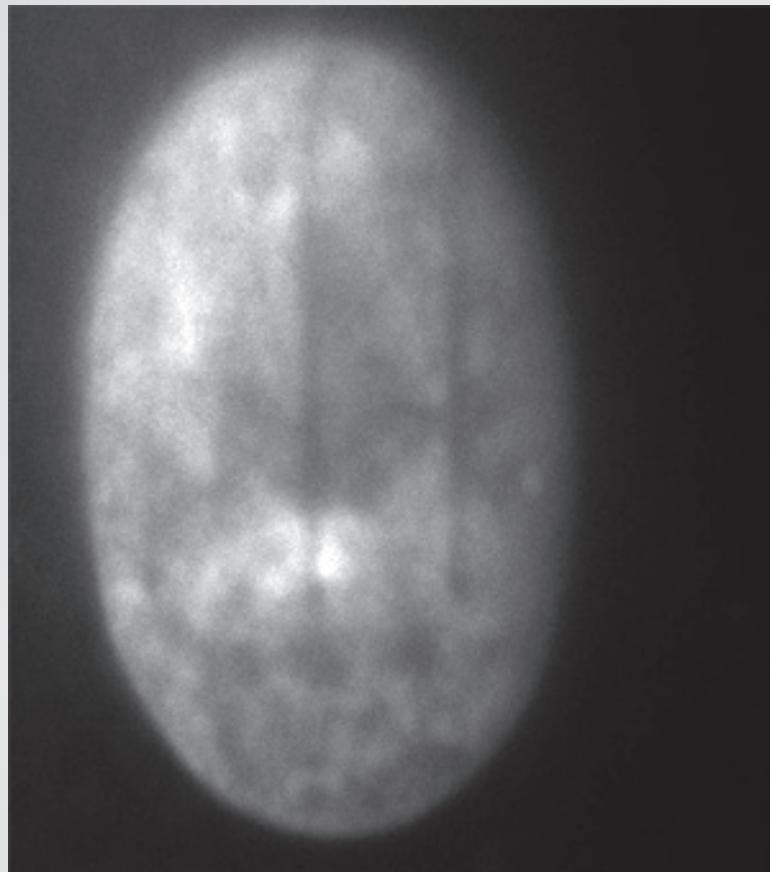
- standard biochemical tools: species selective
- fs laser “nanosurgery”: site specific

Applications

Q: can we ablate material on the subcellular scale?

Applications

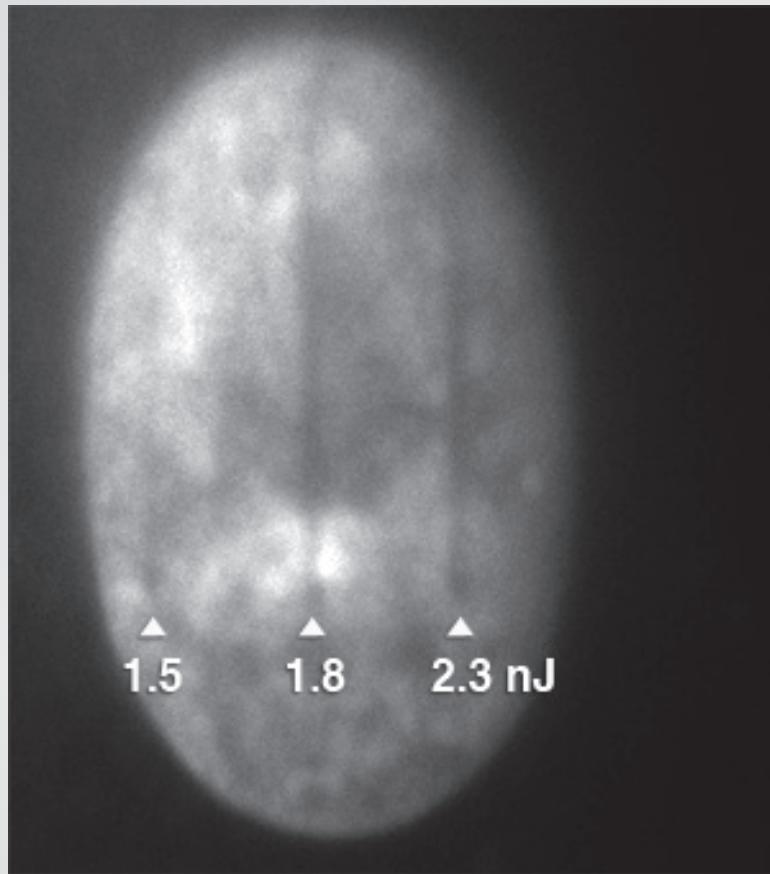
cuts in nucleus of fixed endothelial cell



fluorescence microscopy

Applications

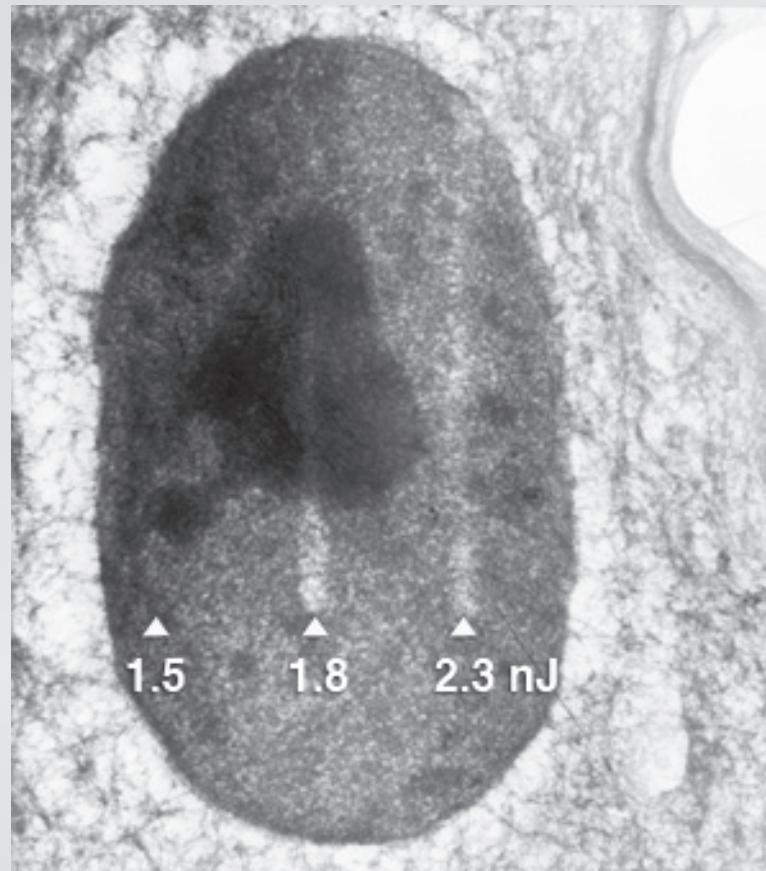
cuts in nucleus of fixed endothelial cell



fluorescence microscopy

Applications

cuts in nucleus of fixed endothelial cell

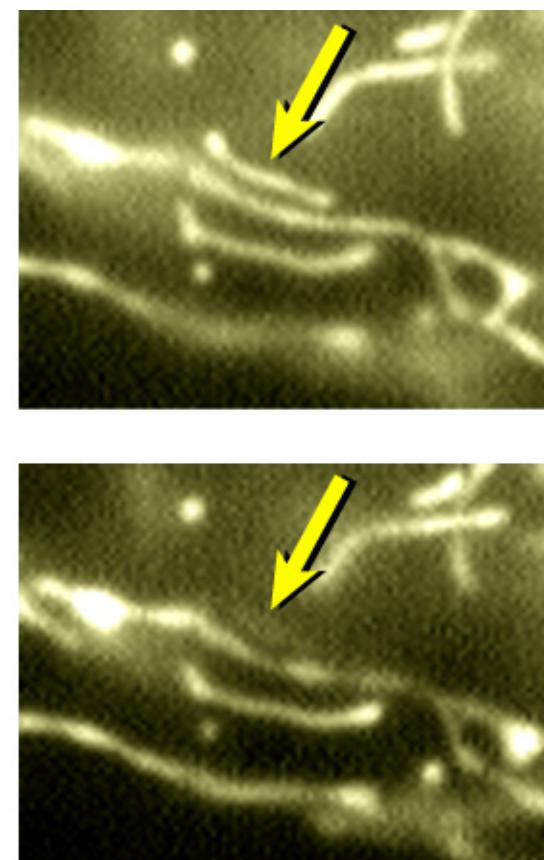
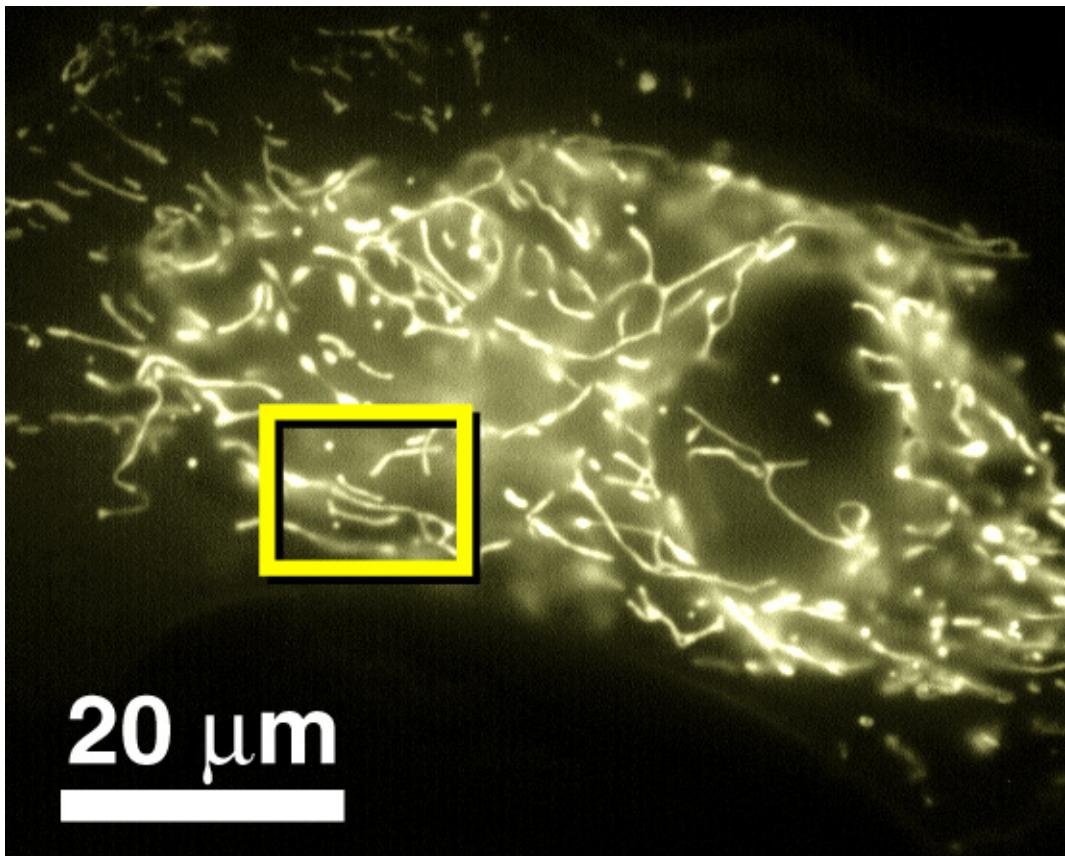


TEM image

Applications

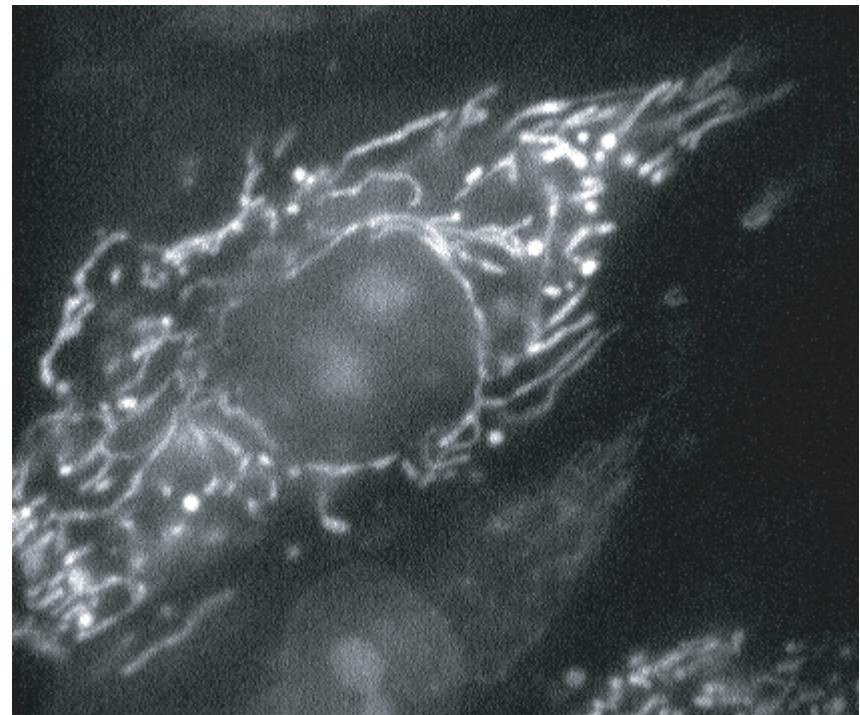
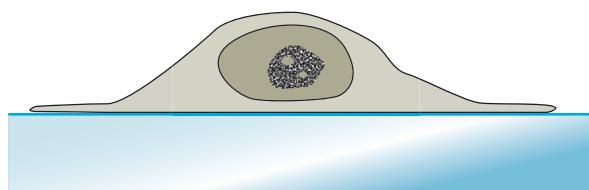
Q: subcellular surgery on live cells?

Applications



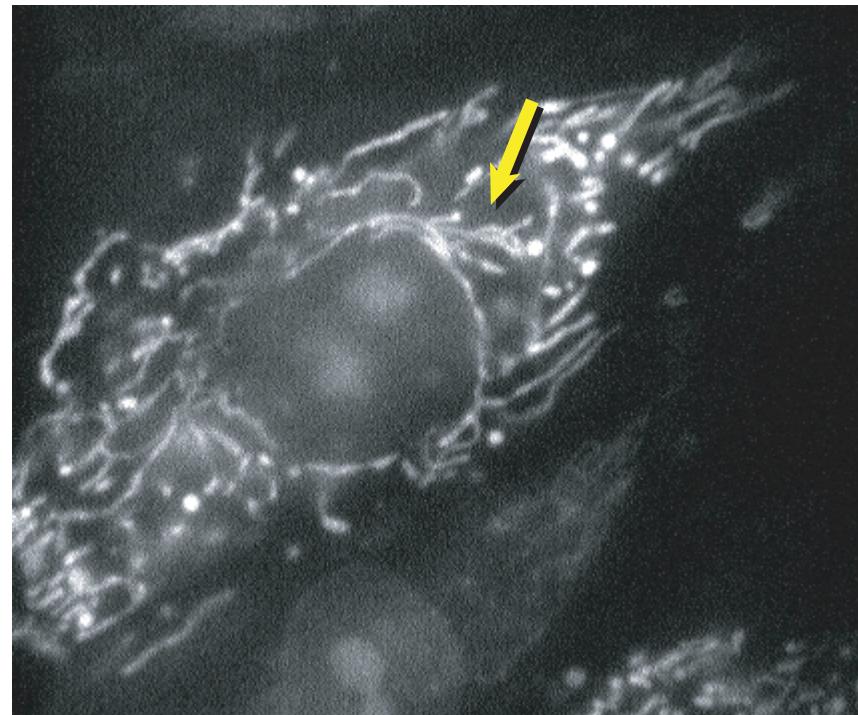
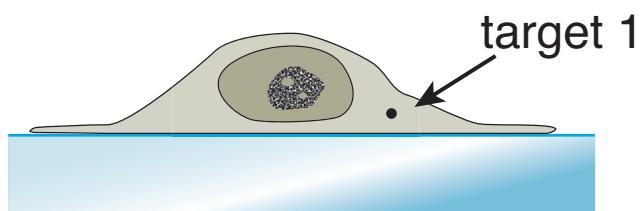
Applications

ethydium bromide test



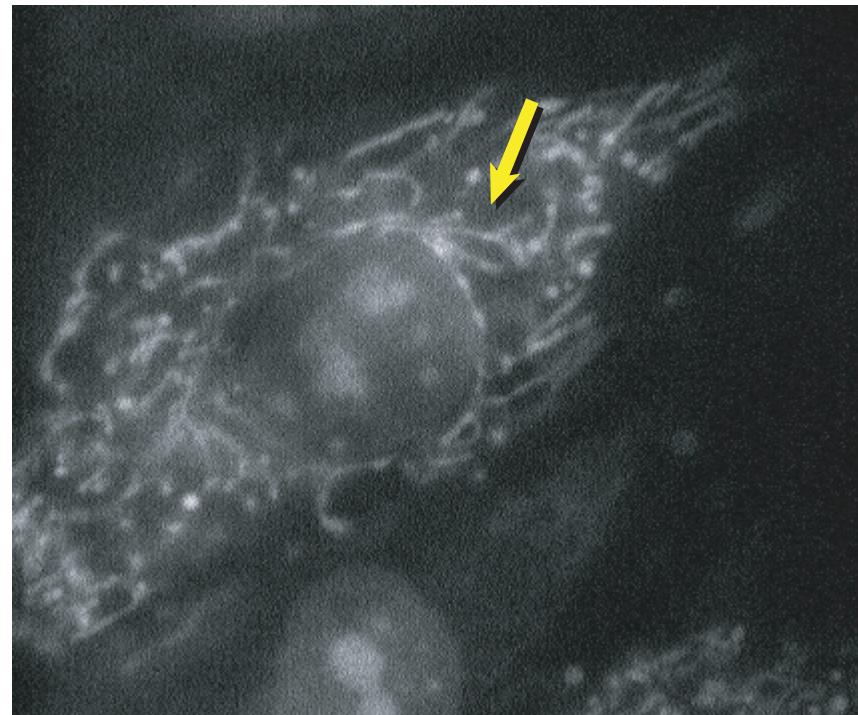
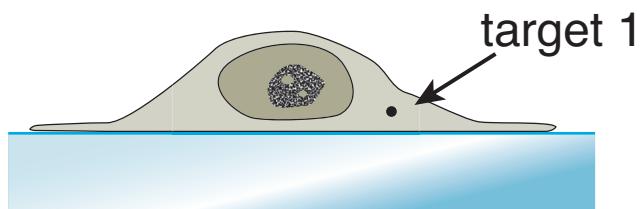
Applications

ethydium bromide test



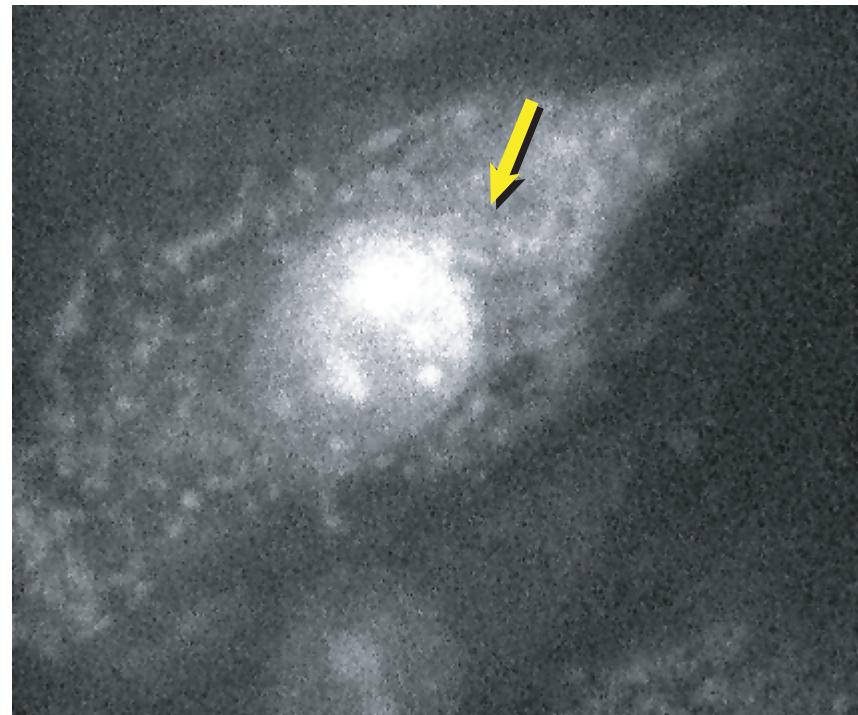
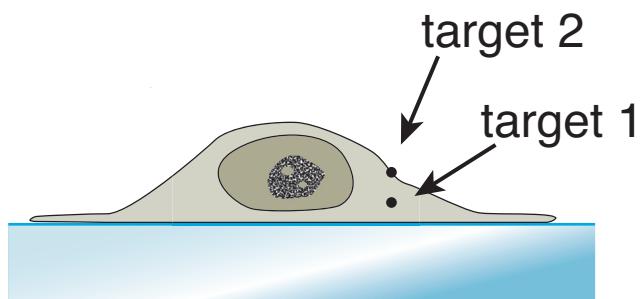
Applications ---

ethydium bromide test



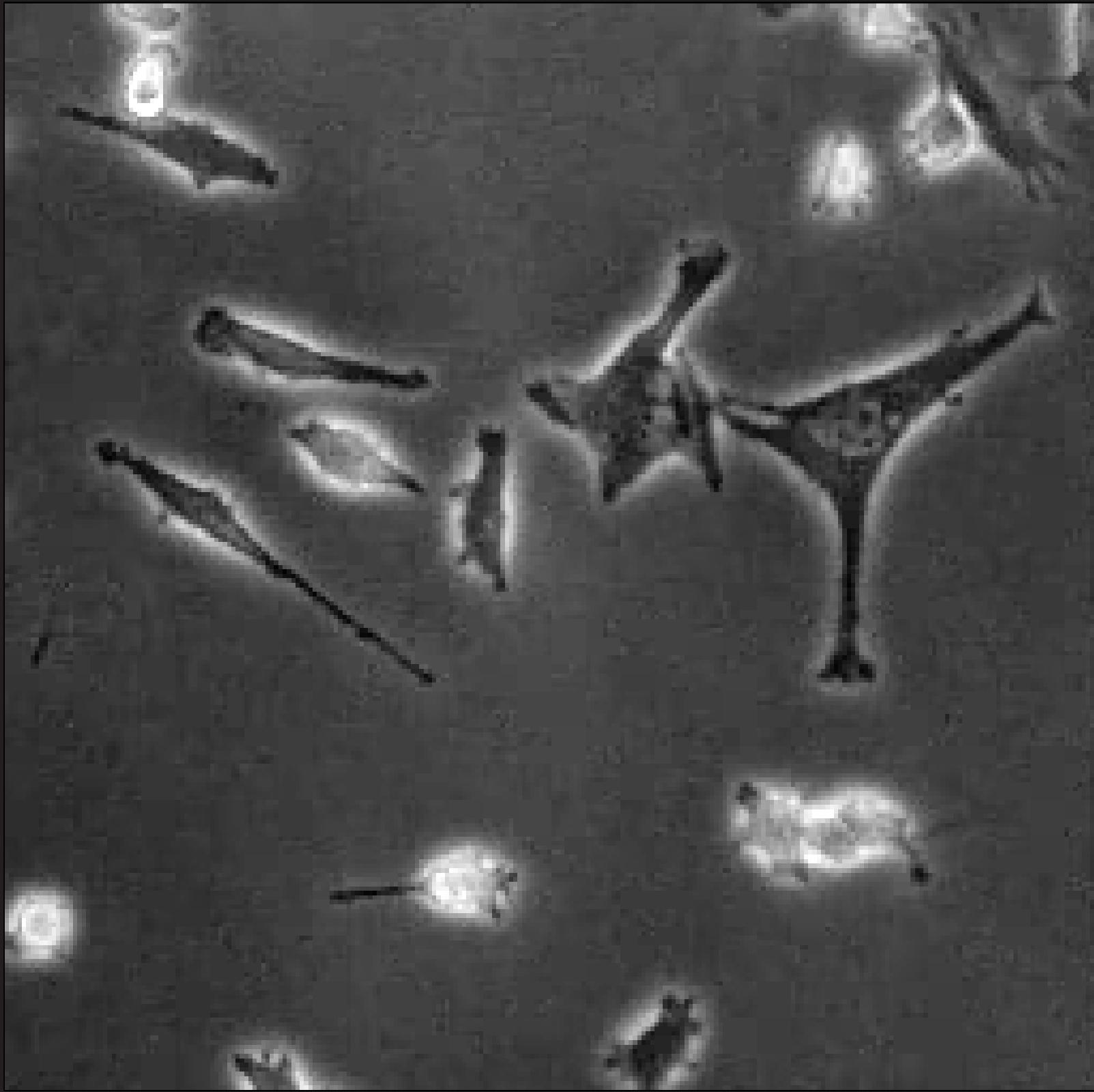
Applications

ethydium bromide test



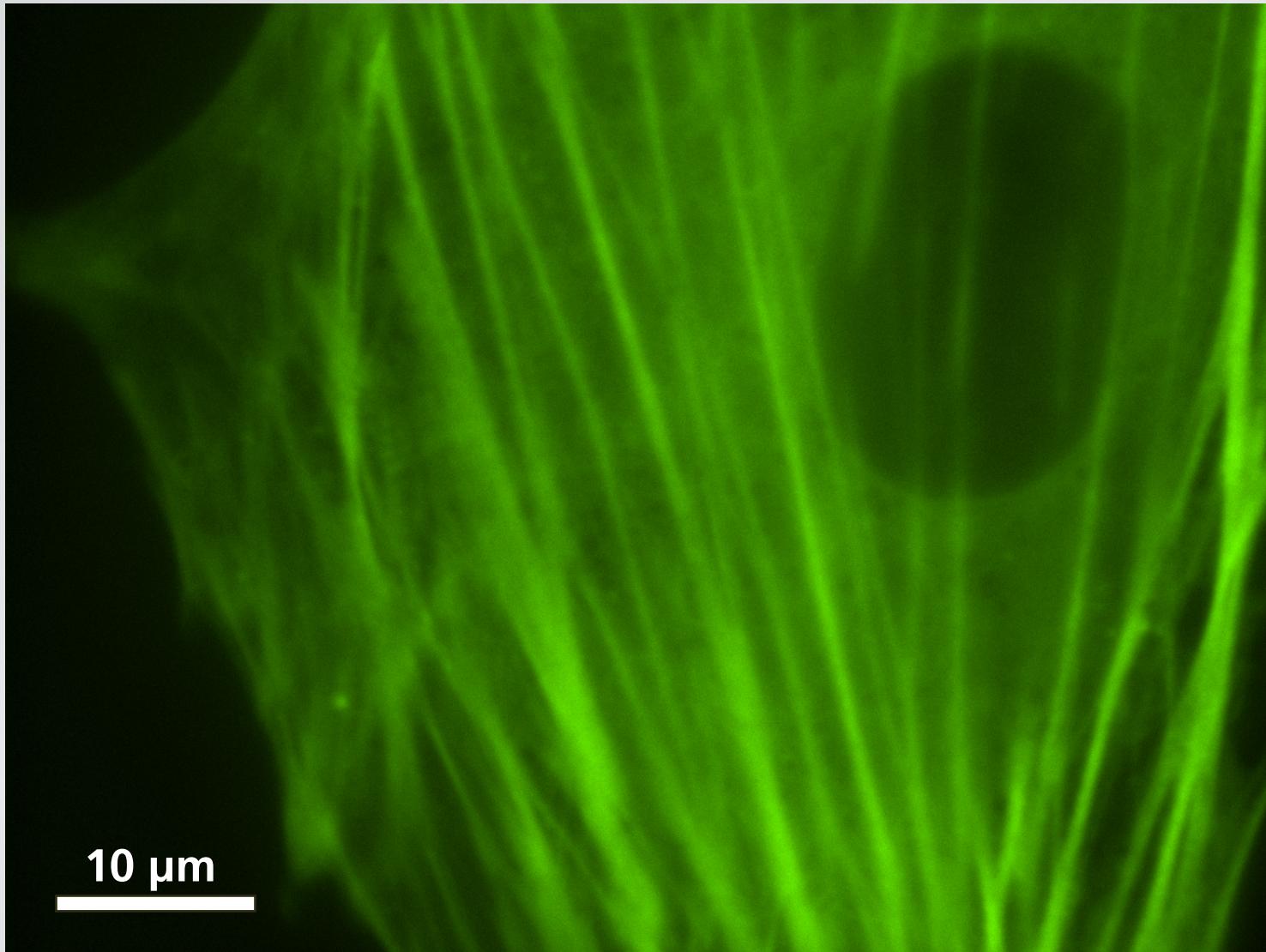
Applications

Q: can we probe the dynamics of the cytoskeleton?



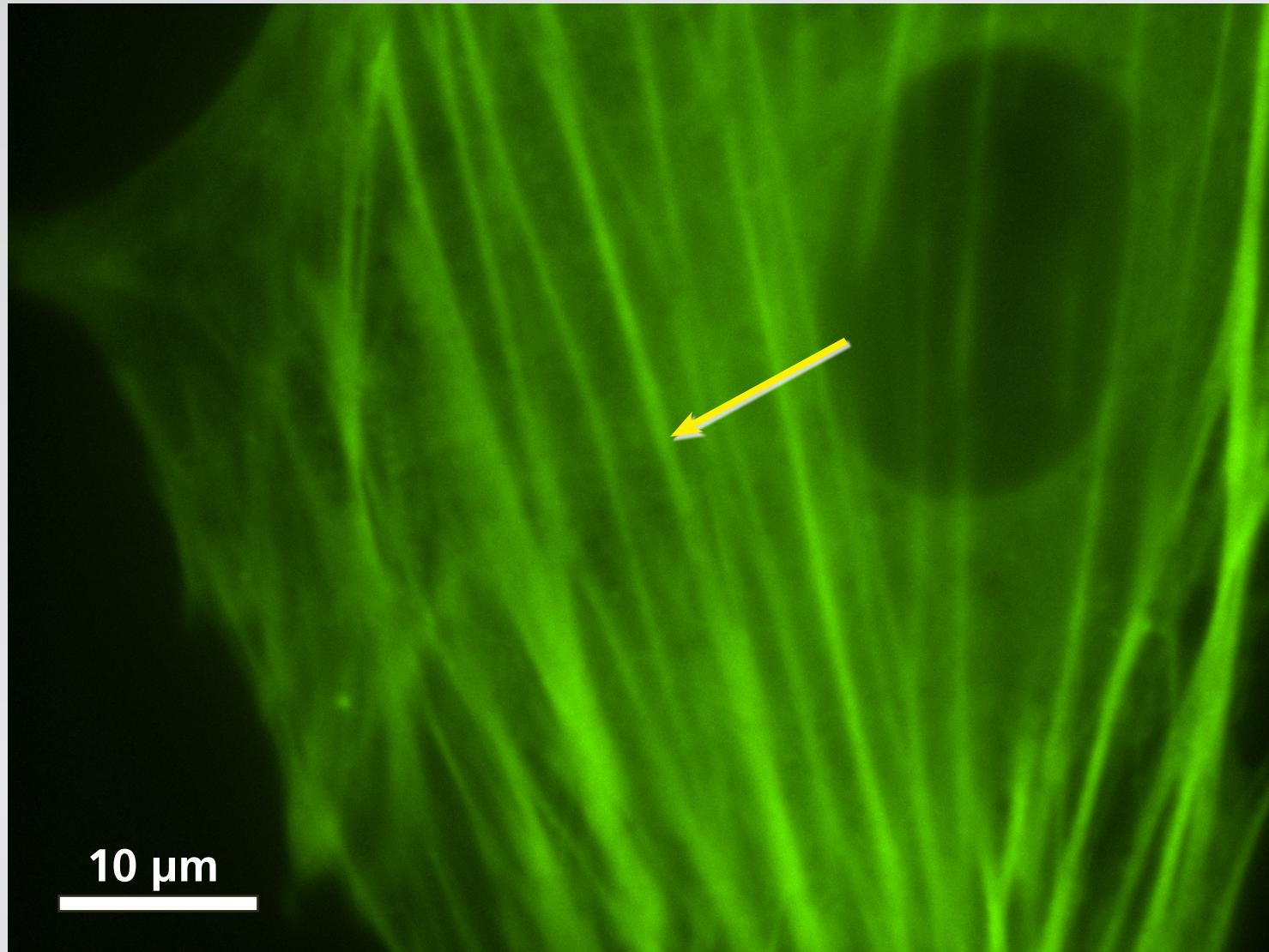
Applications

actin fiber network of a live cell



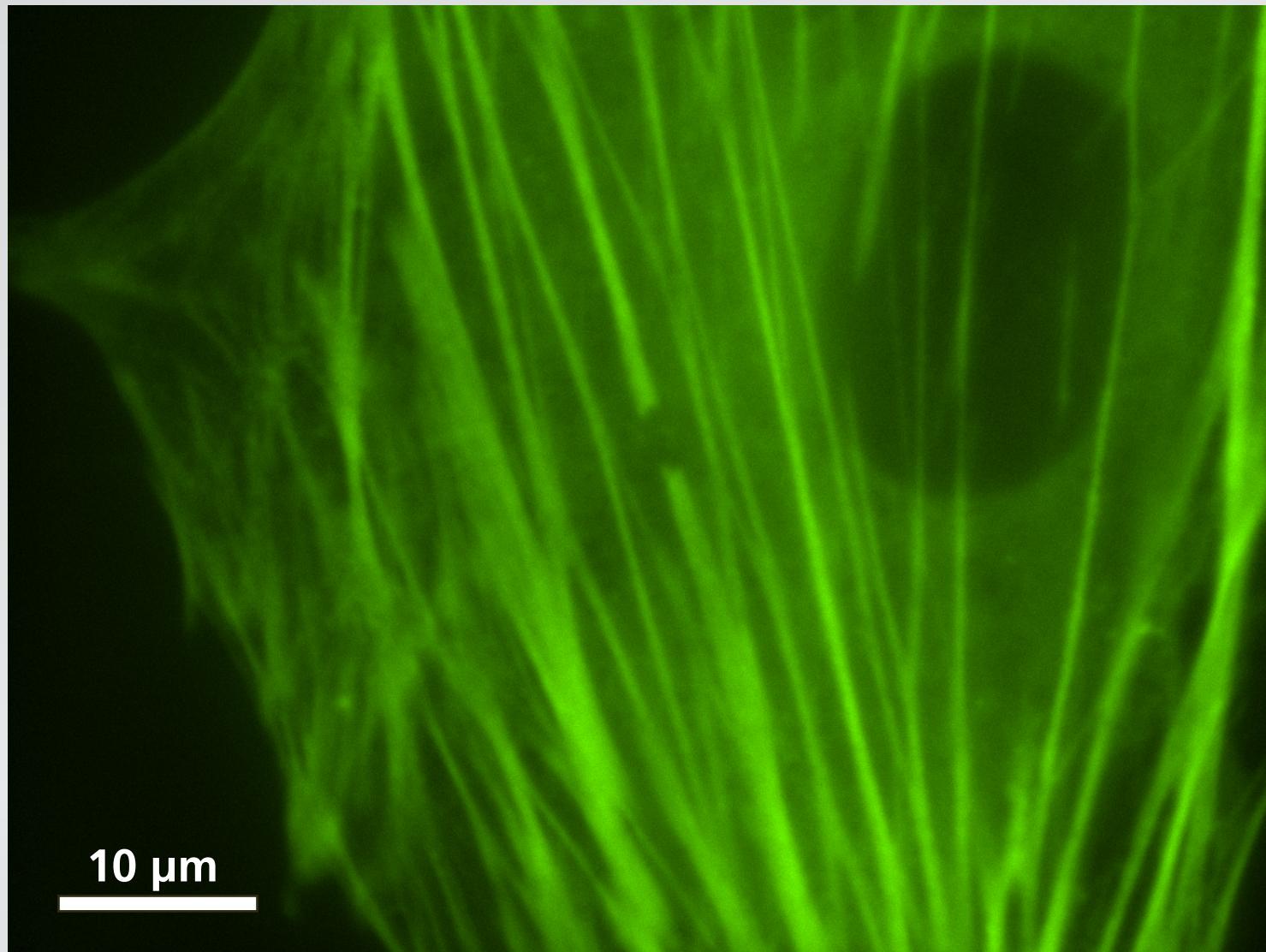
Applications

cut a single fiber bundle



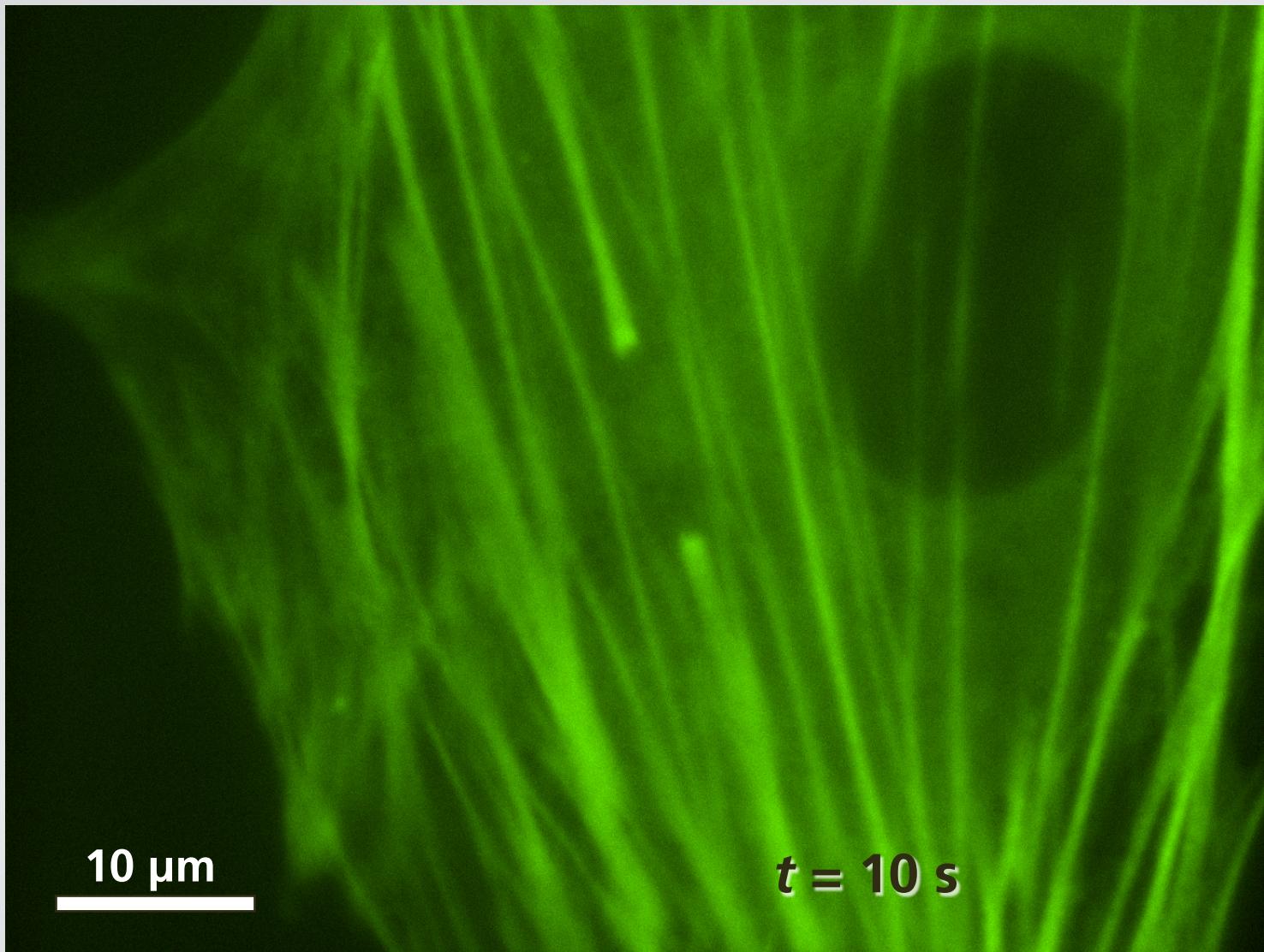
Applications

cut a single fiber bundle



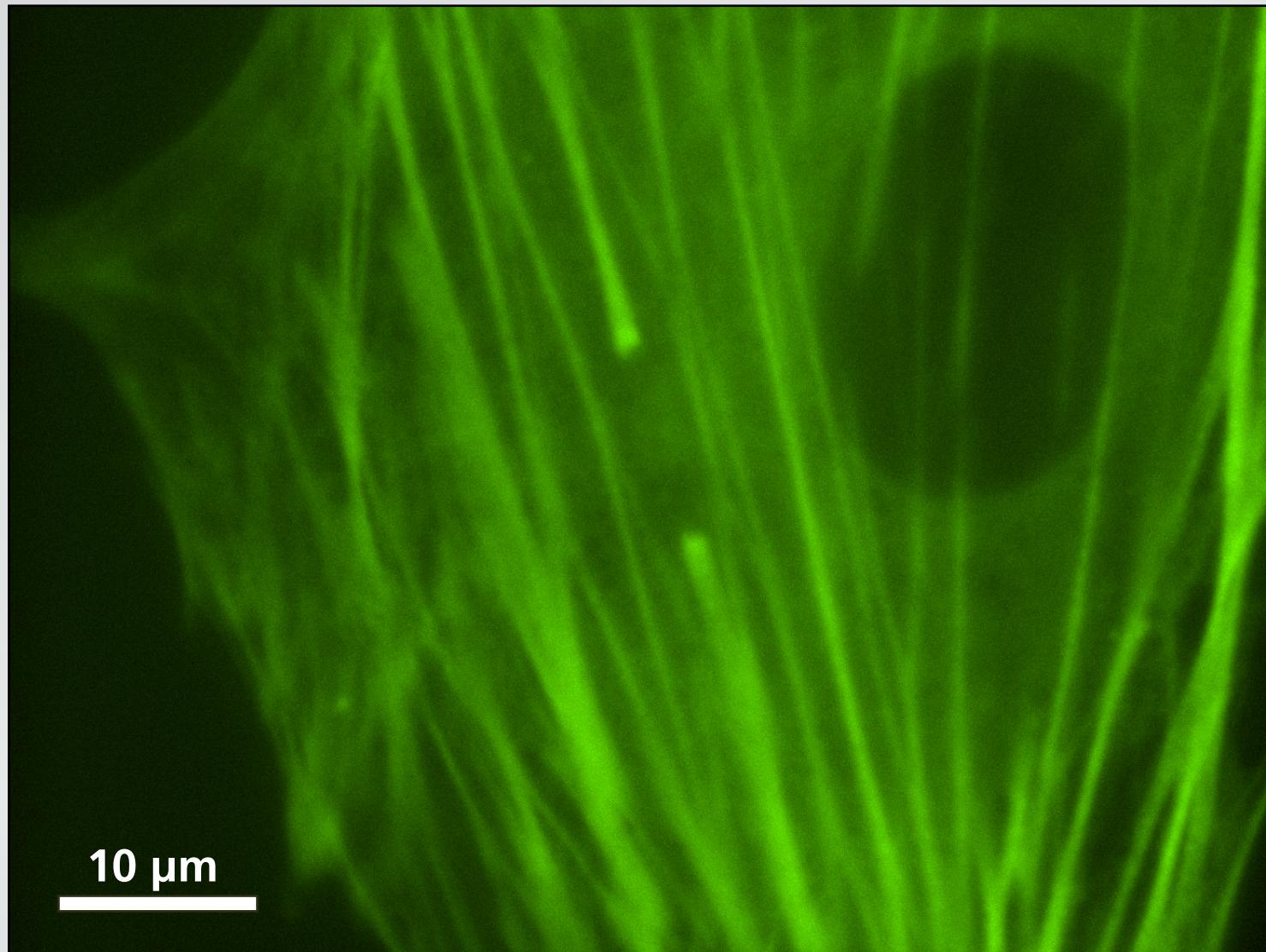
Applications

gap widens with time



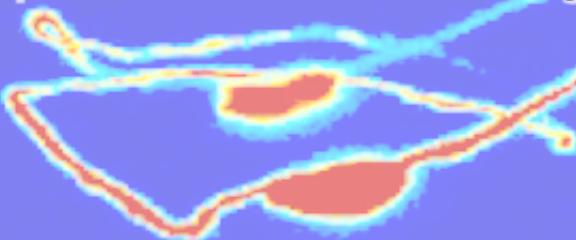
Subcellular surgery

dynamics provides information on *in vivo* mechanics



Applications

Q: can we probe the neurological origins of behavior?



Applications

Caenorhabditis Elegans



Juergen Berger & Ralph Sommer
Max-Planck Institute for Developmental Biology

Applications

Caenorhabditis Elegans

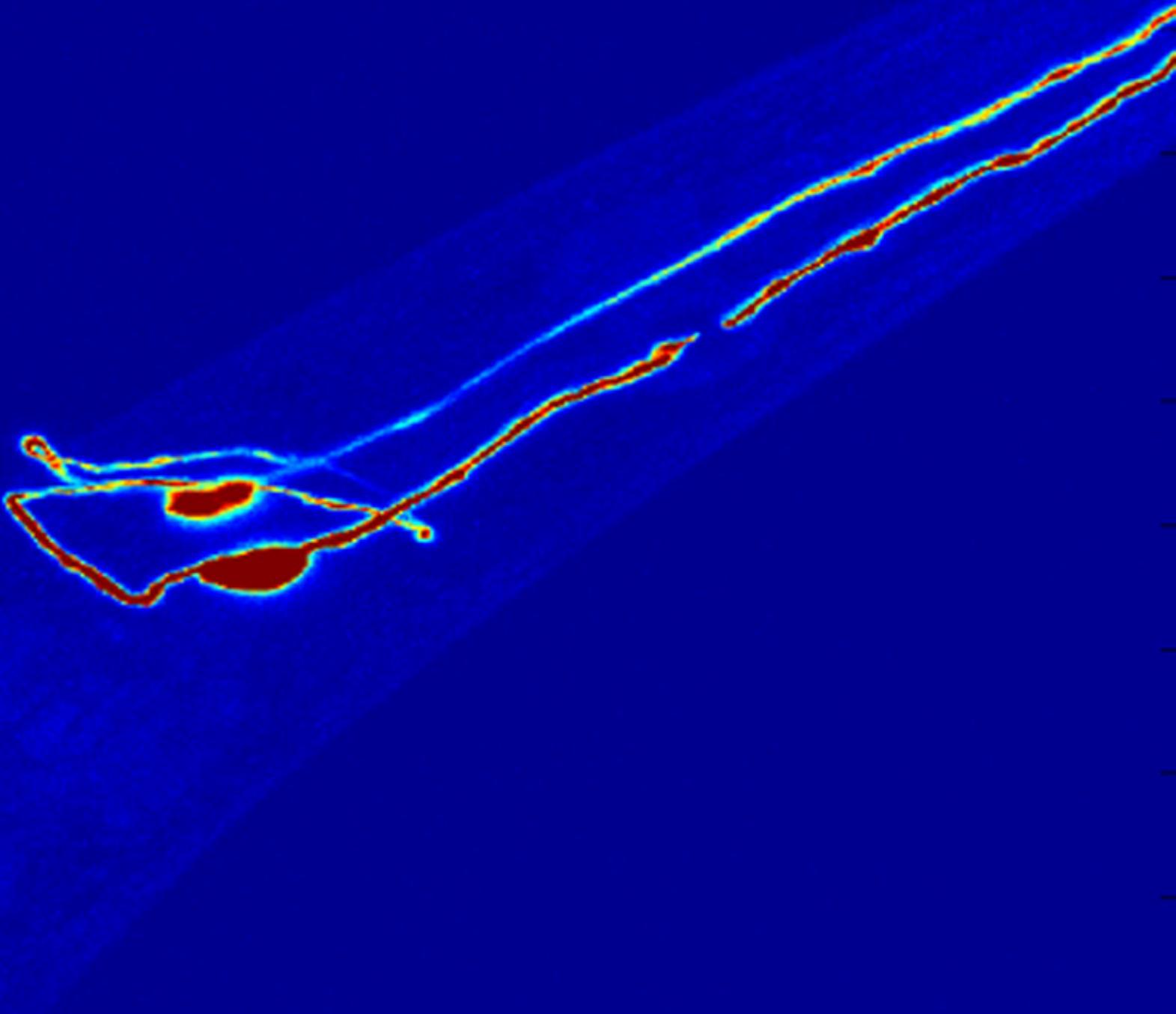
- simple model organism
- similarities to higher organisms
- genome fully sequenced
- easy to handle

Applications

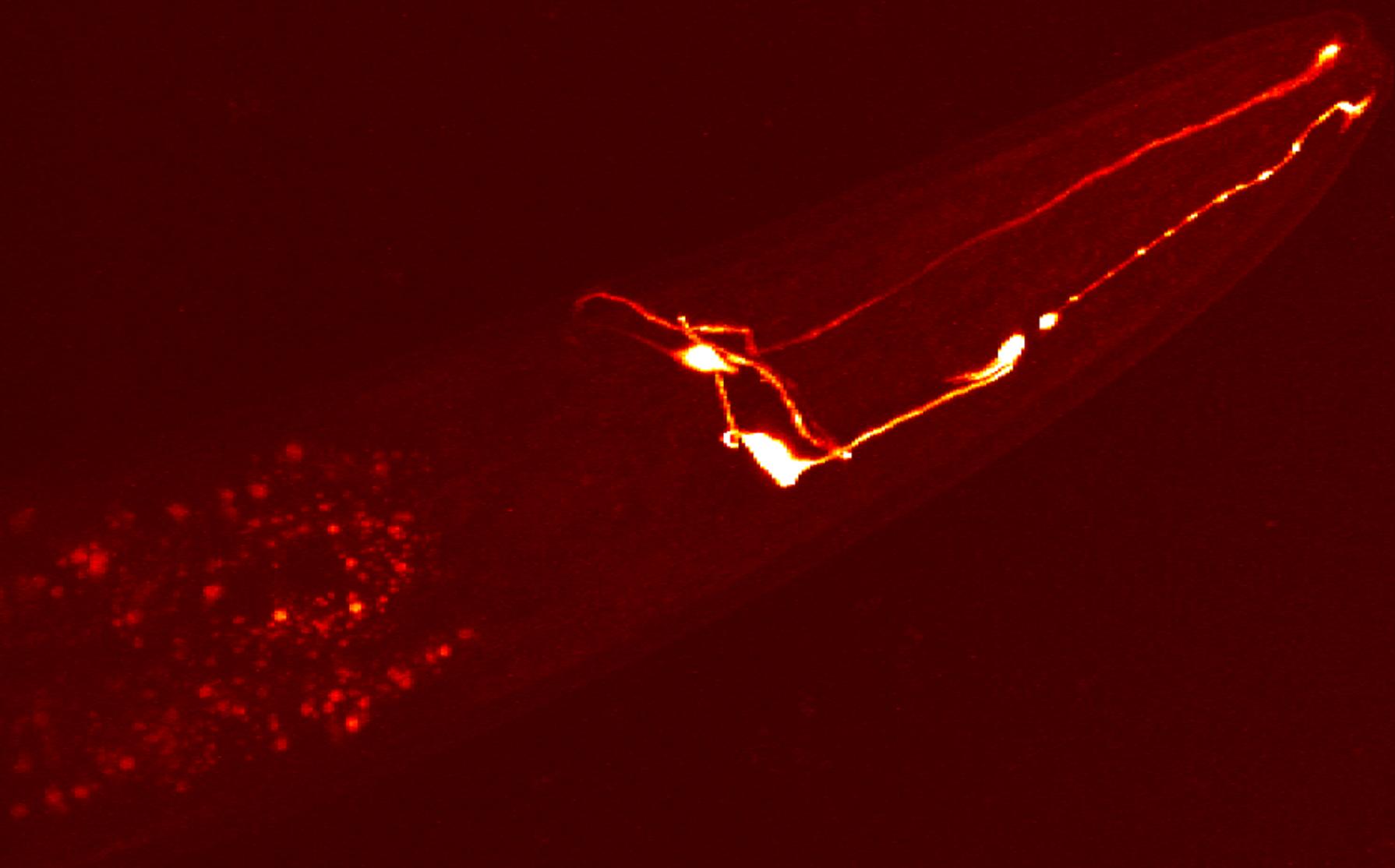
Caenorhabditis Elegans

- 80 µm x 1 mm
- about 1300 cells
- 302 neurons
- invariant wiring diagram
- neuronal system completely encodes behavior

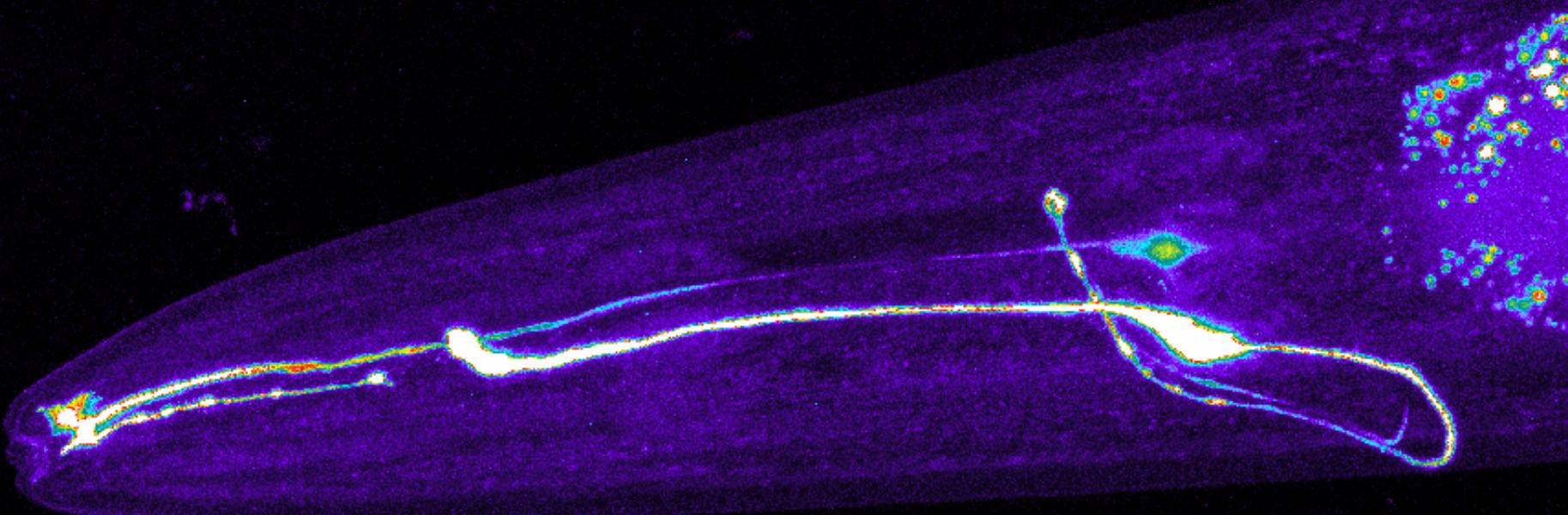
Applications



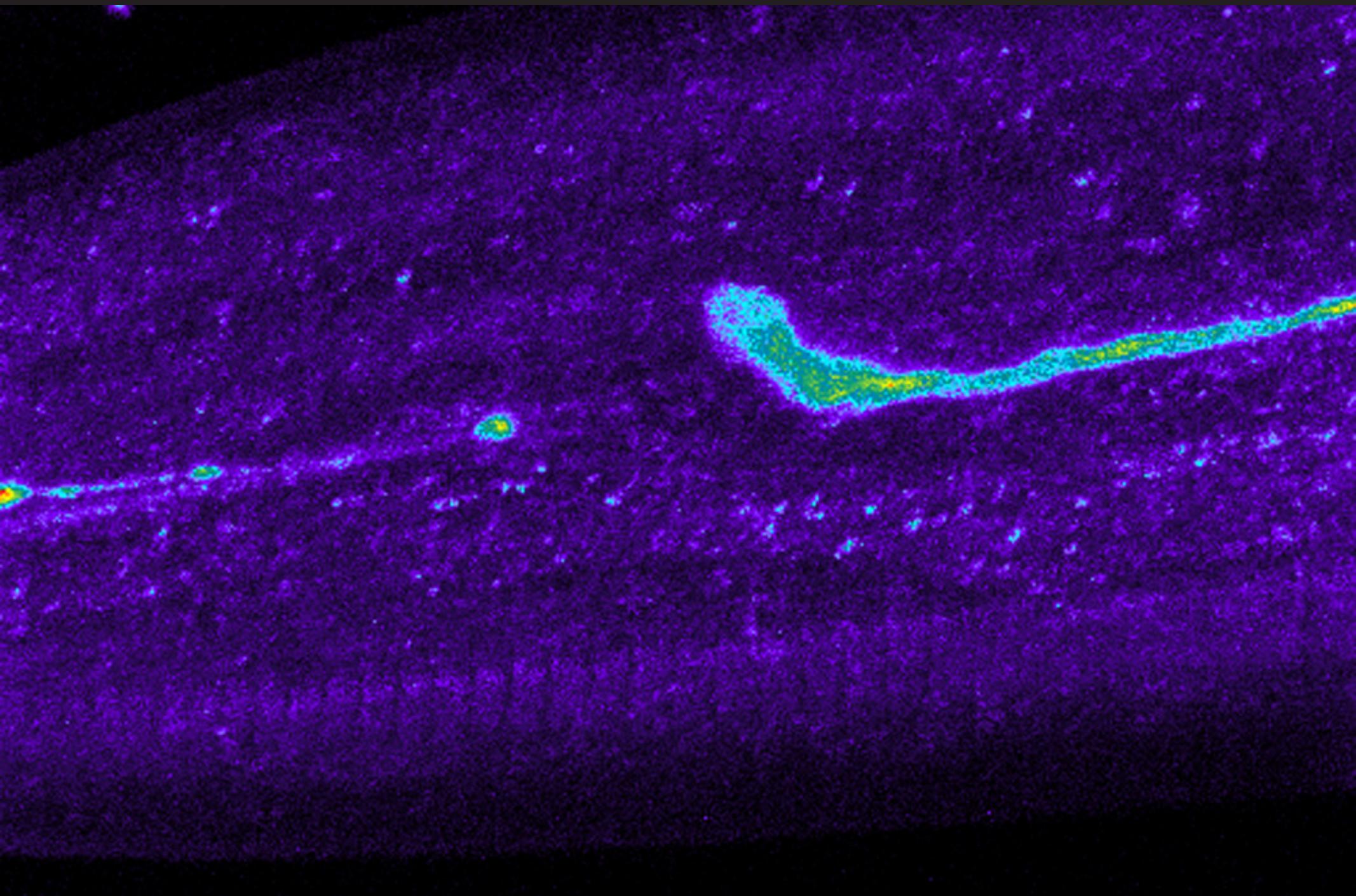
Applications



Applications

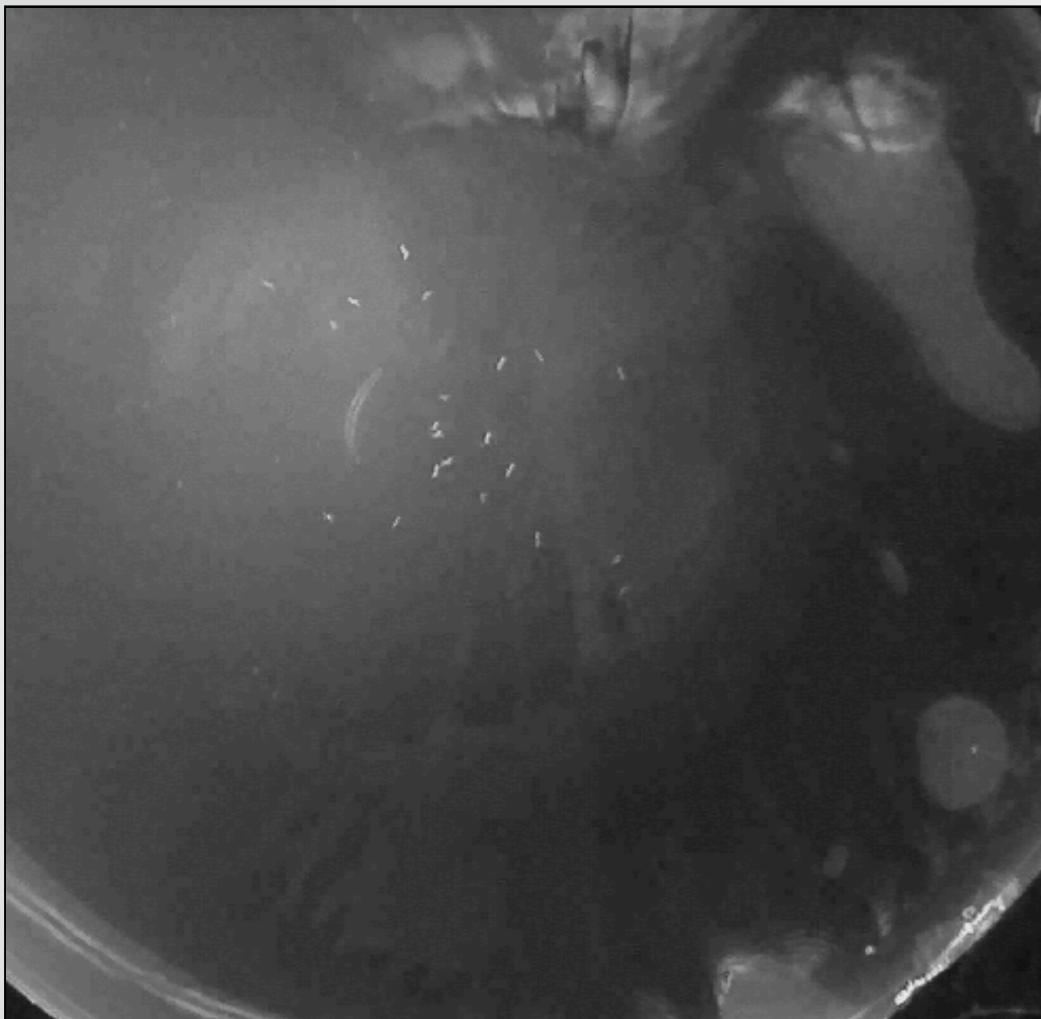


Applications



Nanoneurosurgery

Caenorhabditis elegans



Nanoneurosurgery

Caenorhabditis elegans



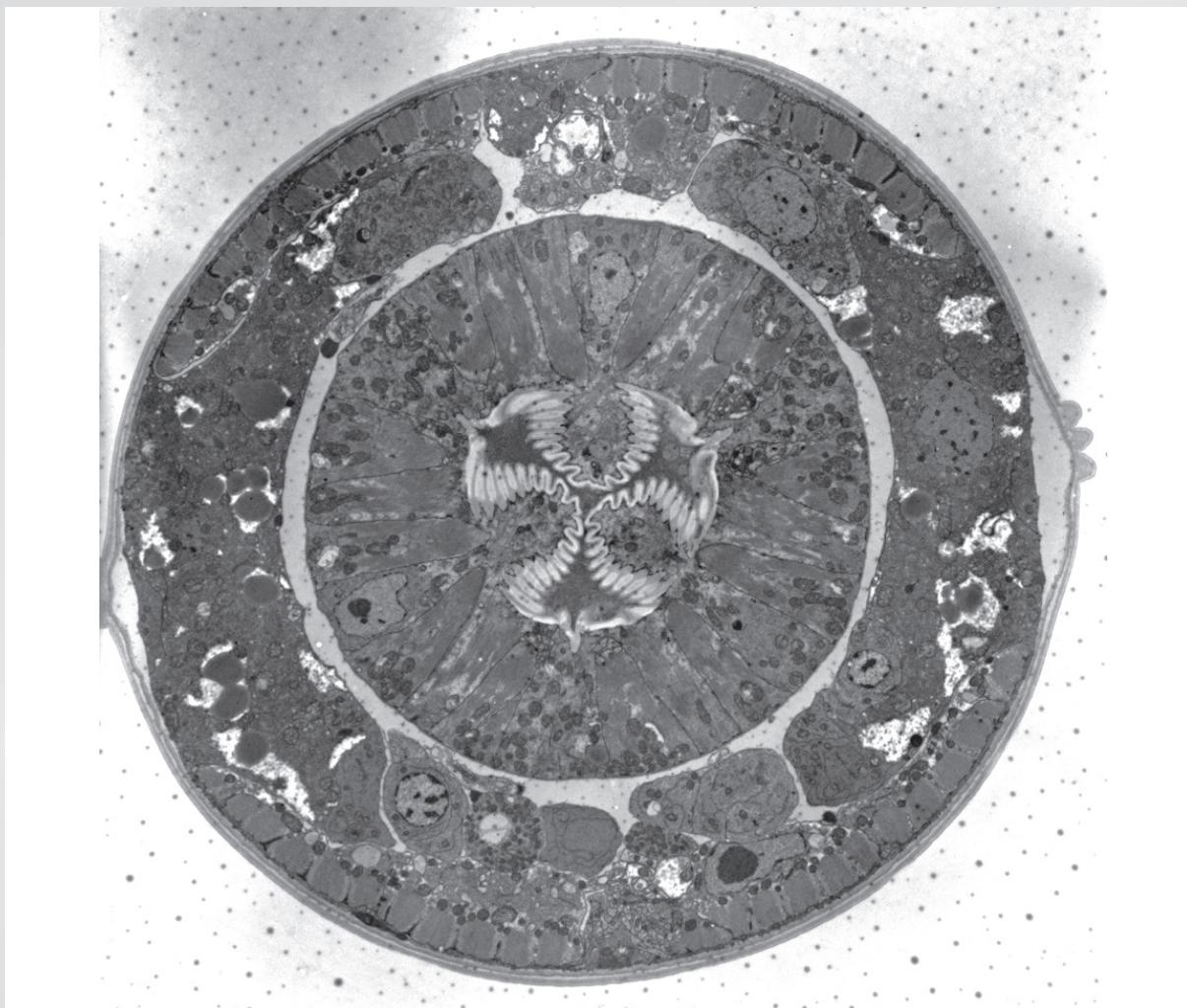
Applications

Caenorhabditis Elegans



Applications

Caenorhabditis Elegans



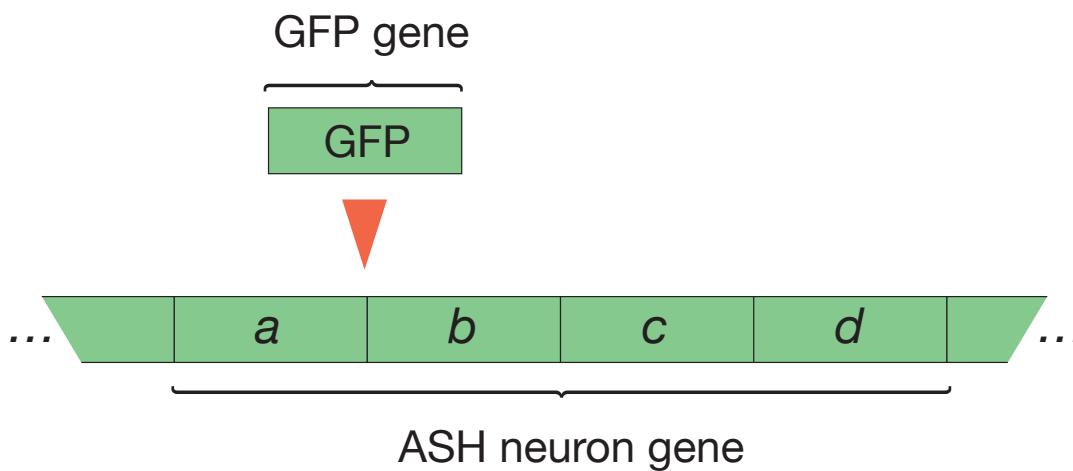
Applications

ASE neurons

- responsible for osmotic avoidance
- ciliary projections extend through skin
- one on each side

Applications

Make ASE neurons express GFP

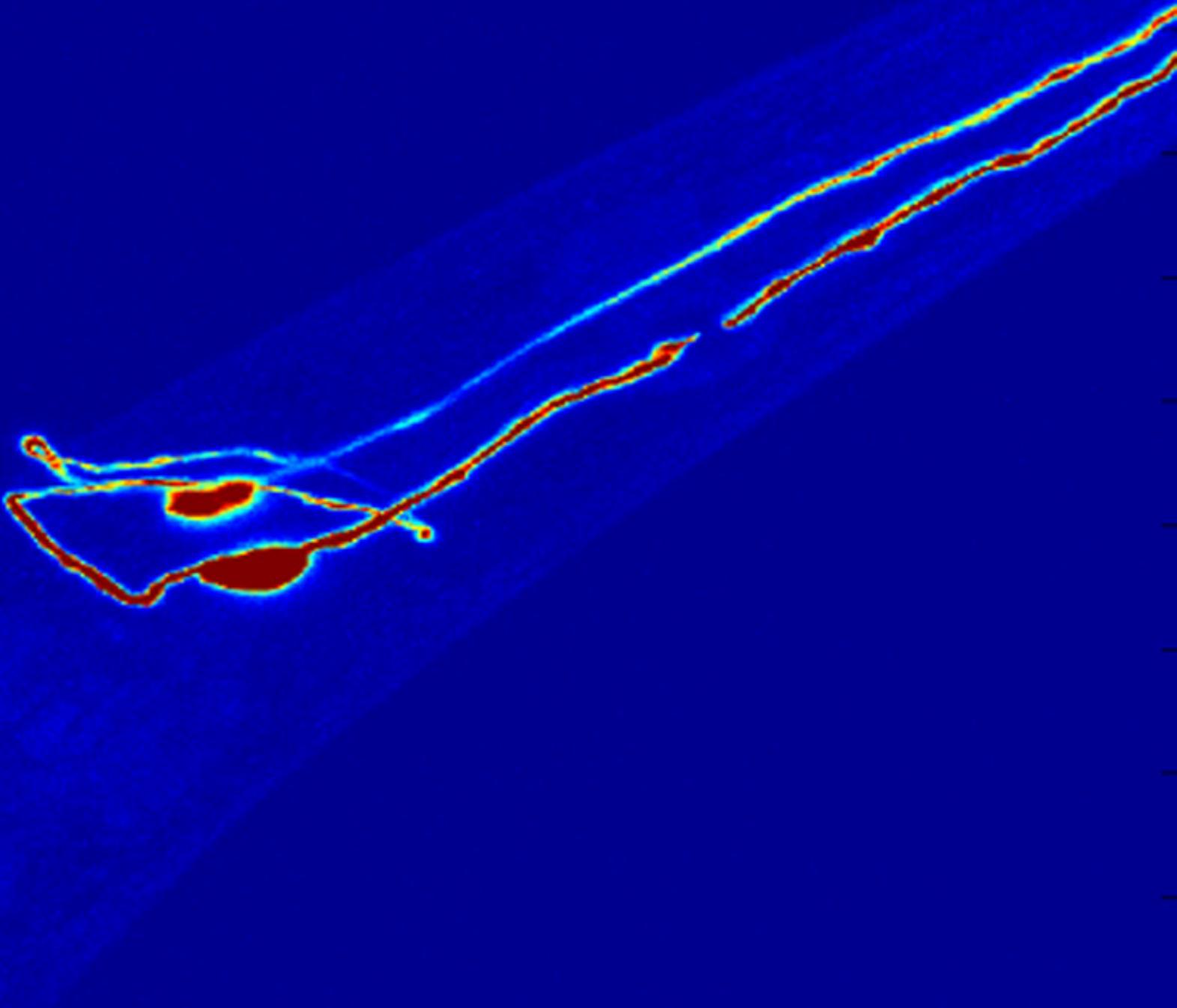


Nanoneurosurgery

GFP: absorbs UV, emits green

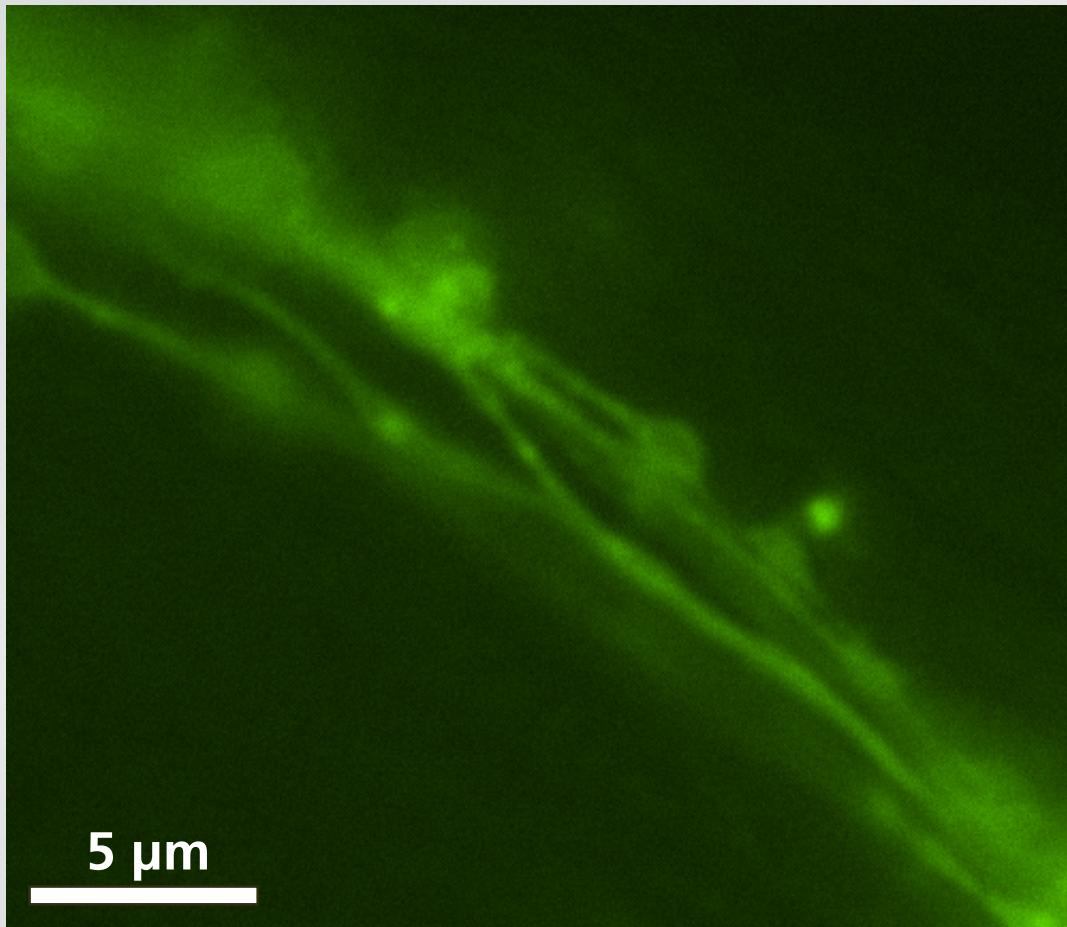


Applications



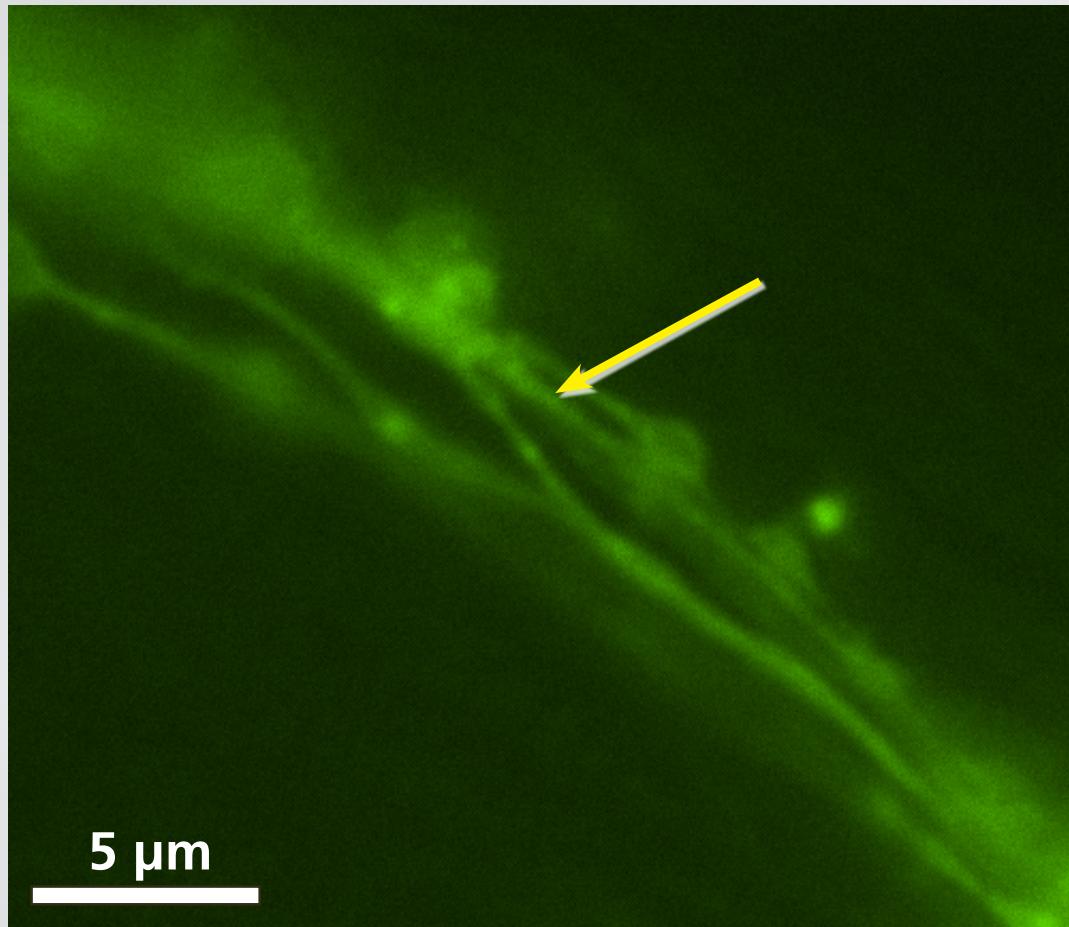
Applications

cut single dendrite in amphid bundle



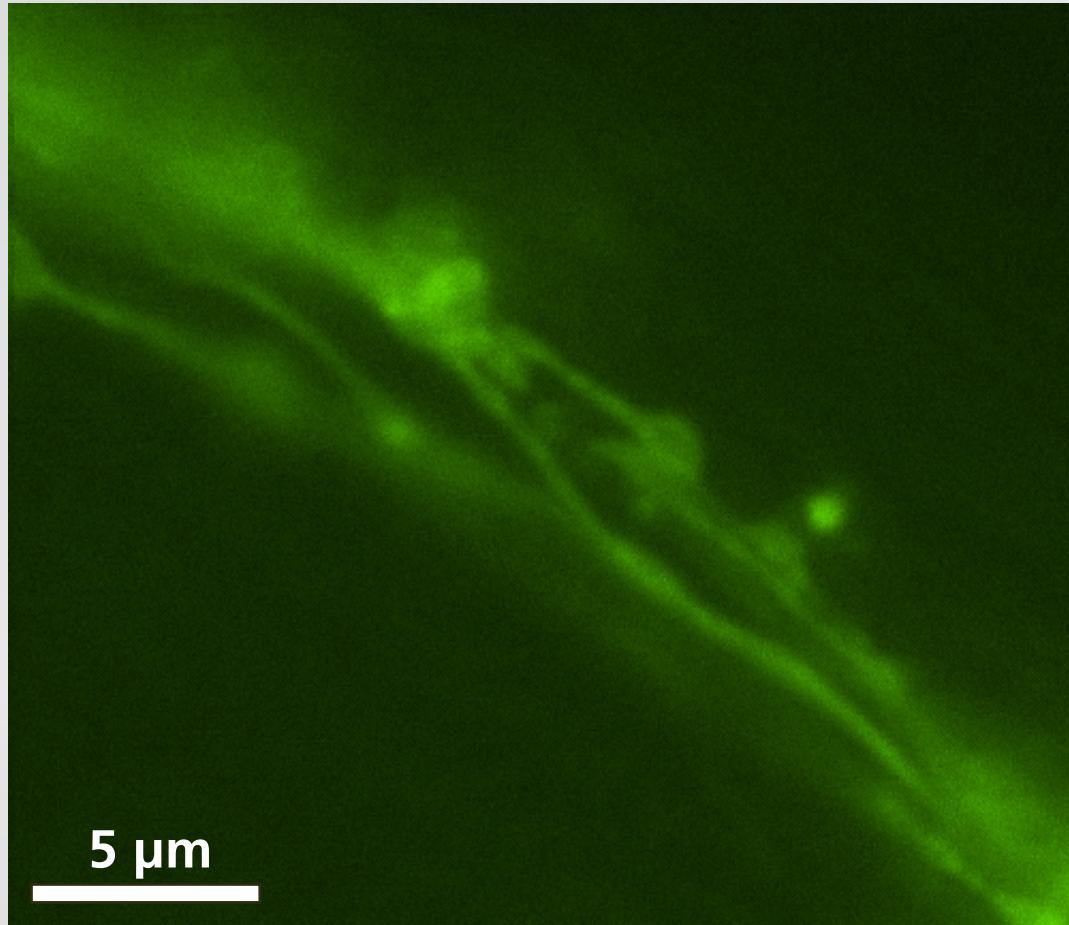
Applications

cut single dendrite in amphid bundle



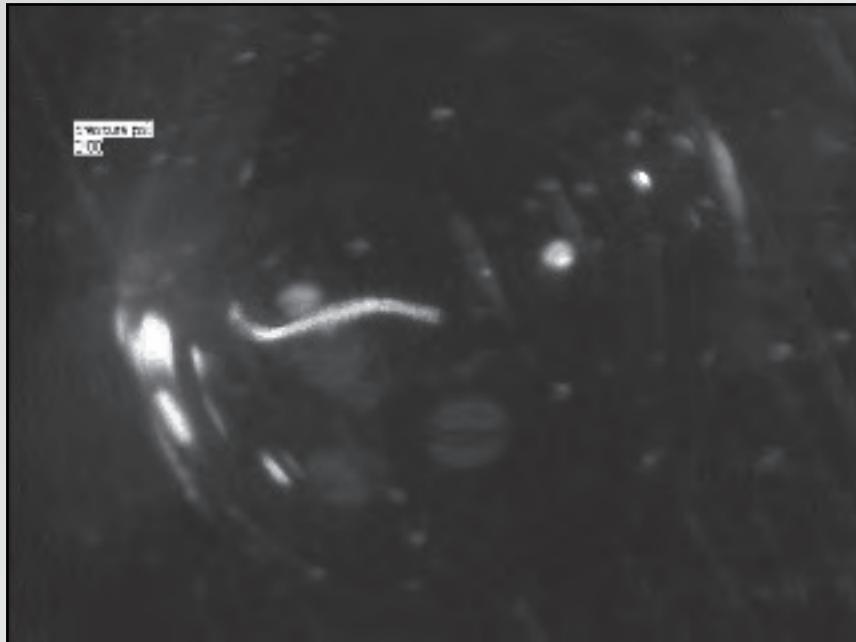
Applications

cut single dendrite in amphid bundle



Nanoneurosurgery

surgery results in quantifiable behavior changes

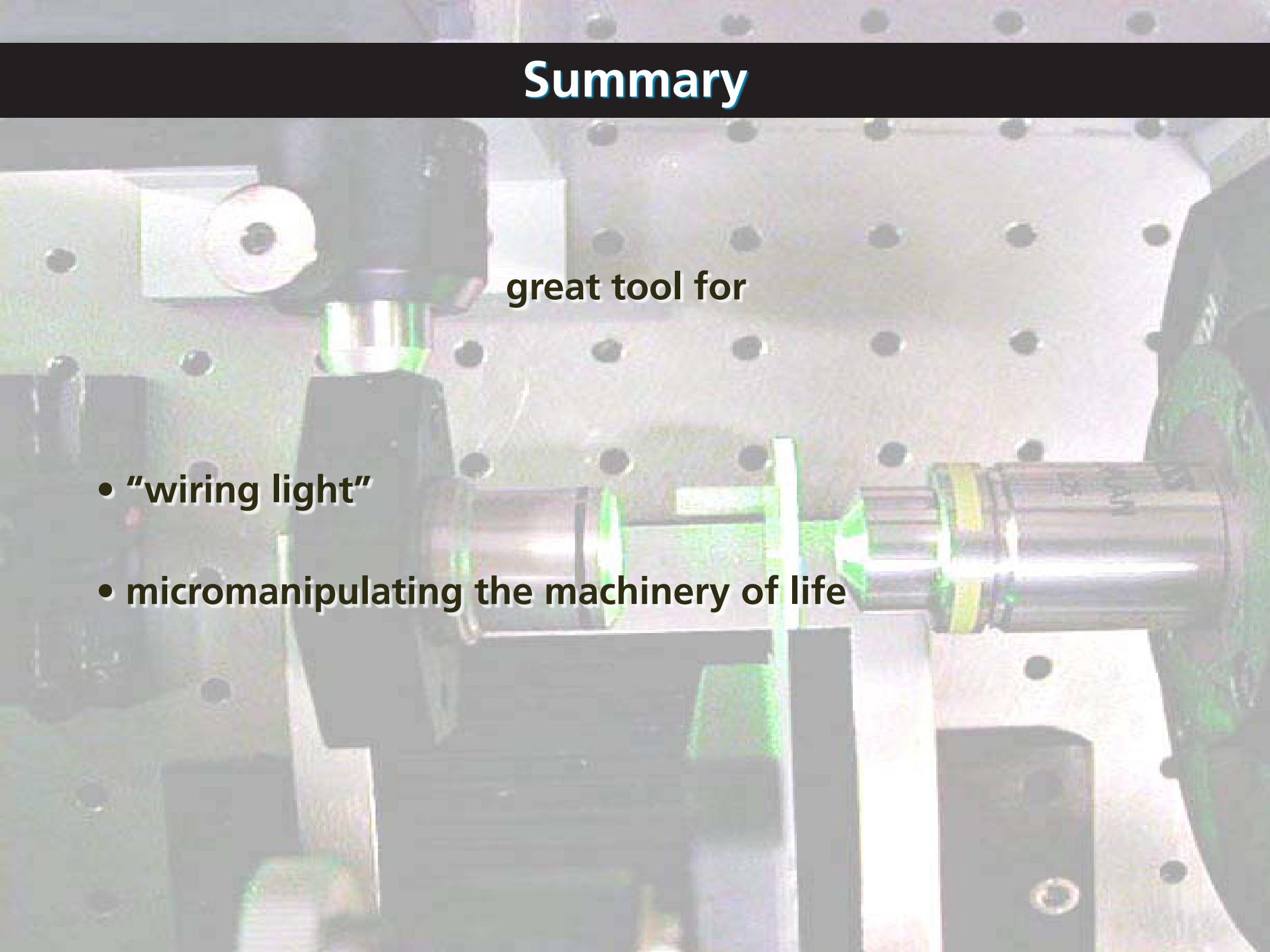


before



after

Summary



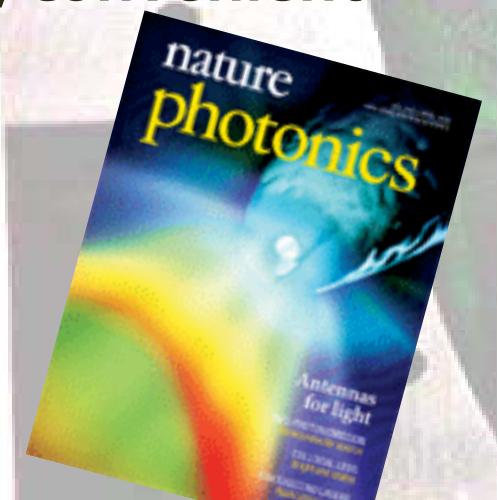
great tool for

- “wiring light”
- micromanipulating the machinery of life

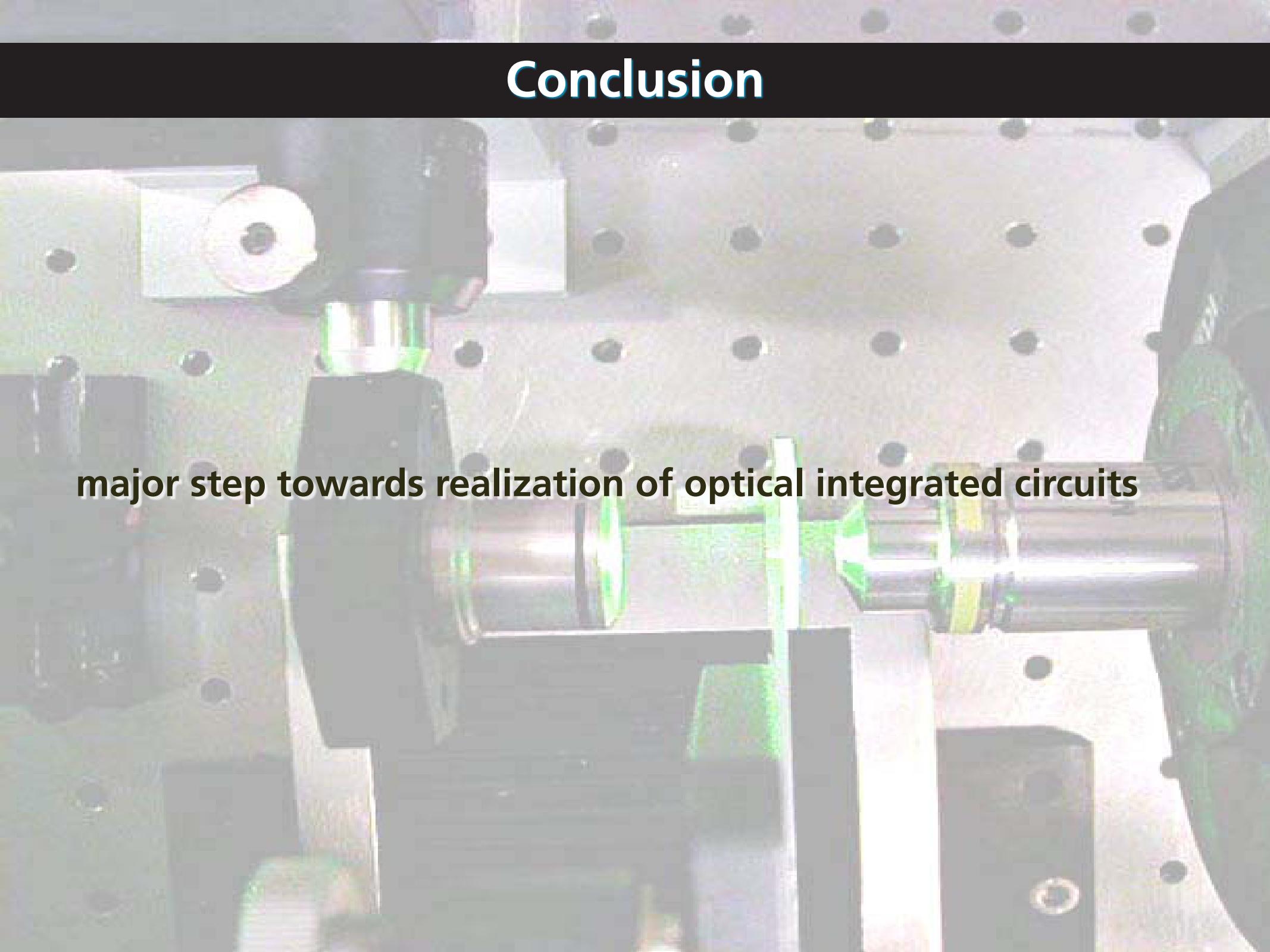
Summary

- important parameters: focusing, energy, repetition rate
- nearly material independent
- two regimes: low and high repetition rate
- high-repetition rate (thermal) machining fast, convenient

Nature Photonics 2, 219 (2008)



Conclusion



major step towards realization of optical integrated circuits





Funding:

Army Research Office
National Science Foundation

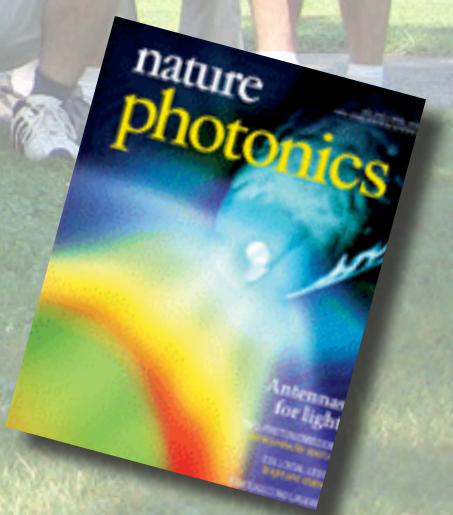
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